

Fyzikální vlastnosti materiálů

FX001

1. Vazba v pevné látce, elastické a tepelné vlastnosti materiálů
2. Elektrické vlastnosti materiálů
3. **Optické vlastnosti materiálů**
4. Magnetické vlastnosti materiálů
5. Supravodiče a grafen

Fyzikální vlastnosti materiálů

3. Optické vlastnosti materiálů

- a) Optická odezva materiálů – Maxwellovy rovnice, Laplaceova transformace, materiálové vztahy a odezvové funkce, komplexní vodivost a dielektrická funkce, index lomu.
- b) Rovinná vlna v materiálu – komplexní vlnový vektor, Poyntingův vektor, intenzita, absorbovaná energie.
- c) Elektromagnetická vlna v materiálu a na rozhraní – okrajové podmínky na rozhraní, přenosové matice, efektivní indexy lomu pro šikmý dopad.
- d) Kramersovy-Kronigovy relace – odezvové funkce v komplexní rovině, kuzalita odezvy, Kramersovy-Kronigovy relace pro odezvové funkce a reflektivitu.
- e) Absorpce mřížky – Lorentzův model pro polární krystaly, spektrální závislosti, závislost na hmotnostech atomů a tuhosti vazeb, nepolární krystaly – vícefononová absorpce.
- f) Odezva volných nositelů náboje – Drudeův model, plazmová frekvence, spektrální závislosti, elementární kovy.
- g) Optická odezva vázaných elektronů – mezipásové přechody, sdružená hustota stavů, nízkorozměrné heterostrukтуры.
- h) Propustná oblast – oblast mezi kmity mříže a elektronovou absorpcí, optická skla, tavený křemen, diamant, safír, materiály pro optická vlákna
- i) Odezva v rtg oblasti – index lomu, absorpční hrany

Optické obory frekvencí

obor	f (Hz)	λ (μm)	$1/\lambda$ (cm^{-1})	$\hbar\omega$ (eV)
Rádiové mikrovlny	3×10^{11}	1000	10	0.0012
FIR	1.5×10^{13}	20	500	0.062
MIR	1.2×10^{14}	2.5	4000	0.5
NIR	3.7×10^{14}	0.8	12500	1.55
VIS	7.5×10^{14}	0.4	25000	3.1
UV	1.7×10^{15}	0.18	55000	6.8
VUV	3×10^{16}	0.01	10^6	125
rtg				

Odezvové funkce

$$\sigma(\omega) = -i\omega\epsilon_0(\epsilon(\omega) - 1)$$

Vztah mezi vodivostí a dielektrickou funkcí

$$\epsilon(\omega) = 1 + i\frac{\sigma(\omega)}{\omega\epsilon_0}.$$

$$(N + iK)^2 = \epsilon_1 + i\epsilon_2,$$

$$\epsilon_1 = N^2 - K^2, \quad \epsilon_2 = 2NK.$$

Vztah mezi dielektrickou funkcí a komplexním indexem lomu

$$N = \sqrt{\frac{\sqrt{\epsilon_1^2 + \epsilon_2^2} + \epsilon_1}{2}}, \quad K = \sqrt{\frac{\sqrt{\epsilon_1^2 + \epsilon_2^2} - \epsilon_1}{2}}.$$

Odezvové funkce

Kramersovy-Kronigovy relace

$$\chi_r(\omega_0) = \frac{2}{\pi} \text{P} \int_0^{\infty} \frac{\omega \chi_i(\omega)}{\omega^2 - \omega_0^2} d\omega$$

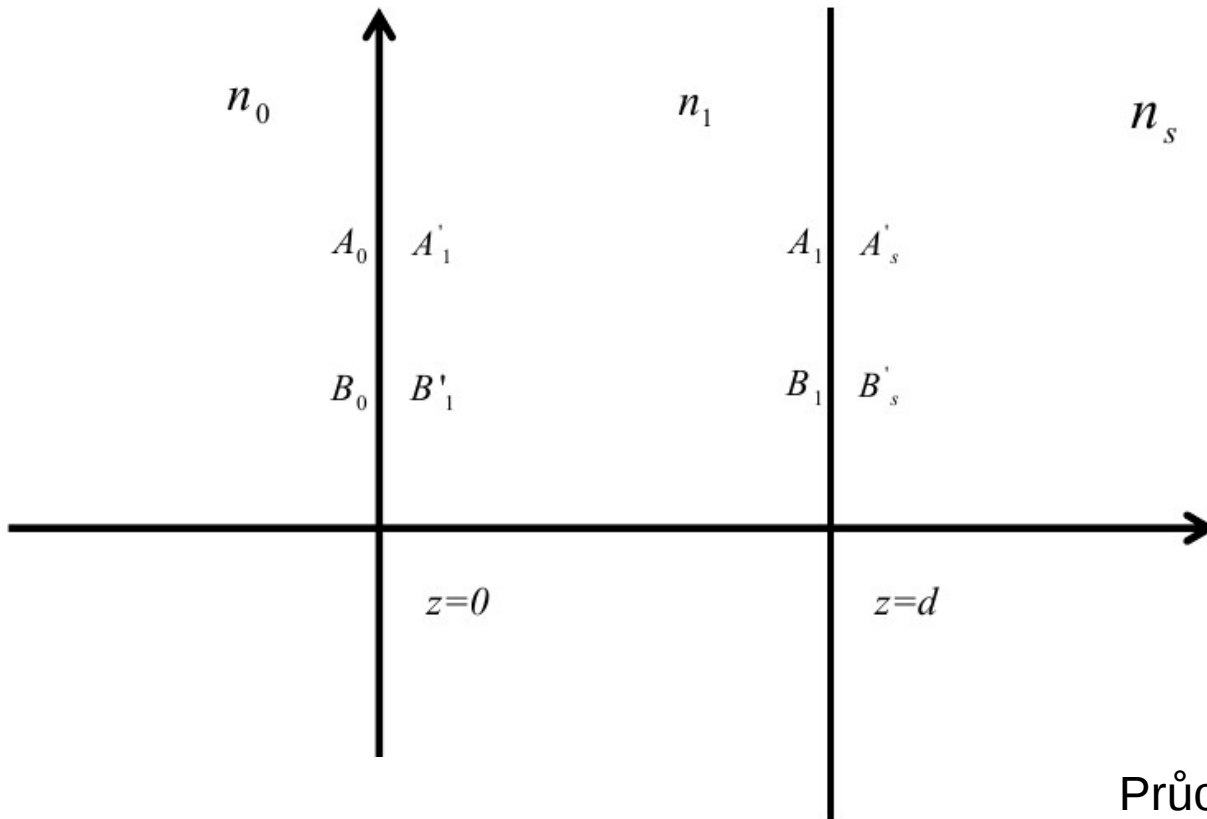
and

$$\chi_i(\omega_0) = -\frac{2\omega_0}{\pi} \text{P} \int_0^{\infty} \frac{\chi_r(\omega)}{\omega^2 - \omega_0^2} d\omega$$

$$\ln r_c(\omega) = \ln \sqrt{R(\omega)} + i\phi(\omega)$$

$$\phi(\omega_0) = -\frac{2\omega_0}{\pi} \text{P} \int_0^{\infty} \frac{\ln \sqrt{R(\omega)} - \ln \sqrt{R(\omega_0)}}{\omega^2 - \omega_0^2} d\omega$$

Formalismus přenosových matic



Průchod homogenním prostředím je popsán maticí P

$$E_p = E_p(z)e^{-jk_x x},$$

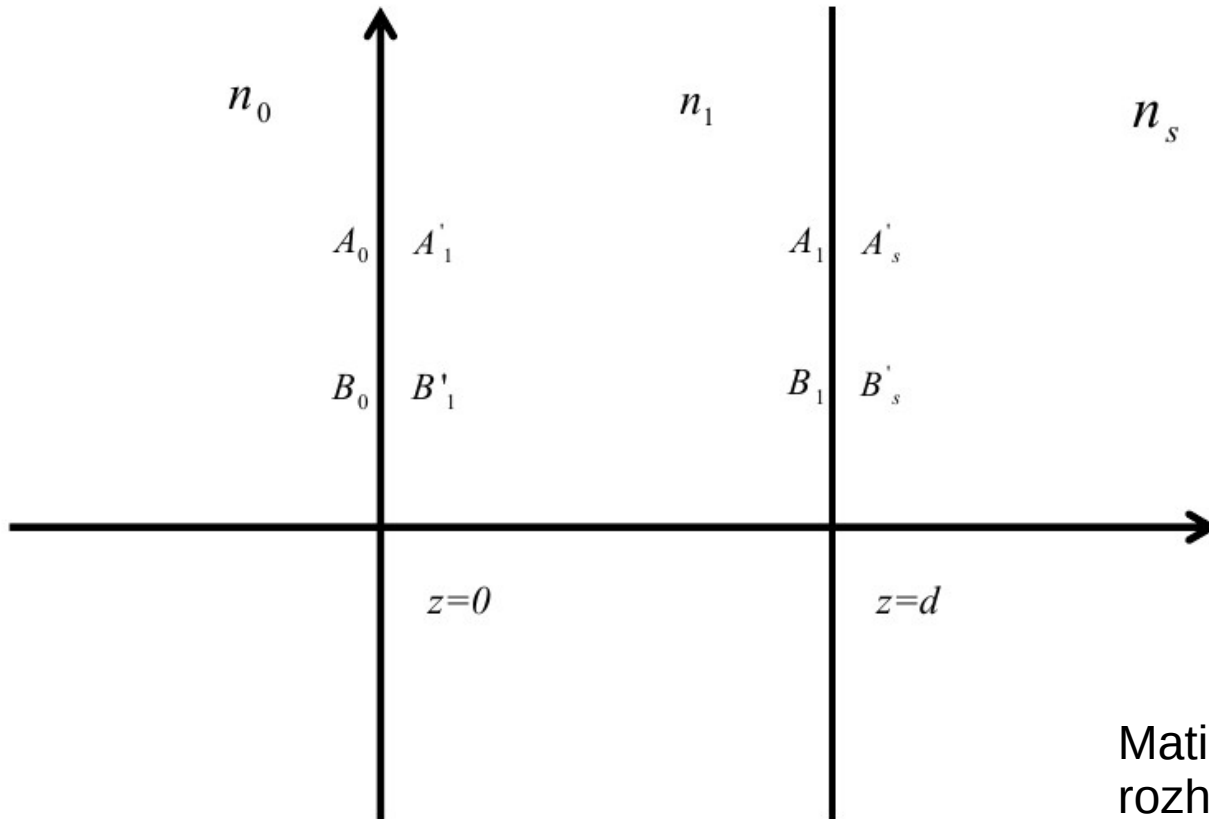
$$E_p(z) = A(z) + B(z) = Ae^{-jk_z z} + Be^{jk_z z}$$

$$\phi = k_z d$$

$$\begin{pmatrix} A'_1 \\ B'_1 \end{pmatrix} = \begin{pmatrix} e^{j\phi} & 0 \\ 0 & e^{-j\phi} \end{pmatrix} = P_1 \begin{pmatrix} A_1 \\ B_1 \end{pmatrix}$$

$$\phi = k_{1z} d = \frac{2\pi d}{\lambda} n_1 \cos \theta_1$$

Formalismus přenosových matic



Matice D popisují podmínky na rozhraní dvou prostředí

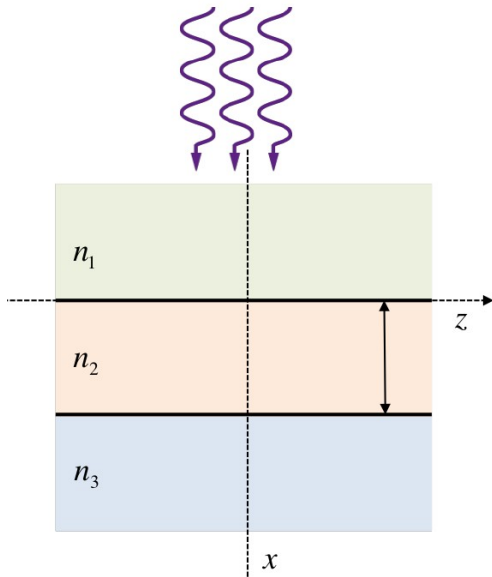
$$E_p(z) = A(z) + B(z) = Ae^{-jk_z z} + Be^{jk_z z}$$

$$\begin{pmatrix} A_0 \\ B_0 \end{pmatrix} = D_0^{-1} D_1 \begin{pmatrix} A'_1 \\ B'_1 \end{pmatrix} \equiv D_{01} \begin{pmatrix} A'_1 \\ B'_1 \end{pmatrix}$$

$$D_i = \begin{cases} \begin{pmatrix} 1 & 1 \\ \sqrt{\frac{\epsilon_i}{\mu_i}} \cos \theta_i & -\sqrt{\frac{\epsilon_i}{\mu_i}} \cos \theta_i \end{pmatrix} & \text{for TE wave} \\ & \text{s-polarizace} \\ \begin{pmatrix} \cos \theta_i & \cos \theta_i \\ \sqrt{\frac{\epsilon_i}{\mu_i}} & -\sqrt{\frac{\epsilon_i}{\mu_i}} \end{pmatrix} & \text{for TM wave} \\ & \text{p-polarizace} \end{cases}$$

Formalismus přenosových matic

Podrobnější odvození pro s-polarizaci – šíření podél osy x



$$E(x) = \begin{cases} E_1 e^{ik_1 x} + E'_1 e^{-ik_1 x}, & x < 0 \\ E_2 e^{ik_2 x} + E'_2 e^{-ik_2 x}, & 0 < x < d \\ E_3 e^{ik_3(x-d)} + E'_3 e^{-ik_3(x-d)}, & x > d \end{cases}$$

$$\vec{E}_{\parallel} = \vec{E}'_{\parallel} \Rightarrow E_{1y} + E'_{1y} = E_{2y} + E'_{2y}$$

$$H_{\parallel} = H'_{\parallel} \Rightarrow H_{1z} + H'_{1z} = H_{2z} + H'_{2z} \Rightarrow n_1 \cos \theta_1 E_{1y} - n_1 \cos \theta_1 E'_{1y} = n_2 \cos \theta_2 E_{2y} - n_2 \cos \theta_2 E'_{2y}$$

$$\begin{pmatrix} 1 & 1 \\ n_1 \cos \theta_1 & -n_1 \cos \theta_1 \end{pmatrix} \begin{pmatrix} E_{1y} \\ E'_{1y} \end{pmatrix} = \begin{pmatrix} 1 & 1 \\ n_2 \cos \theta_2 & -n_2 \cos \theta_2 \end{pmatrix} \begin{pmatrix} E_{2y} \\ E'_{2y} \end{pmatrix} \Rightarrow D_1 \begin{pmatrix} E_{1y} \\ E'_{1y} \end{pmatrix} = D_2 \begin{pmatrix} E_{2y} \\ E'_{2y} \end{pmatrix}$$

$$D_2^{-1} D_1 \begin{pmatrix} E_{1y} \\ E'_{1y} \end{pmatrix} = \begin{pmatrix} E_{2y} \\ E'_{2y} \end{pmatrix} \Rightarrow D_{12} \begin{pmatrix} E_{1y} \\ E'_{1y} \end{pmatrix} = \begin{pmatrix} E_{2y} \\ E'_{2y} \end{pmatrix}$$

Formalismus přenosových matic

$$D_2^{-1}D_1 \begin{pmatrix} E_{1y} \\ E'_{1y} \end{pmatrix} = \begin{pmatrix} E_{2y} \\ E'_{2y} \end{pmatrix} \Rightarrow D_{12} \begin{pmatrix} E_{1y} \\ E'_{1y} \end{pmatrix} = \begin{pmatrix} E_{2y} \\ E'_{2y} \end{pmatrix}$$

$$D_{12} = D_2^{-1}D_1 = \begin{pmatrix} 1 & 1 \\ n_2 \cos \theta_2 & -n_2 \cos \theta_2 \end{pmatrix}^{-1} \begin{pmatrix} 1 & 1 \\ n_1 \cos \theta_1 & -n_1 \cos \theta_1 \end{pmatrix} = \begin{pmatrix} \frac{1}{2} & \frac{1}{2n_2 \cos \theta_2} \\ \frac{1}{2} & -\frac{1}{2n_2 \cos \theta_2} \end{pmatrix} \begin{pmatrix} 1 & 1 \\ n_1 \cos \theta_1 & -n_1 \cos \theta_1 \end{pmatrix}$$

$$D_{12} = \begin{pmatrix} \frac{n_2 \cos \theta_2 + n_1 \cos \theta_1}{2n_2 \cos \theta_2} & \frac{n_2 \cos \theta_2 - n_1 \cos \theta_1}{2n_2 \cos \theta_2} \\ \frac{n_2 \cos \theta_2 - n_1 \cos \theta_1}{2n_2 \cos \theta_2} & \frac{n_2 \cos \theta_2 + n_1 \cos \theta_1}{2n_2 \cos \theta_2} \end{pmatrix}$$

Formalismus přenosových matic

Pro systém s jednou vrstvou

$$\begin{pmatrix} A_0 \\ B_0 \end{pmatrix} = D_0^{-1} D_1 P_1 D_1^{-1} D_s \begin{pmatrix} A'_s \\ B'_s \end{pmatrix} = M \begin{pmatrix} A'_s \\ B'_s \end{pmatrix}$$

Obecný mnohvrstevný systém – každá vrstva je popsána součinem tří matic $D_n P_n D_n^{-1}$

Celek je popsán maticí M = součin všech jednotlivých matic

Koeficienty
Odrazivosti r a
propustnosti t

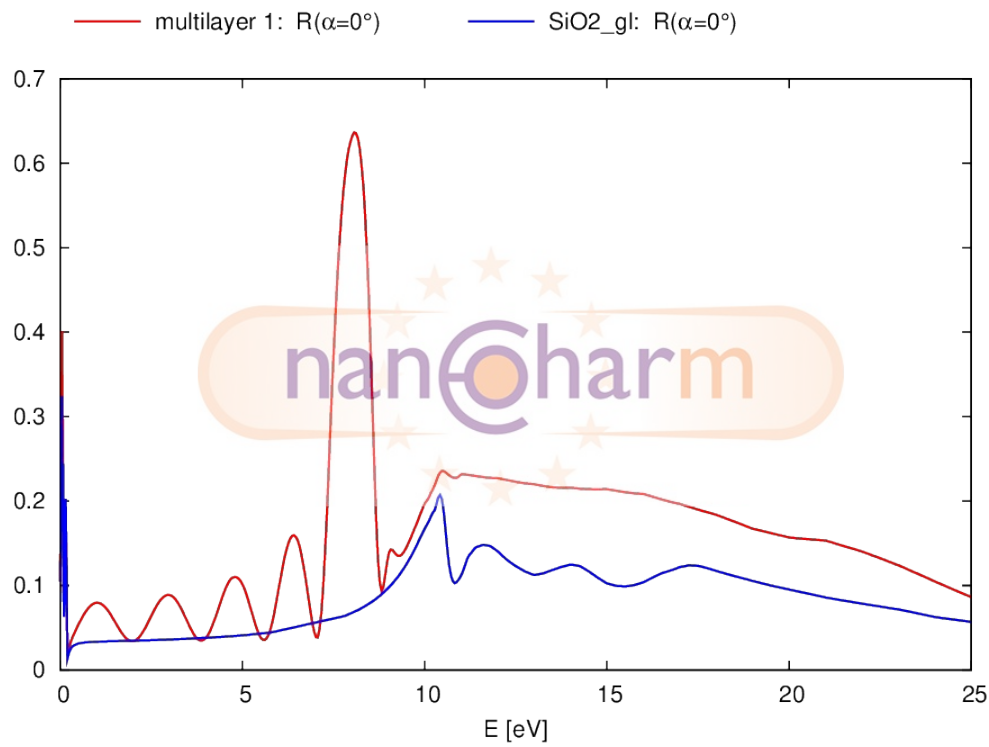
$$\begin{cases} r = \frac{B_0}{A_0}, \\ t = \frac{A'_s}{A_0}. \end{cases}$$

Vyjádření
pomocí prvků
matice M

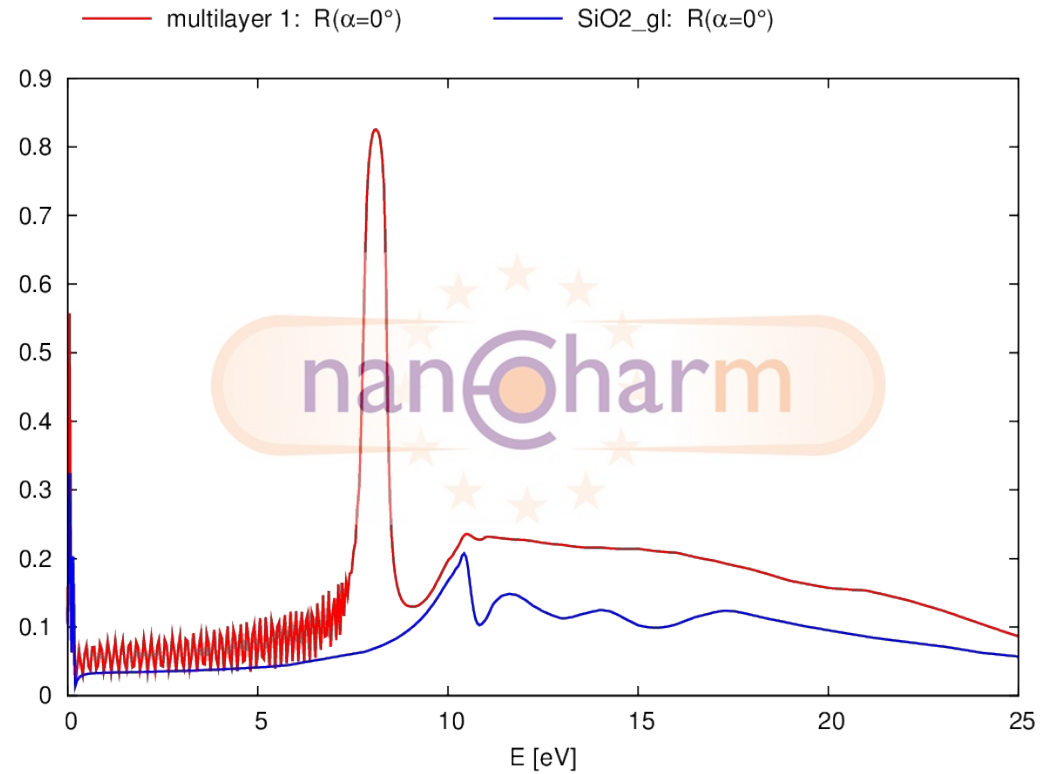
$$\begin{cases} r = \frac{M_{21}}{M_{11}}, \\ t = \frac{1}{M_{11}}. \end{cases}$$

$$\text{Odrazivost systému } R = |r|^2 = |M_{21}/M_{11}|^2$$

Multivrstva – kolmá odrazivost

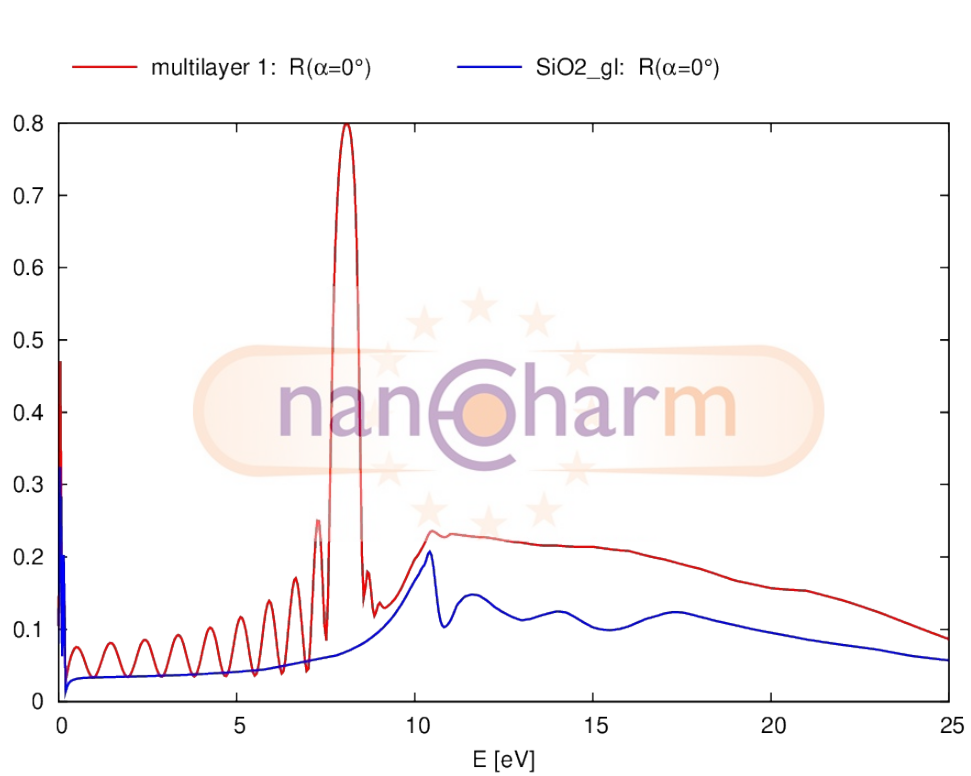


$(\text{SiO}_2 \text{ 20nm}/\text{Al}_2\text{O}_3 \text{ 20nm})\times 5$

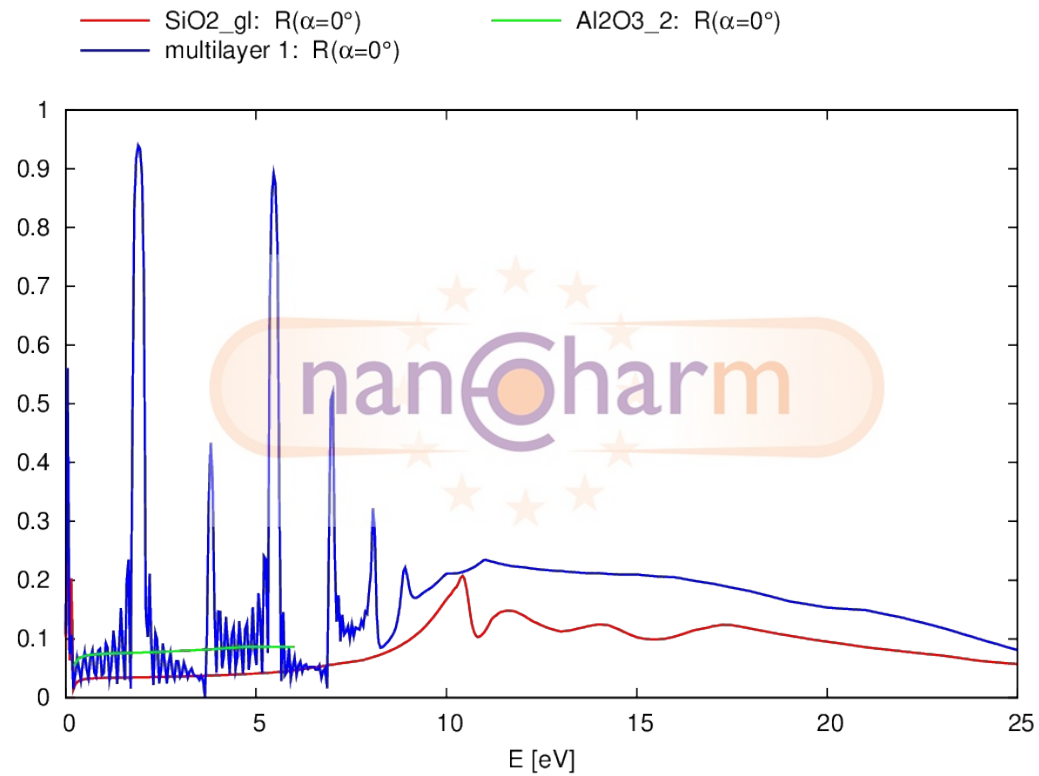


$(\text{SiO}_2 \text{ 20nm}/\text{Al}_2\text{O}_3 \text{ 20nm})\times 50$

Multivrstva – kolmá odrazivost



$(\text{SiO}_2 \text{ 20nm}/\text{Al}_2\text{O}_3 \text{ 20nm})\times 10$



$(\text{SiO}_2 \text{ 100nm}/\text{Al}_2\text{O}_3 \text{ 100nm})\times 10$

Lorentzův model

$$\epsilon(\omega) = 1 + \frac{Ne^2}{\epsilon_0 m} \frac{1}{\omega_0^2 - \omega^2 - i\omega/\tau} = 1 + \frac{Ne^2}{\epsilon_0 m} \frac{\omega_0^2 - \omega^2}{(\omega_0^2 - \omega^2)^2 + \omega^2/\tau^2} + i \frac{Ne^2}{\epsilon_0 m} \frac{\omega/\tau}{(\omega_0^2 - \omega^2)^2 + \omega^2/\tau^2}$$

$$\epsilon(\omega) = 1 + \frac{F}{\omega_0^2 - \omega^2 - i\omega/\tau} = 1 + F \frac{\omega_0^2 - \omega^2}{(\omega_0^2 - \omega^2)^2 + \omega^2/\tau^2} + iF \frac{\omega/\tau}{(\omega_0^2 - \omega^2)^2 + \omega^2/\tau^2}$$

$$F = \frac{Ne^2}{\epsilon_0 m}$$

$$\sigma(\omega) = -i\omega\epsilon_0(\epsilon(\omega) - 1) = \frac{-i\omega\epsilon_0 F}{\omega_0^2 - \omega^2 - i\omega/\tau} = \epsilon_0 F \frac{\omega^2/\tau}{(\omega_0^2 - \omega^2)^2 + \omega^2/\tau^2} - i\omega\epsilon_0 F \frac{\omega_0^2 - \omega^2}{(\omega_0^2 - \omega^2)^2 + \omega^2/\tau^2}$$

$$\epsilon(0) = 1 + \frac{F}{\omega_0^2}, \quad \epsilon(\infty) = 1$$

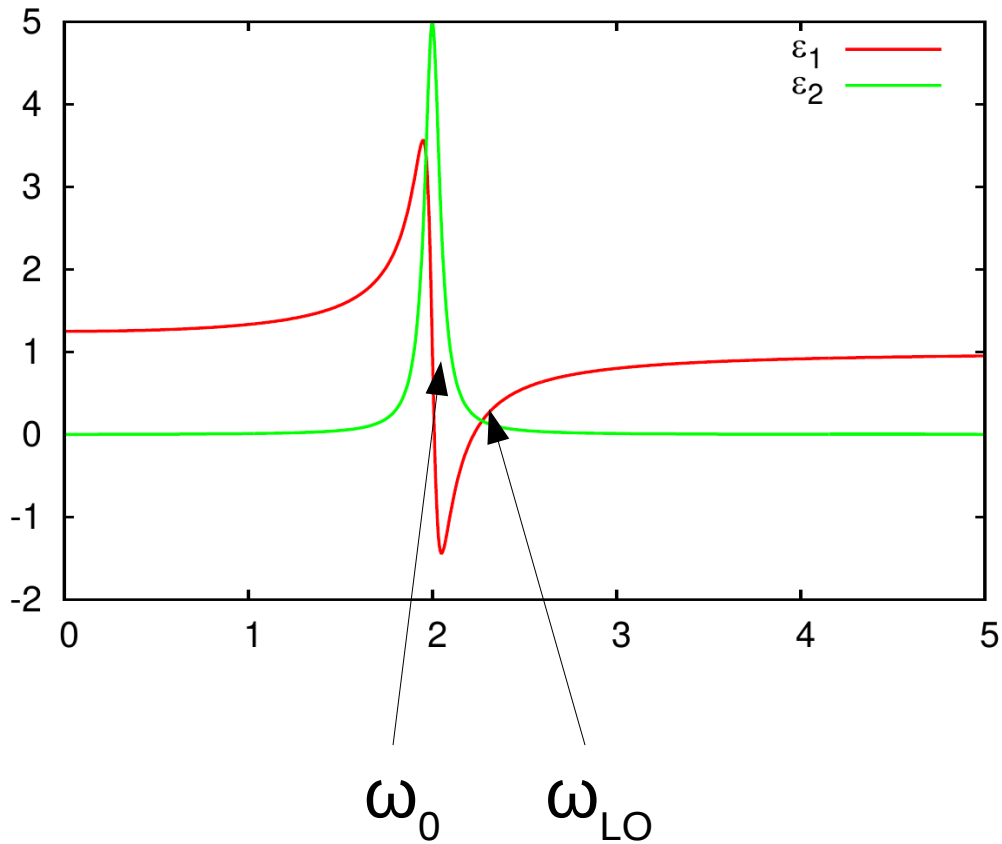
$$\epsilon_1(\omega_{LO}) = 0, \quad \frac{F}{\omega_0^2 - \omega_{LO}^2} + 1 = 0, \quad \omega_{LO}^2 \approx \omega_0^2 + F$$

Pří LO frekvence je reálná
část dielektrické funkce rovna
nule

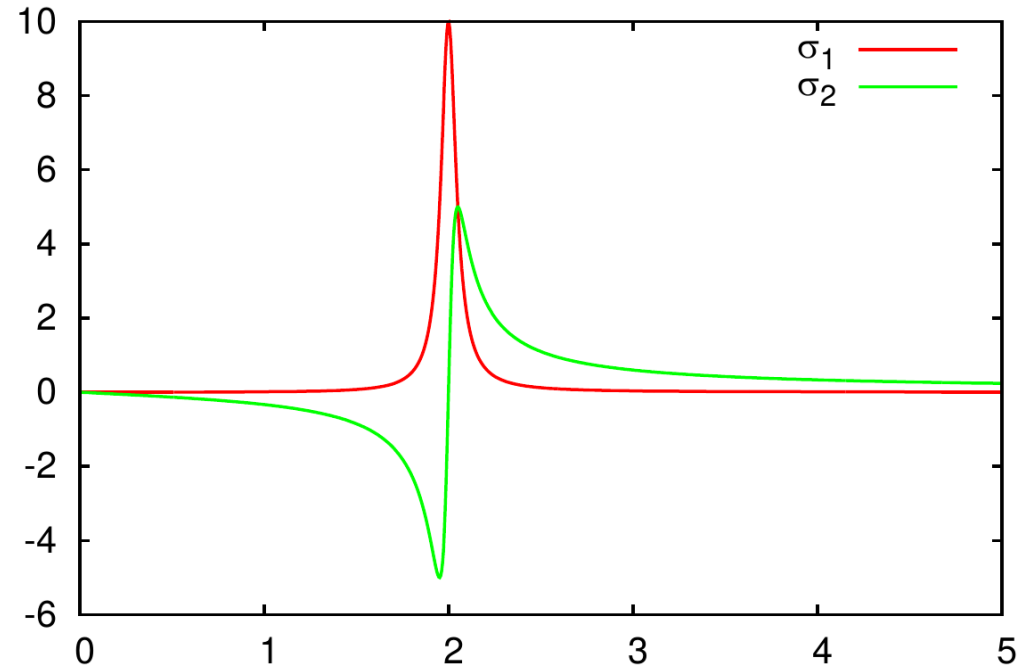
$$\frac{\omega_{LO}^2}{\omega_0^2} = \frac{\epsilon(0)}{\epsilon(\infty)}$$

Lorentzian model

$\omega_0=2.0, \gamma=0.1, F=1.0$

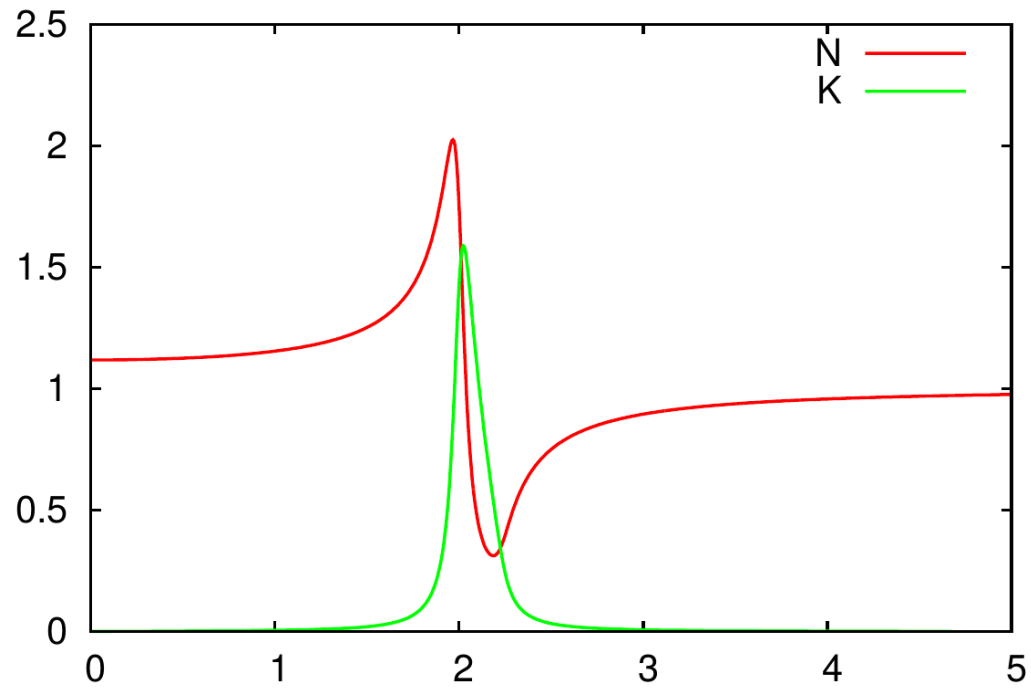


$\omega_0=2.0, \gamma=0.1, F=1.0$

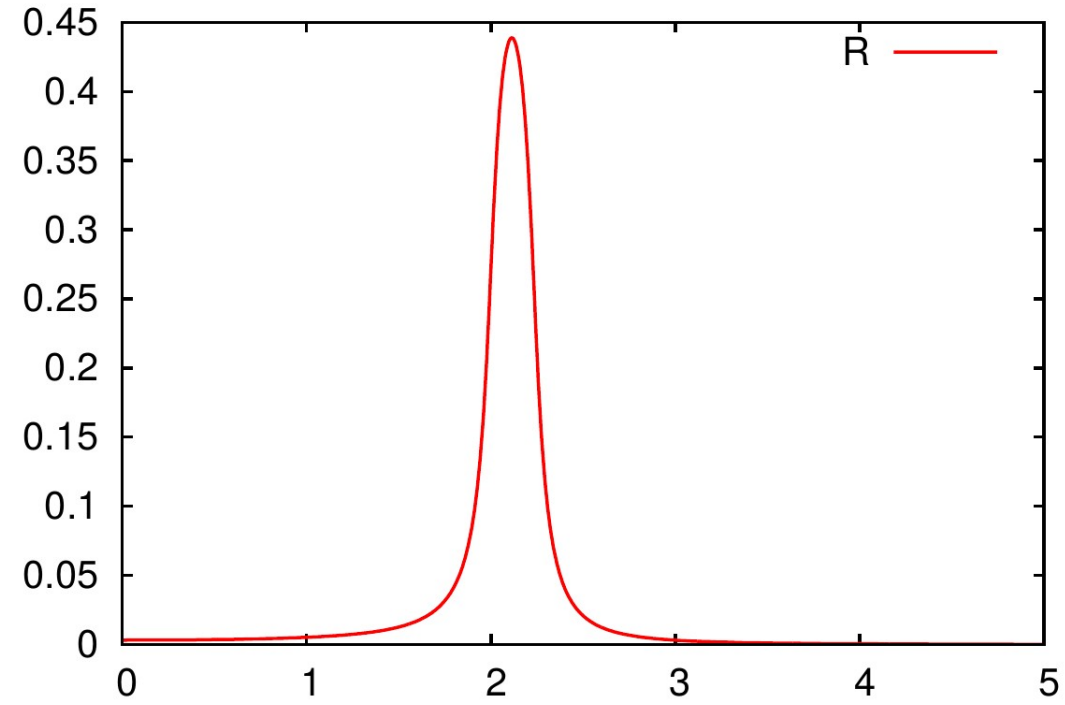


Lorentzian model

$\omega_0=2.0, \gamma=0.1, F=1.0$

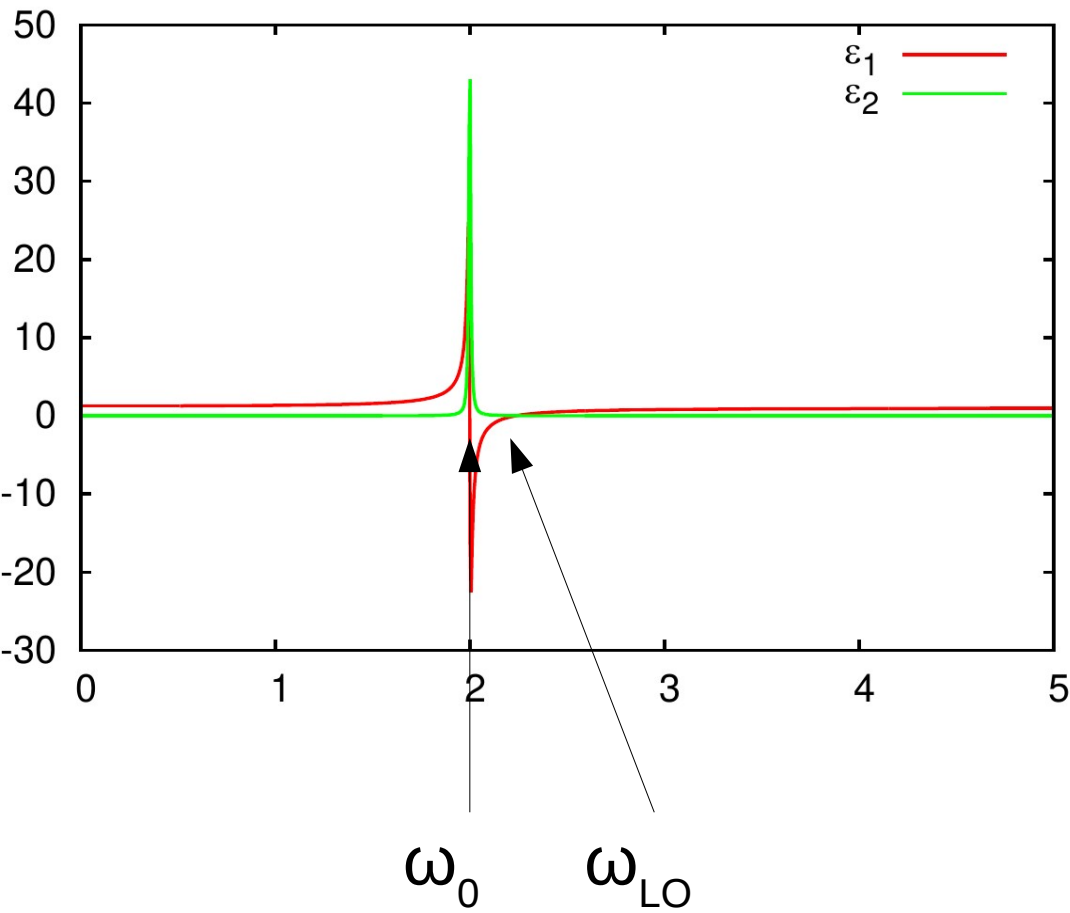


$\omega_0=2.0, \gamma=0.1, F=1.0$

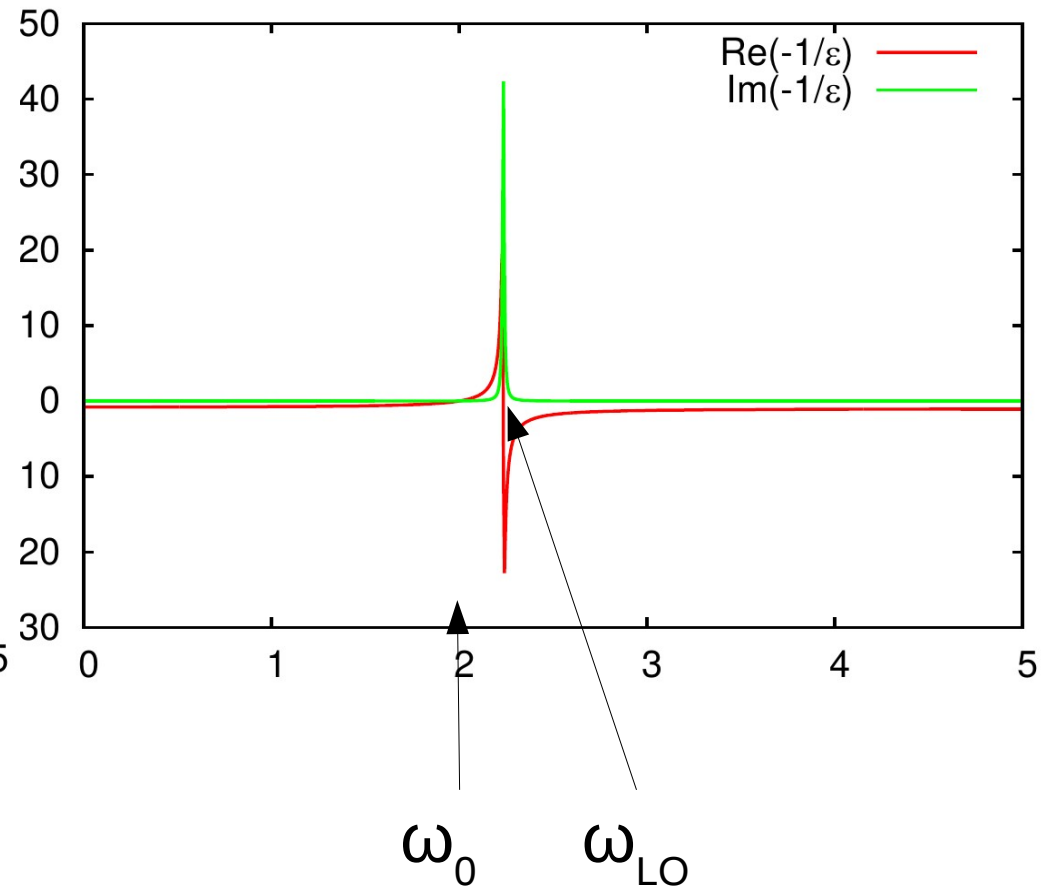


Lorentzian model

$\omega_0=2.0, \gamma=0.01, F=1.0$

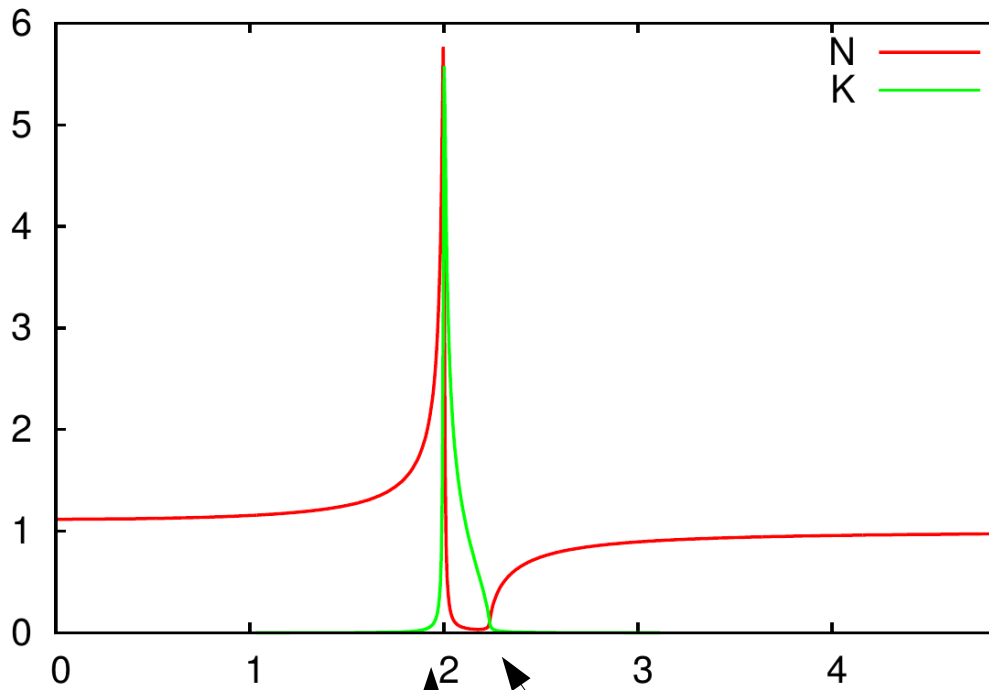


$\omega_0=2.0, \gamma=0.01, F=1.0$



Lorentzian model

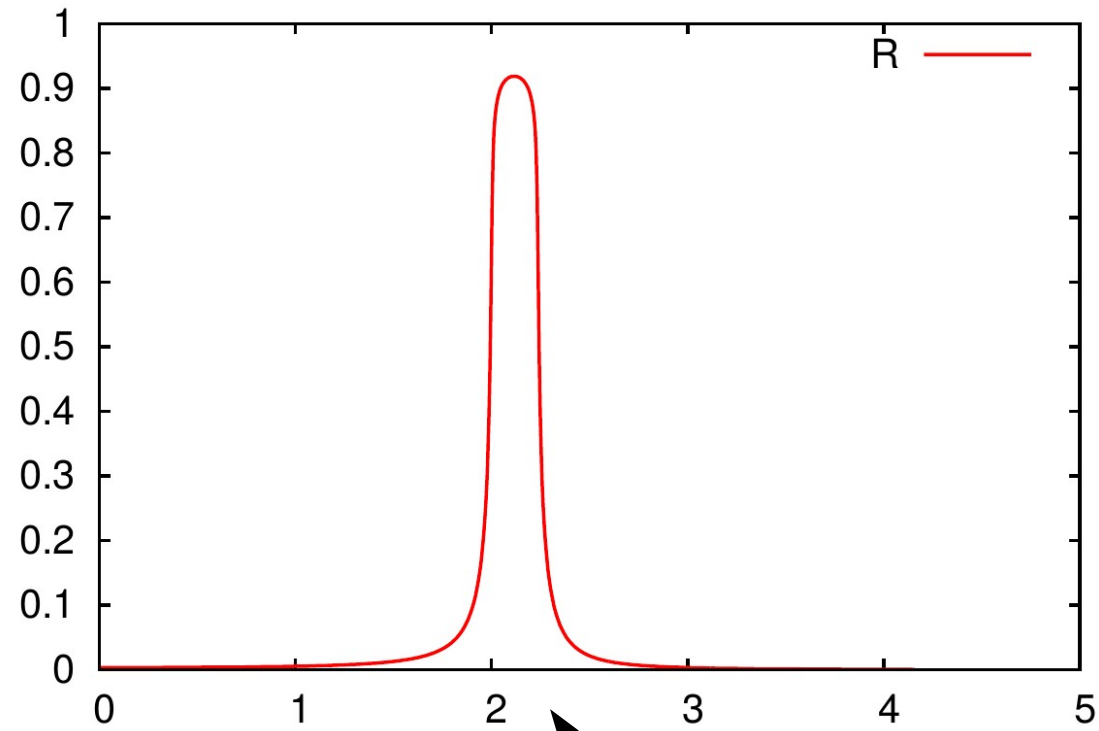
$\omega_0=2.0, \gamma=0.01, F=1.0$



ω_0

$$\omega_{LO} = \sqrt{\omega_0^2 + F}$$

$\omega_0=2.0, \gamma=0.01, F=1.0$

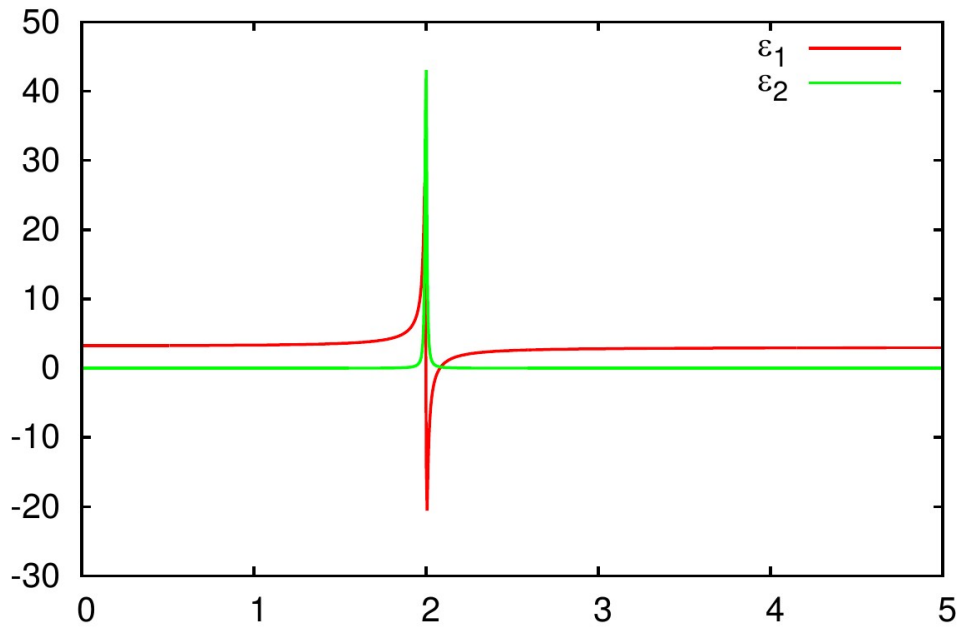


ω_0

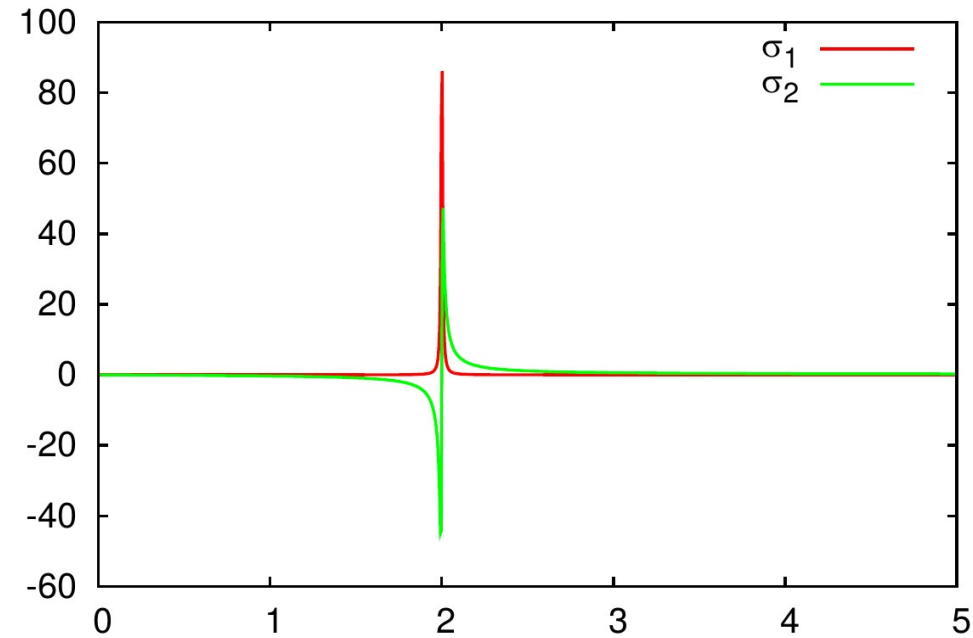
ω_{LO}

Lorentzian model

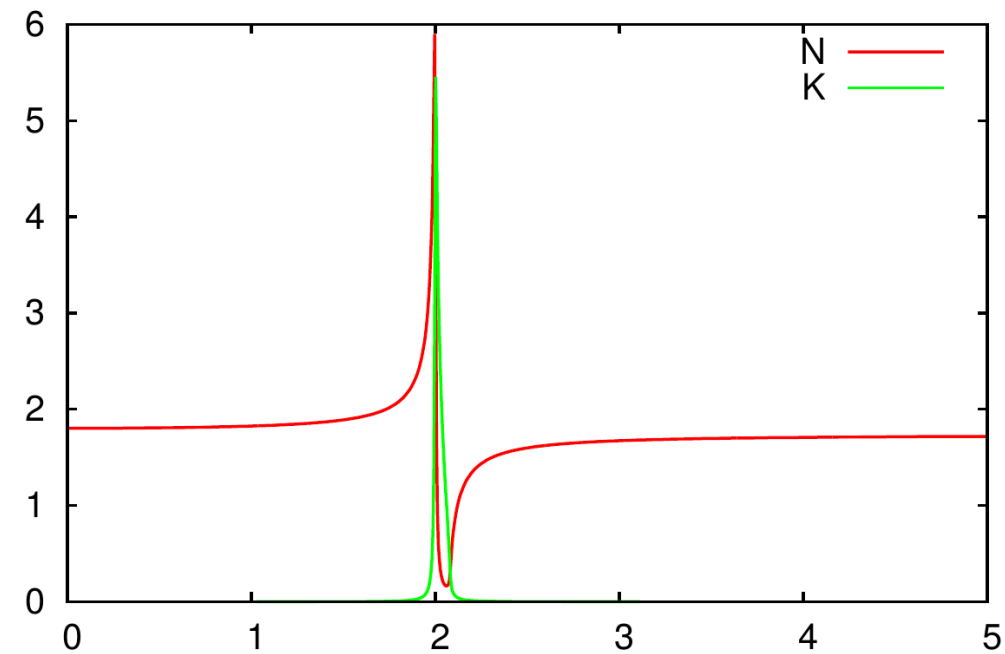
$\varepsilon_{\text{inf}}=3.0, \omega_0=2.0, \gamma=0.01, F=1.0$



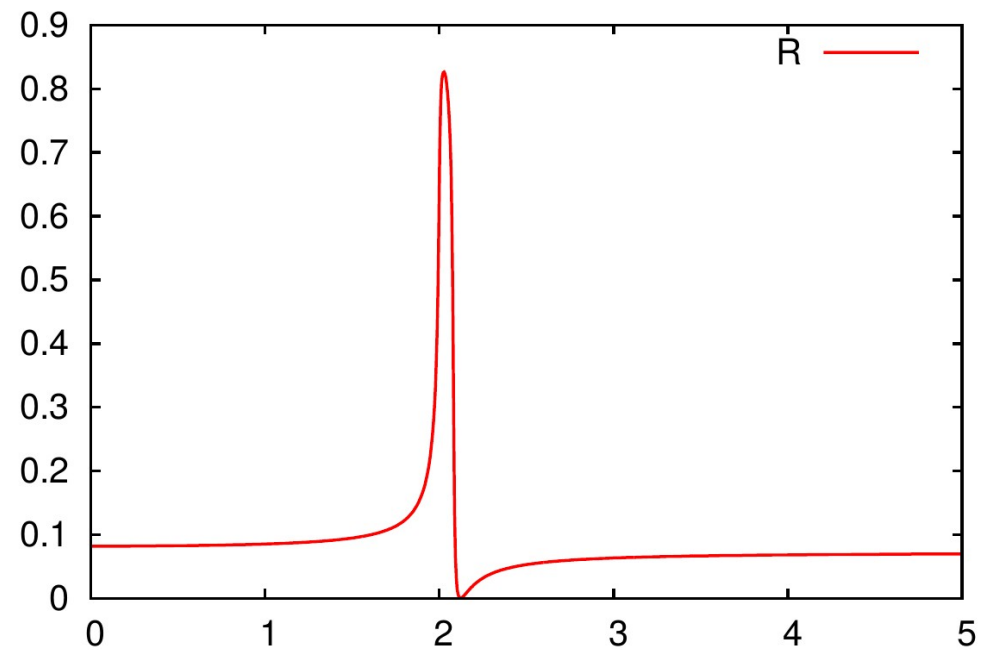
$\varepsilon_{\text{inf}}=3.0, \omega_0=2.0, \gamma=0.01, F=1.0$



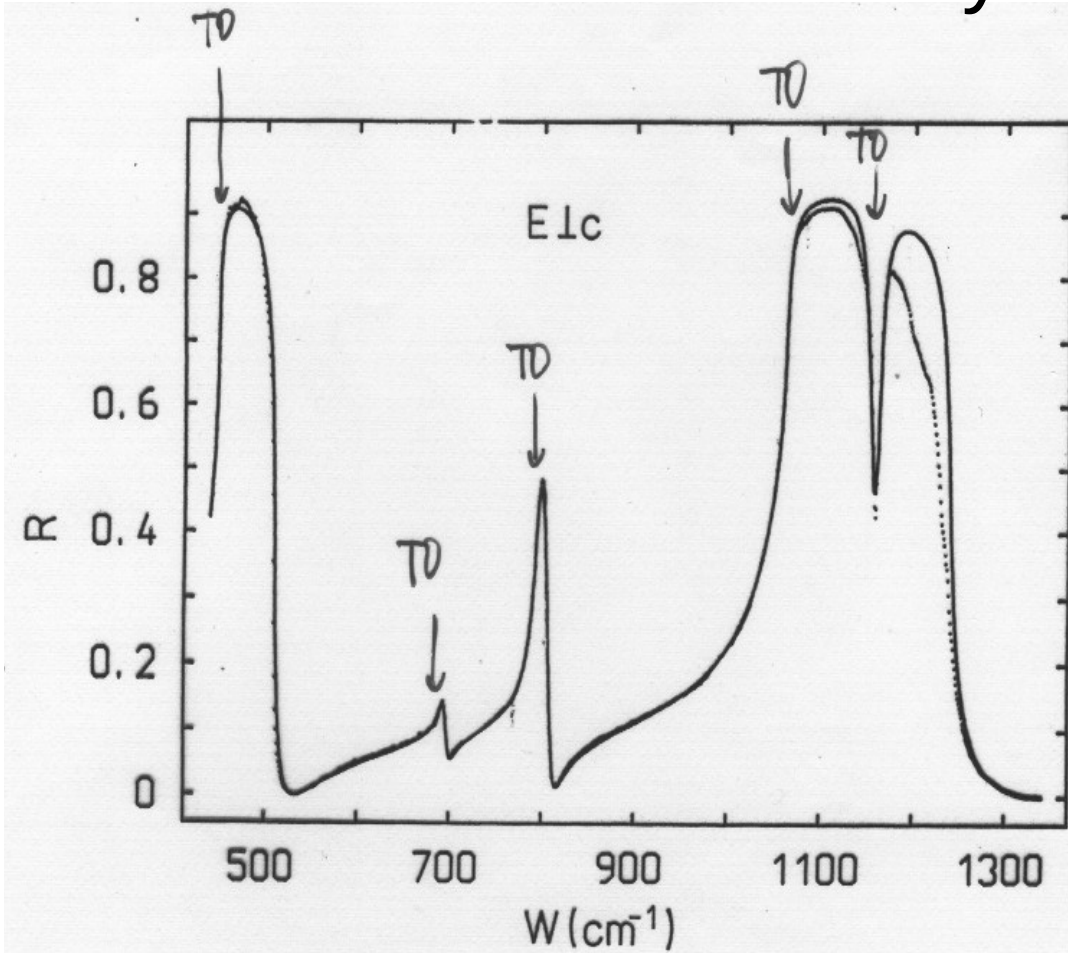
$\varepsilon_{\text{inf}}=3.0, \omega_0=2.0, \gamma=0.01, F=1.0$



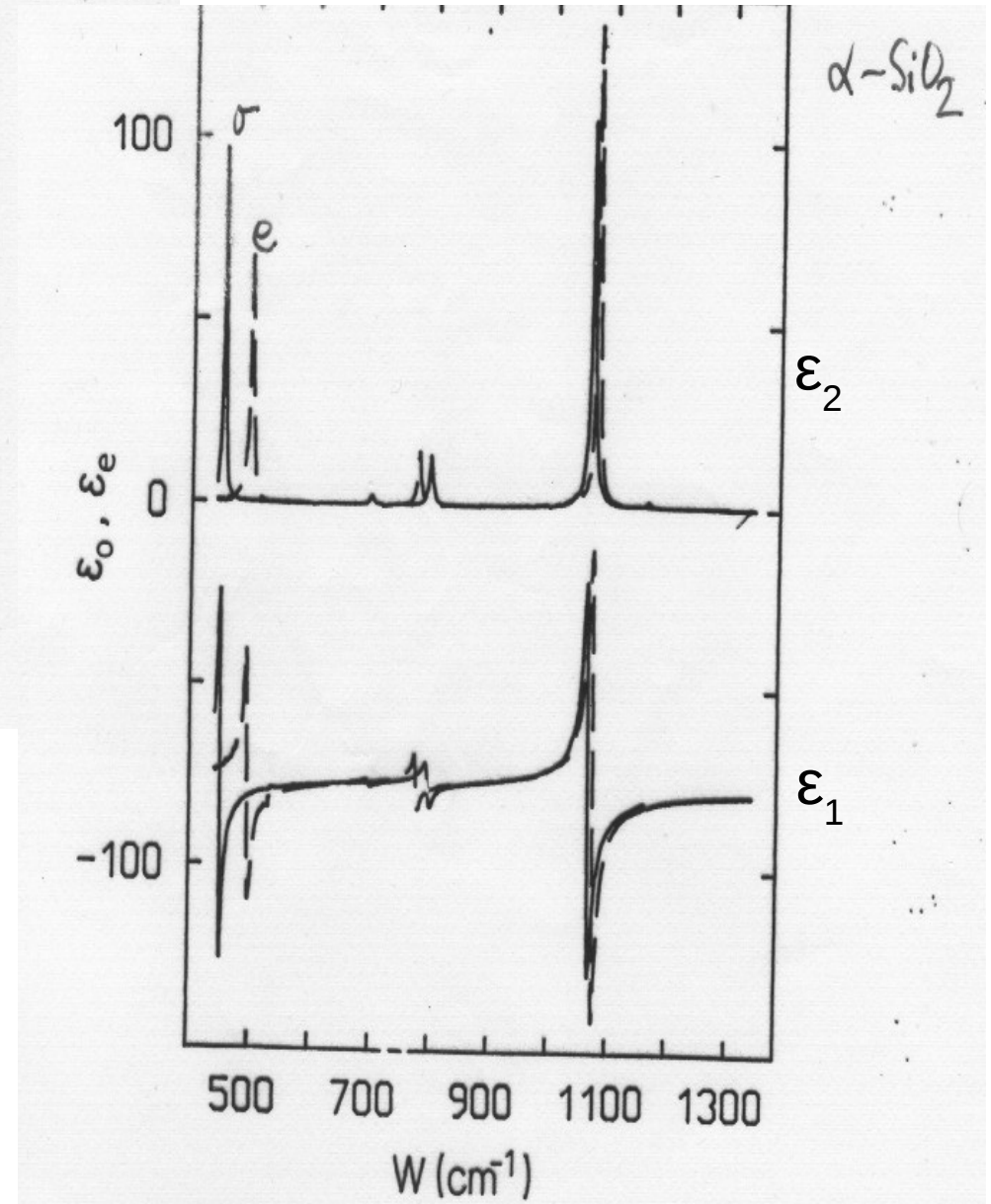
$\varepsilon_{\text{inf}}=3.0, \omega_0=2.0, \gamma=0.01, F=1.0$



Odrazivost krystalického α -SiO₂



α -SiO₂



Odrazivost GaAs

fotonová disperze $\omega = ck$
 $c = 300000 \text{ km/s}$

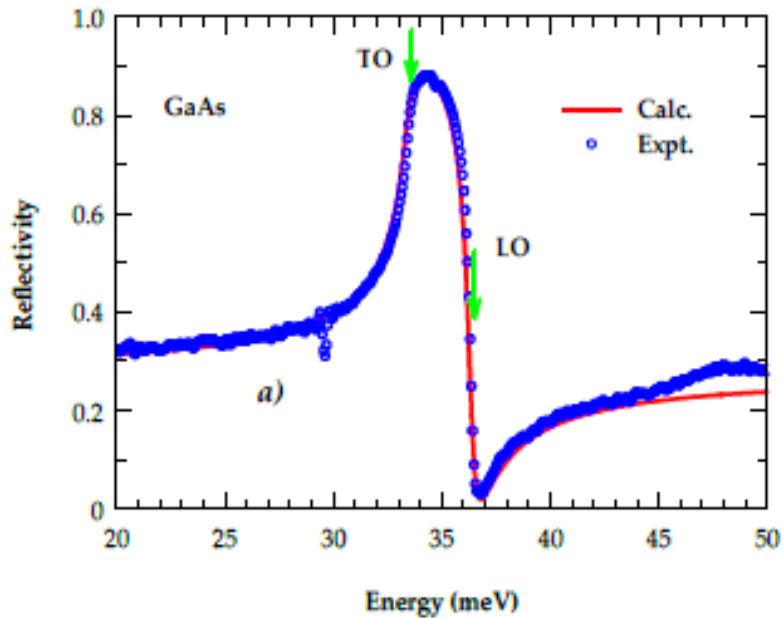
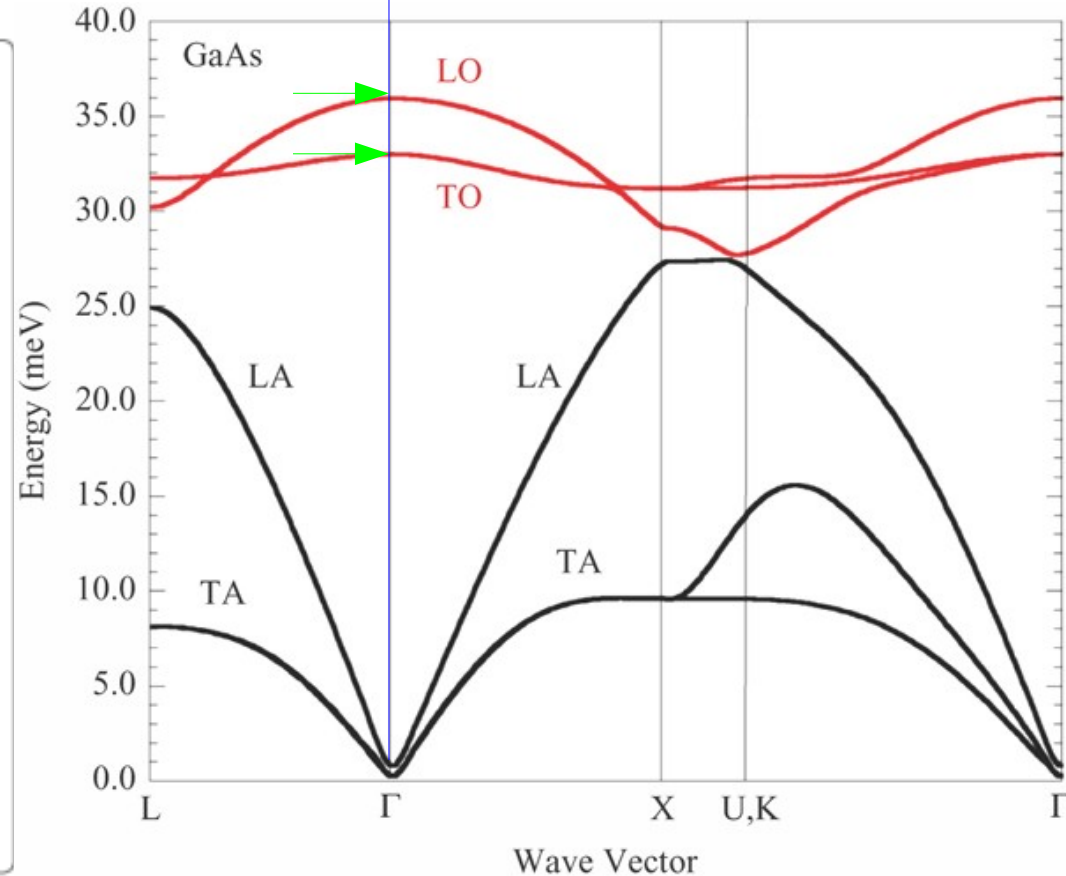


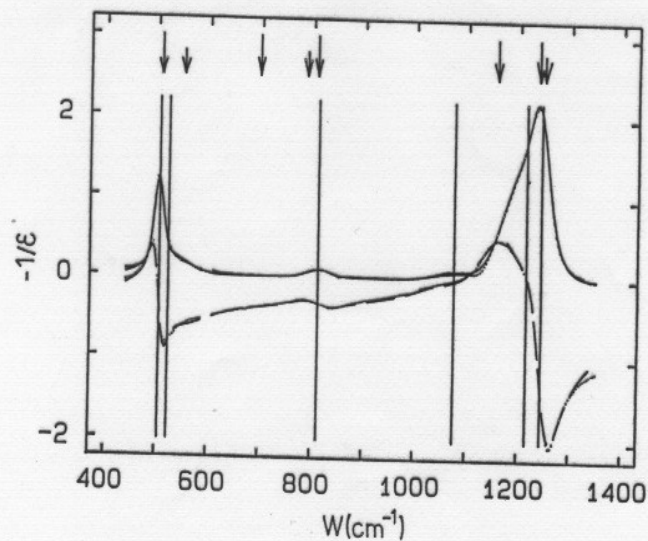
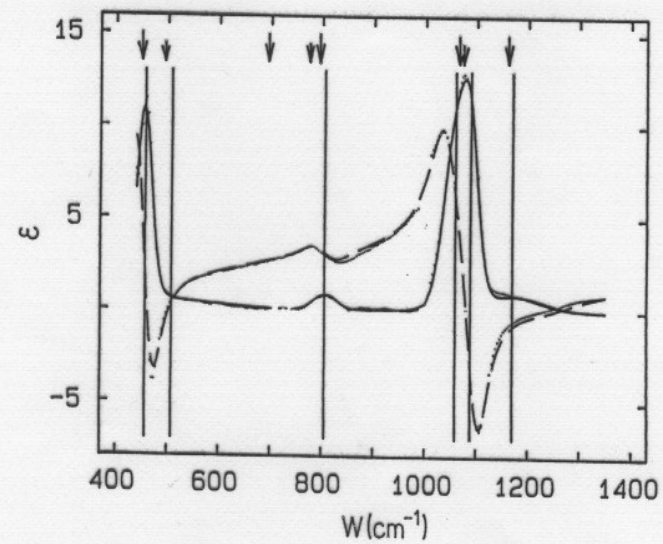
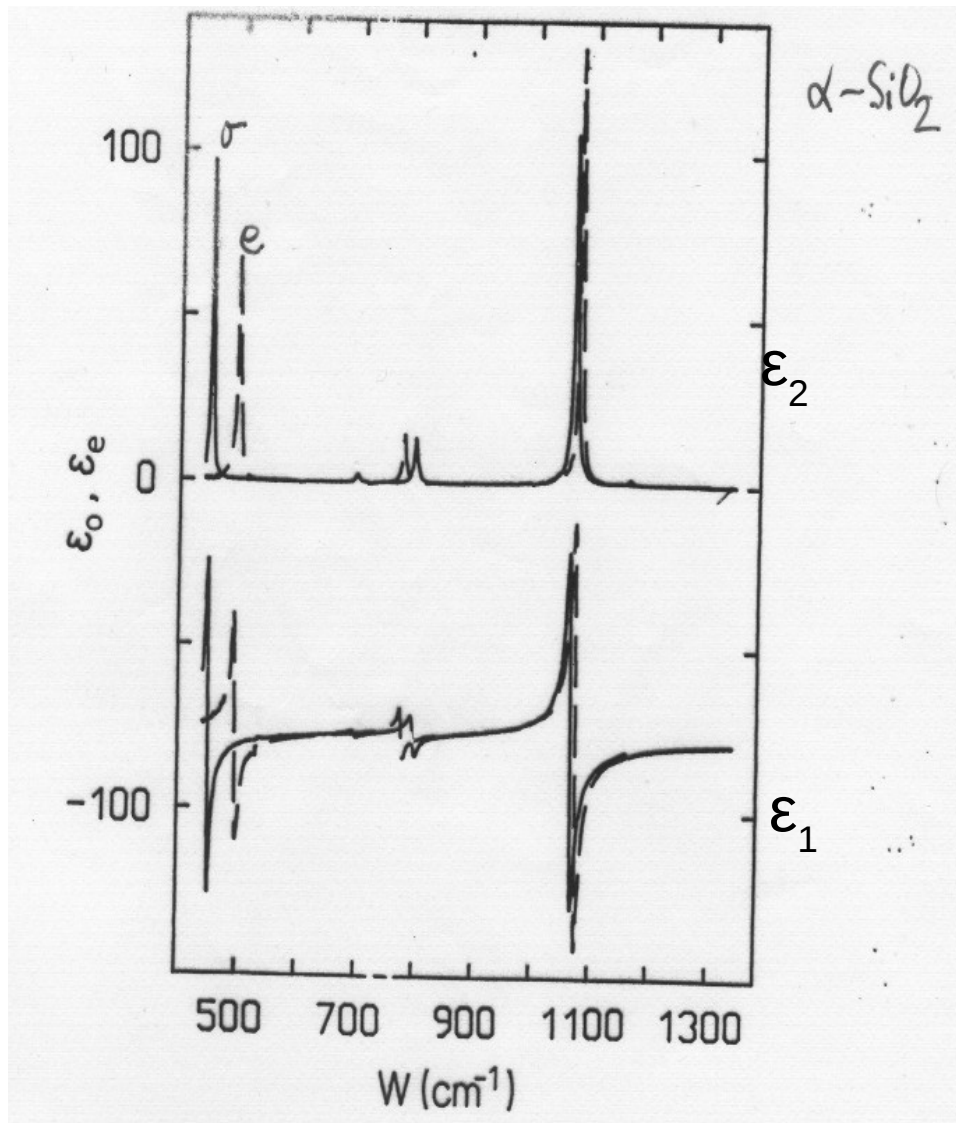
Figure 2a: Comparison of the experimental FIR reflectivity spectra for GaAs represented by blue color open circles (○) with the best fit simulated reflectivity results shown by red color solid line (—) using a classical Drude-Lorentz model (Eq. 3) with parameter values from Table 1 b) – green colored vertical arrows are used to represent TO and LO modes.



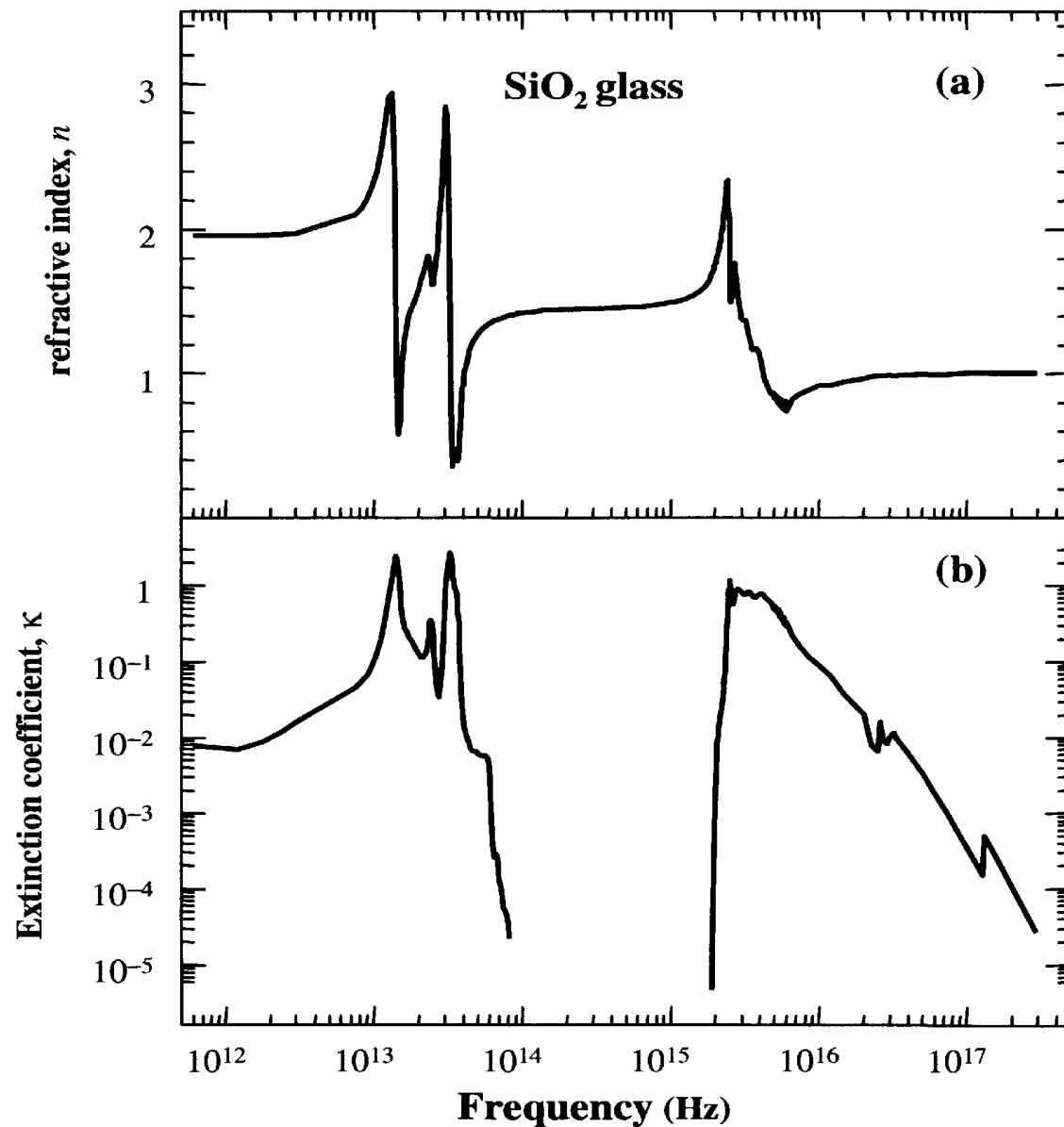
fononová disperze $\omega = vk$
 pro akustické fonony $v \approx 1 \text{ km/s}$

Frekvence oscilátoru je rovna frekvenci optických fononů v bodě Γ

Dielektrická funkce krystalického α -SiO₂ a amorfního ν -SiO₂



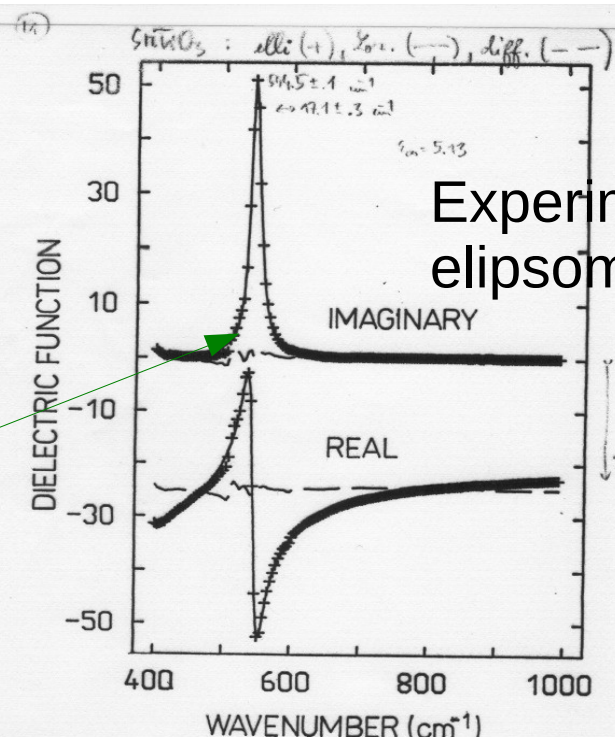
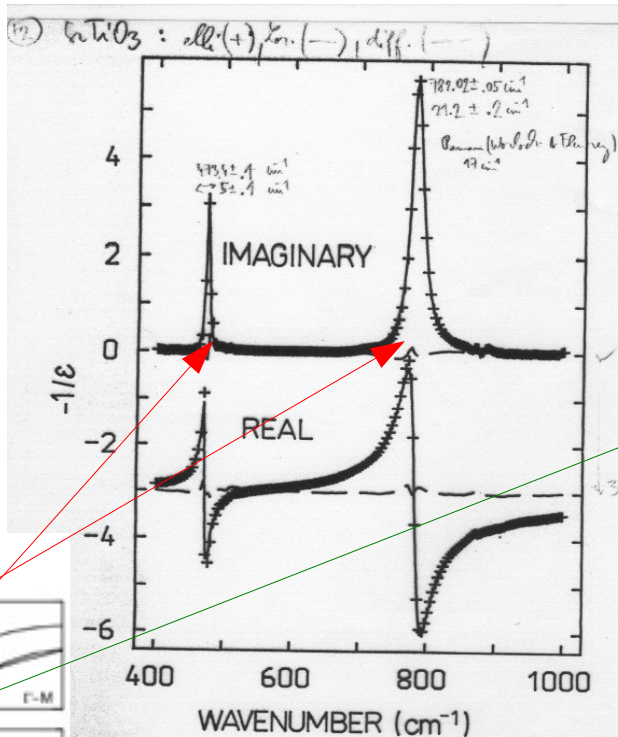
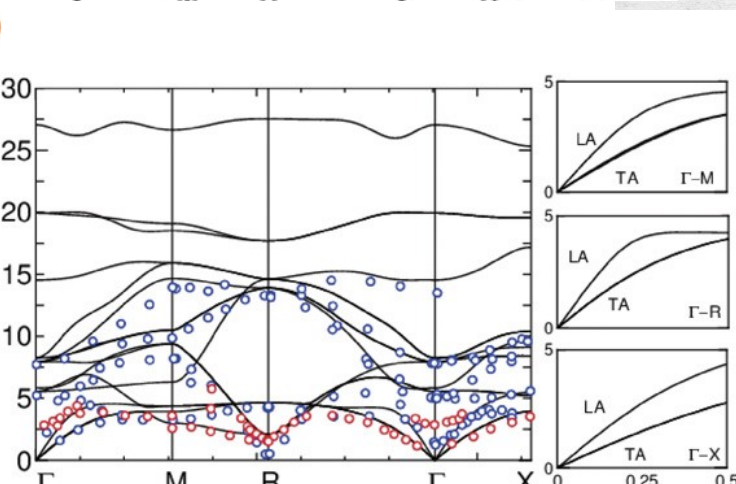
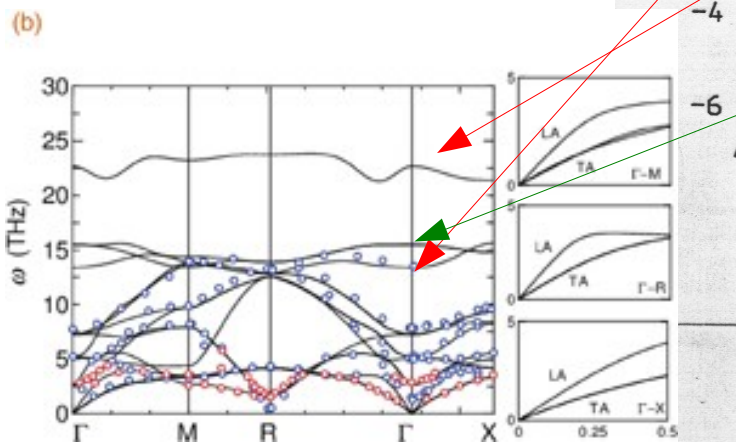
Index lomů amorfního SiO₂ skla



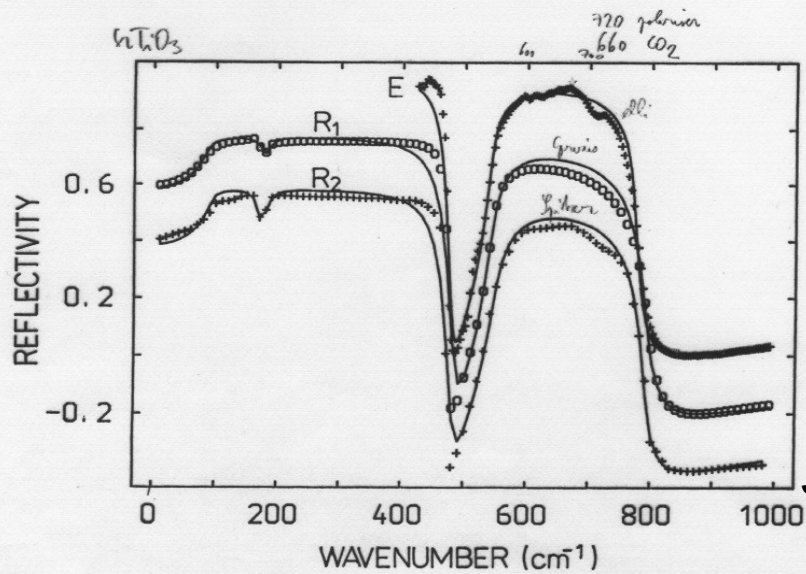
SrTiO₃ – měření a fit Lorentzovým modelem

TO
530 cm⁻¹ ... 16 THz

LO
470 cm⁻¹ ... 14 THz
780 cm⁻¹ ... 23 THz



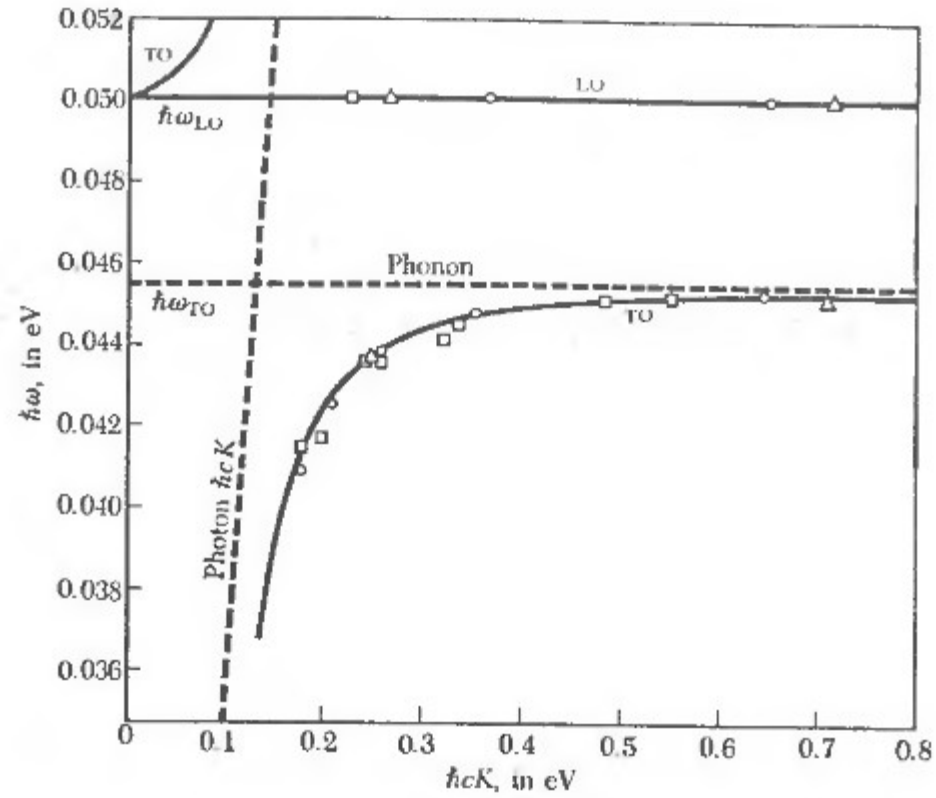
Experiment:
elipsometrie



J. Humlíček

GaP disperzni relace polaritonu

GaP



Drudeho model

$$\sigma(\omega) = -nev_0/E = \frac{\sigma_0}{1 - i\omega\tau} = \frac{\sigma_0}{1 + \omega^2\tau^2} + i\frac{\sigma_0\omega\tau}{1 + \omega^2\tau^2}$$

$$\sigma_0 = \frac{Ne^2\tau}{m} \quad \text{Stejnosem\u0159n\u00e1 vodivost}$$

$$\epsilon(\omega) = 1 - \frac{Ne^2}{\epsilon_0 m} \frac{1}{\omega^2 + i\omega/\tau} = 1 - \frac{Ne^2\tau}{\epsilon_0 m} \frac{1}{\omega(i + \omega\tau)} = 1 - \frac{\omega_P^2\tau}{\omega(i + \omega\tau)} = 1 - \frac{\sigma_0}{\epsilon_0\omega} \frac{1}{i + \omega\tau}$$

$$\epsilon(\omega) = 1 - \frac{\omega_P^2\tau^2}{1 + \omega^2\tau^2} + i\frac{\omega_P^2\tau/\omega}{1 + \omega^2\tau^2} = 1 - \frac{\sigma_0}{\epsilon_0} \frac{\tau}{1 + \omega^2\tau^2} + i\frac{\sigma_0}{\epsilon_0\omega} \frac{1}{1 + \omega^2\tau^2}$$

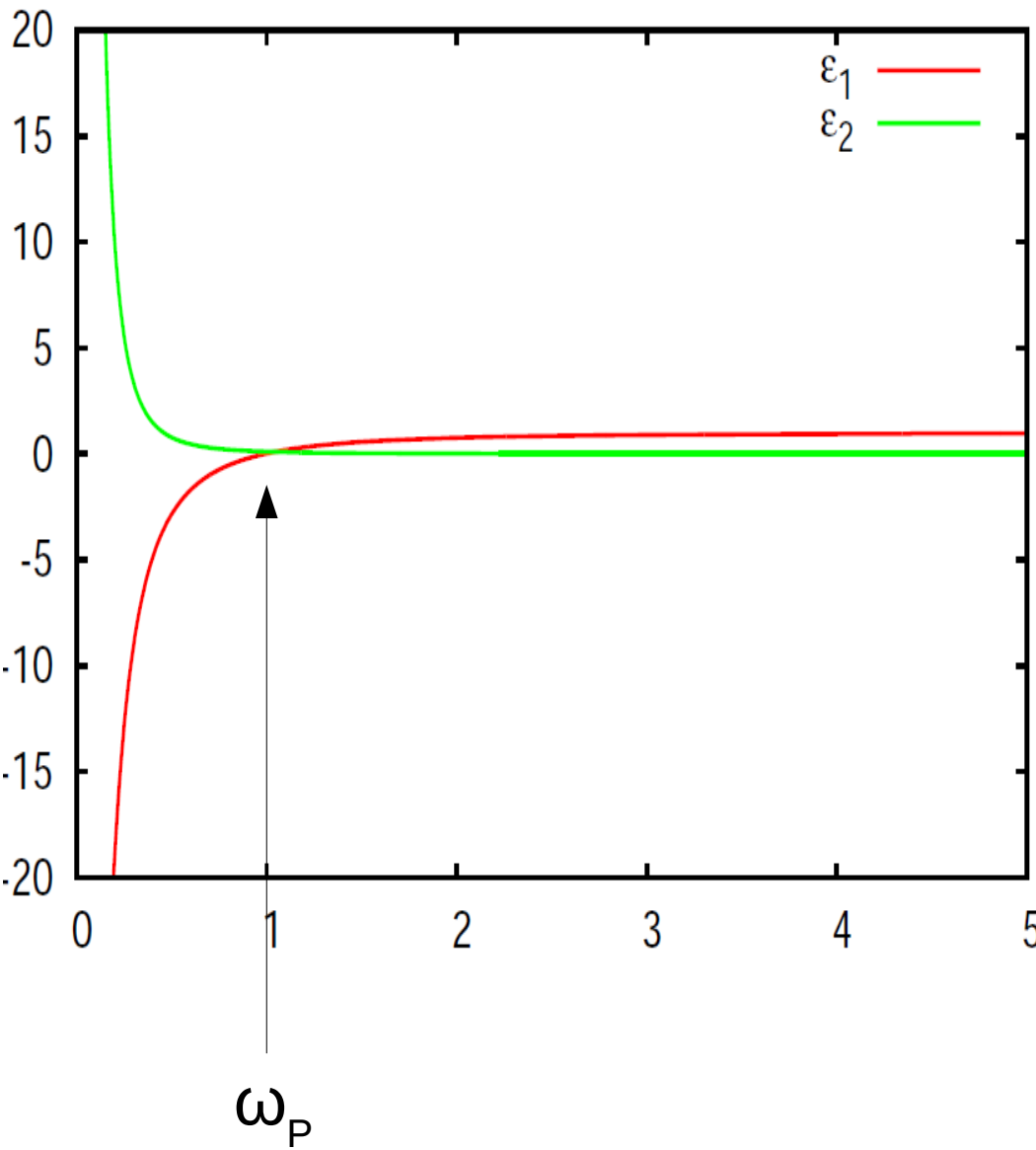
$$\sigma_0 = \frac{Ne^2\tau}{m} = \epsilon_0\omega_P^2\tau$$

$$\epsilon_1(\omega_L) = 0, \quad \omega_L = \sqrt{\omega_P^2 - 1/\tau^2} \approx \omega_P \quad \begin{array}{l} \text{LO frekvence je rovna plazmov\u00e9} \\ \text{frekvenci} \end{array}$$

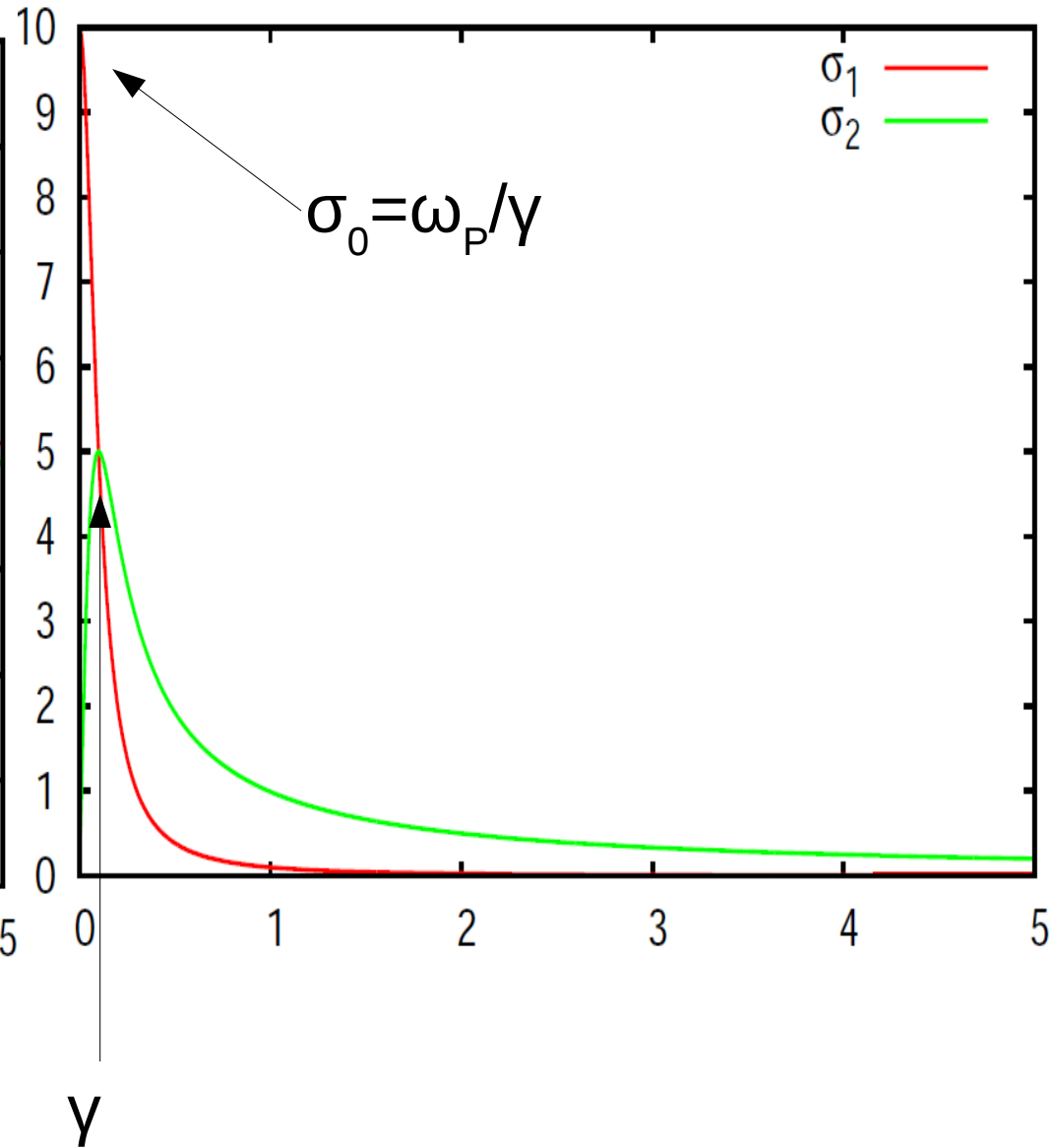
$$\sigma(0) = \sigma_0. \quad \sigma_1(1/\tau) = \sigma_2(1/\tau) = \sigma_0/2. \quad \text{Stejnosem\u0159n\u00e1 vodivost}$$

Drudeho model

$\omega_0=0.0, \gamma=0.1, \omega_p=1.0$

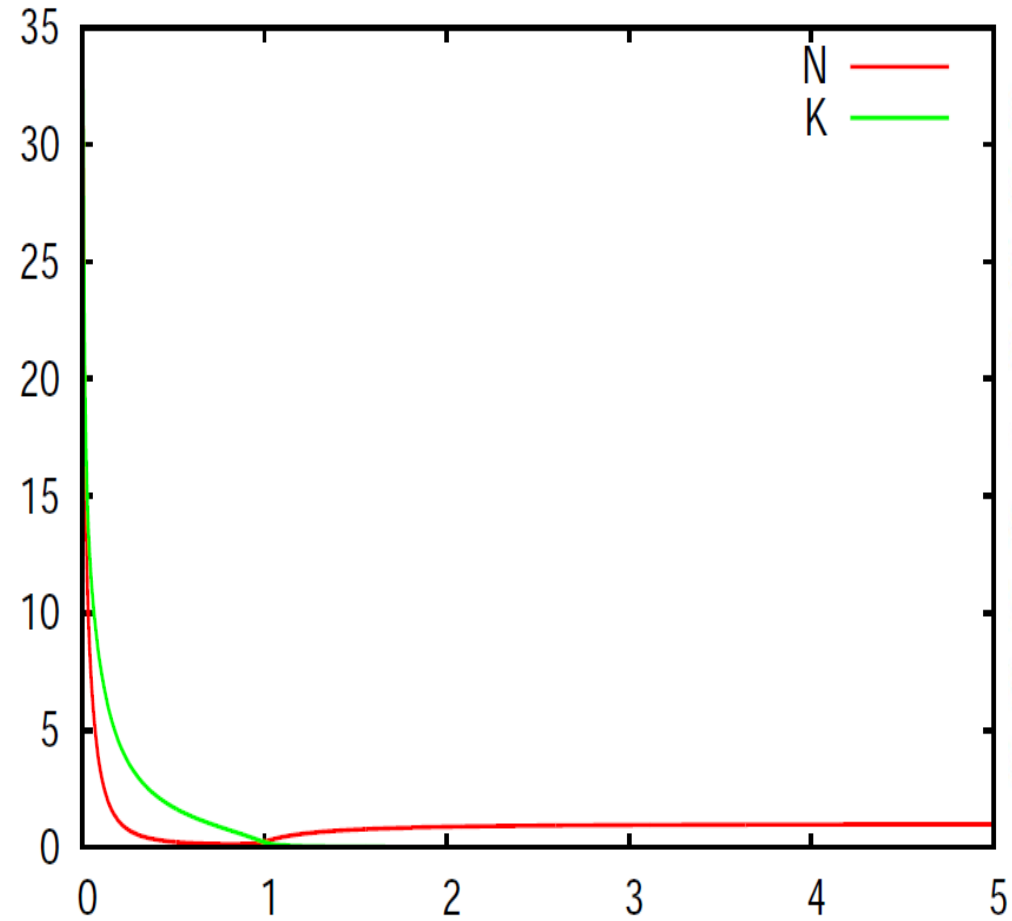


$\omega_0=0.0, \gamma=0.1, \omega_p=1.0$

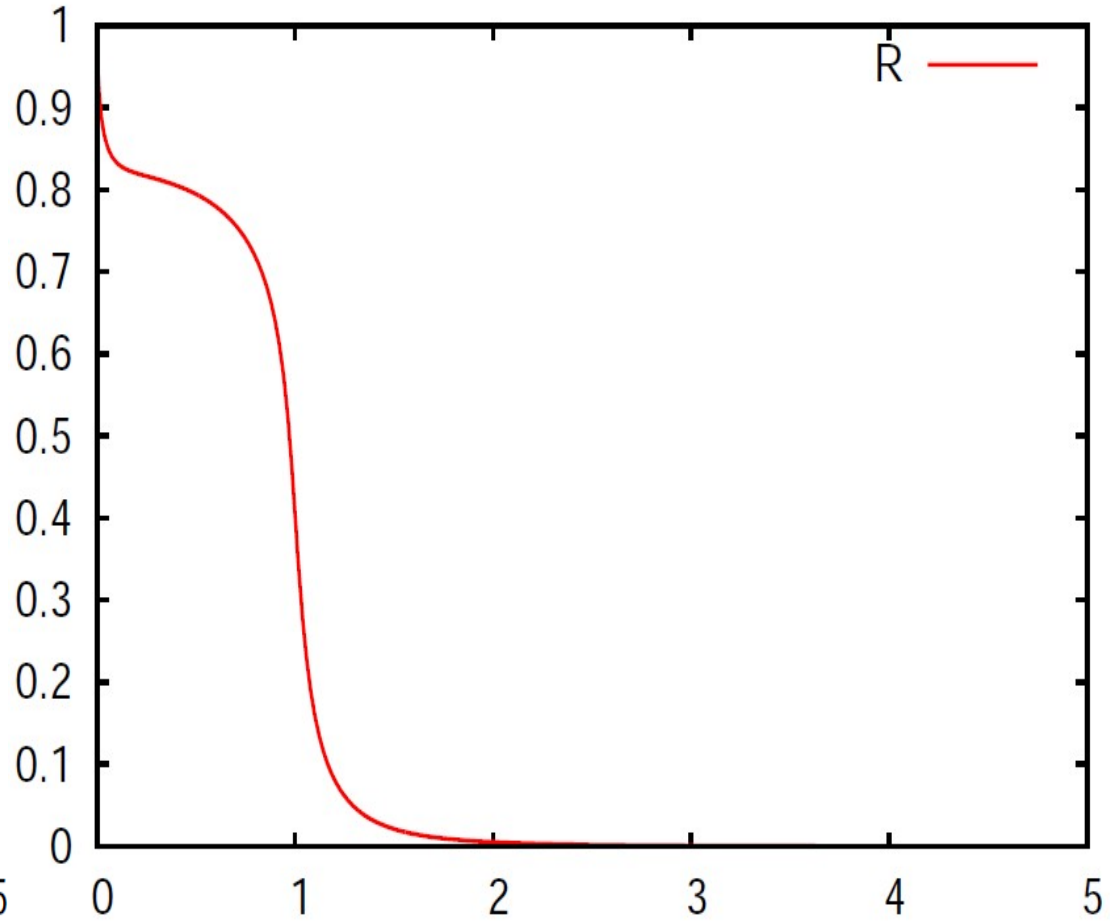


Drudeho model

$\omega_0=0.0, \gamma=0.1, \omega_p=1.0$

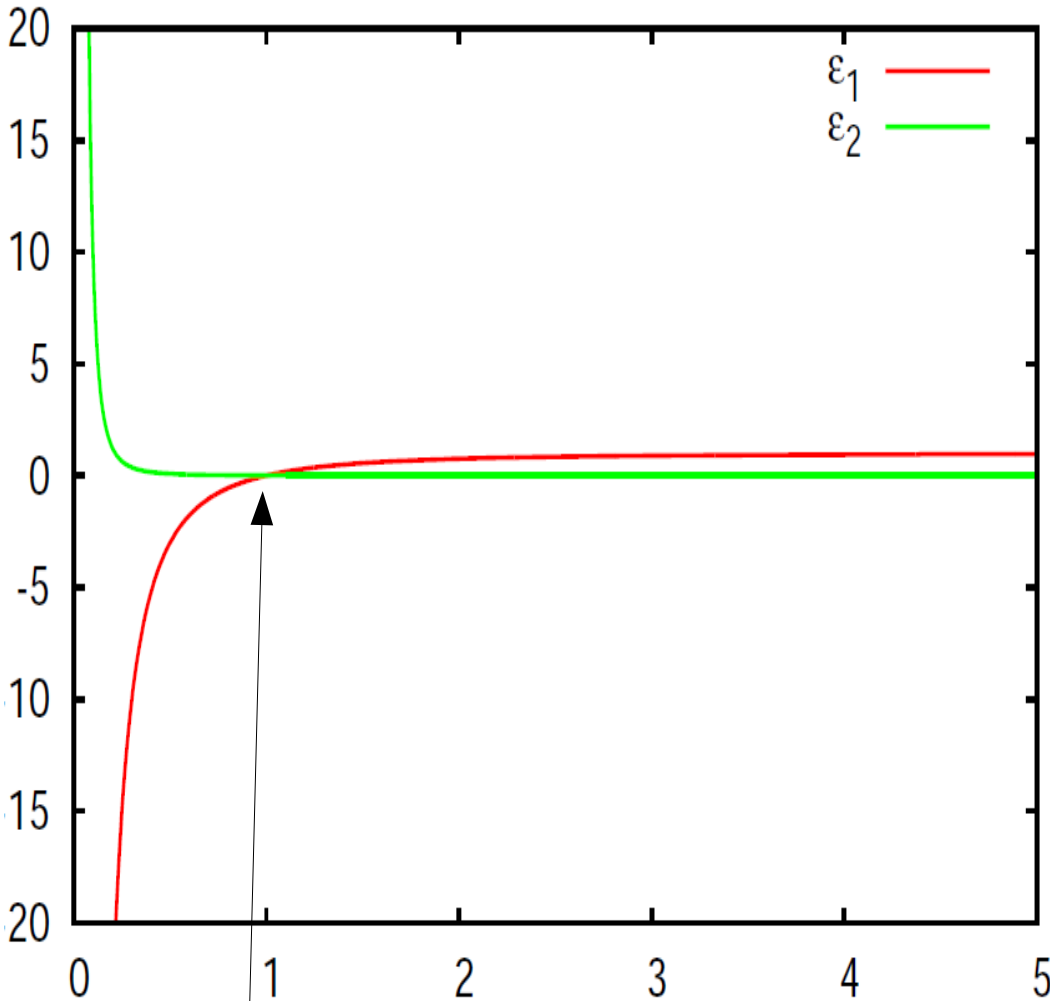


$\omega_0=0.0, \gamma=0.1, \omega_p=1.0$

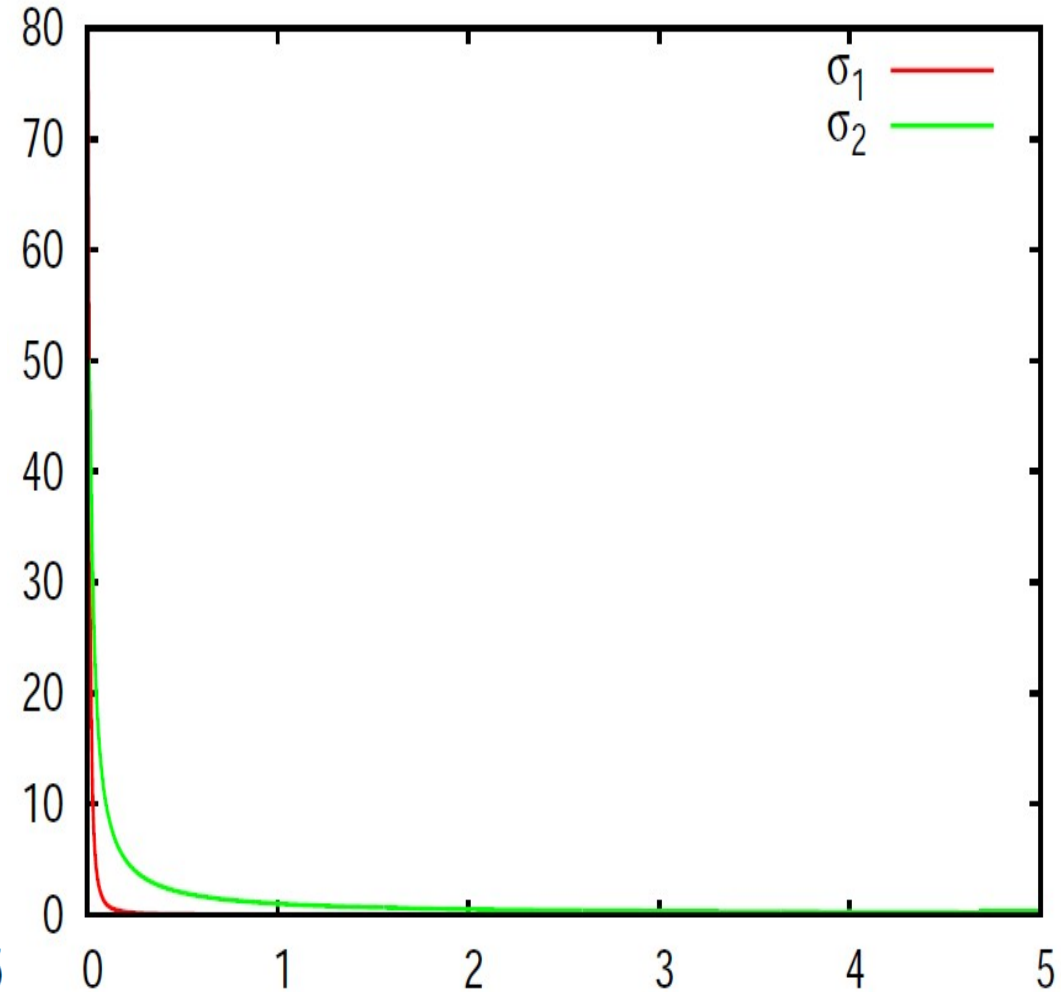


Drudeho model

$\omega_0=0.0, \gamma=0.01, \omega_p=1.0$



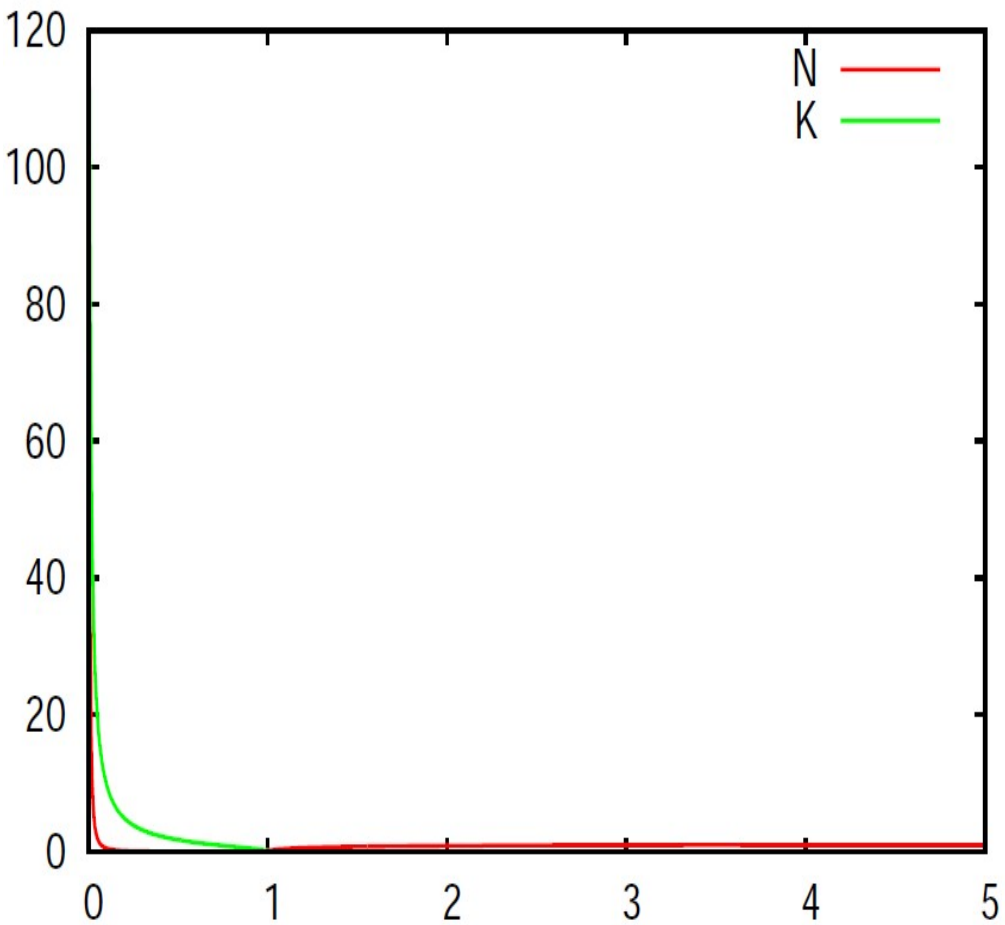
$\omega_0=0.0, \gamma=0.01, \omega_p=1.0$



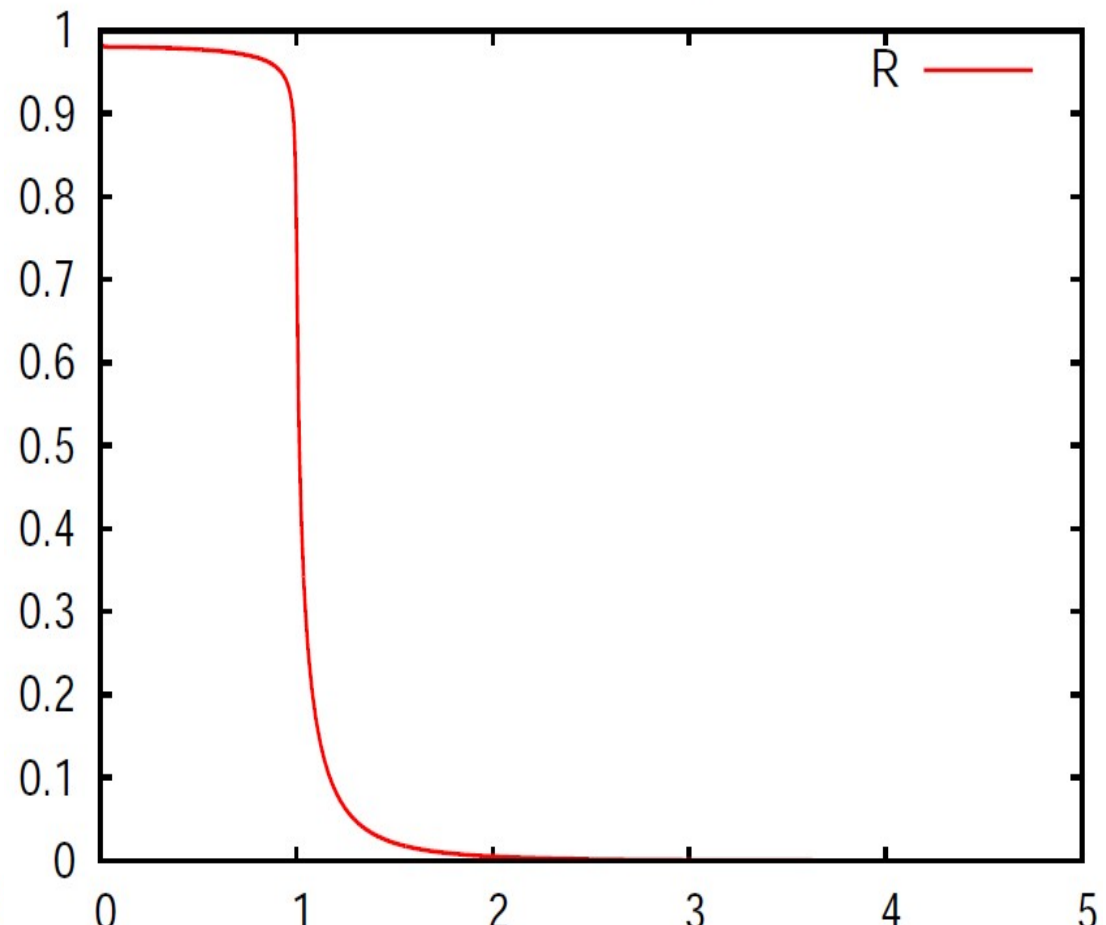
ω_p

Drudeho model

$\omega_0=0.0, \gamma=0.01, \omega_p=1.0$



$\omega_0=0.0, \gamma=0.01, \omega_p=1.0$

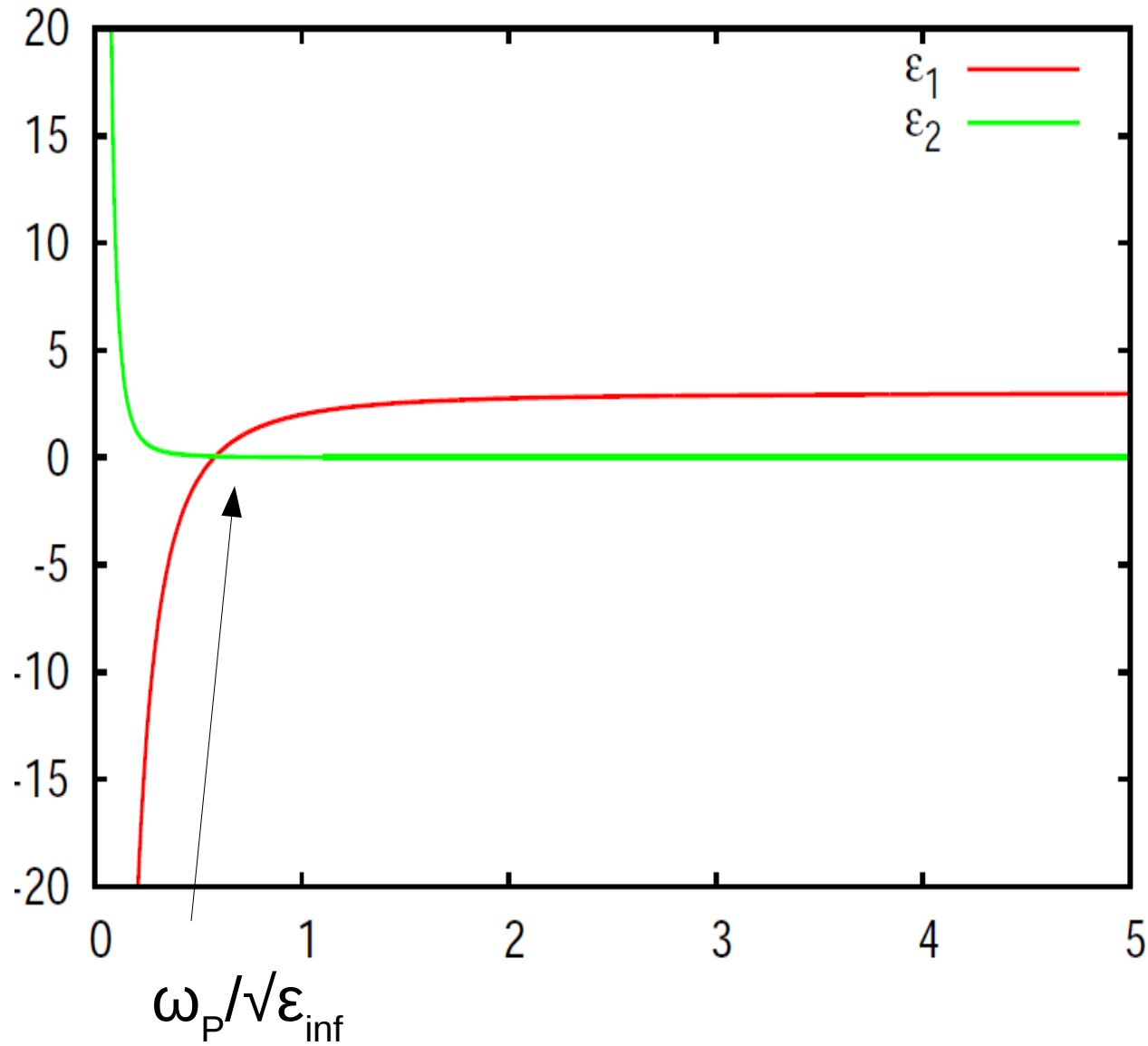


ω_p

ω_p

Drudeho model

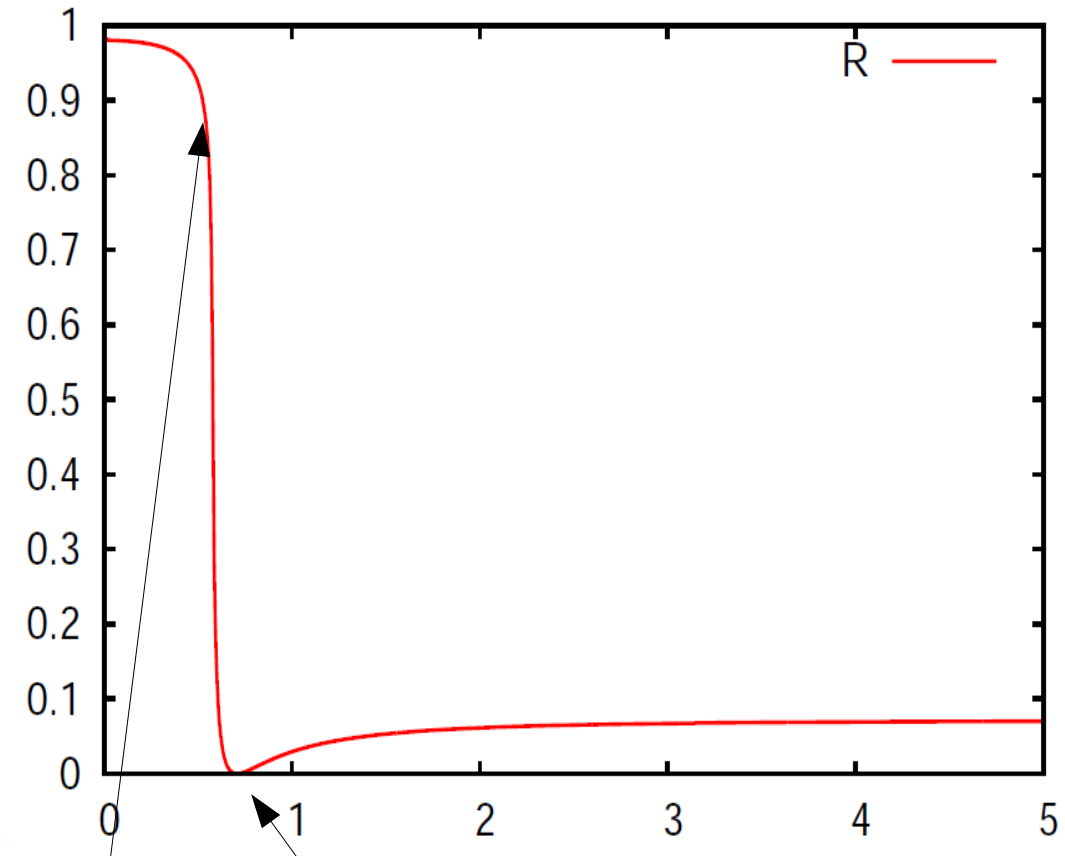
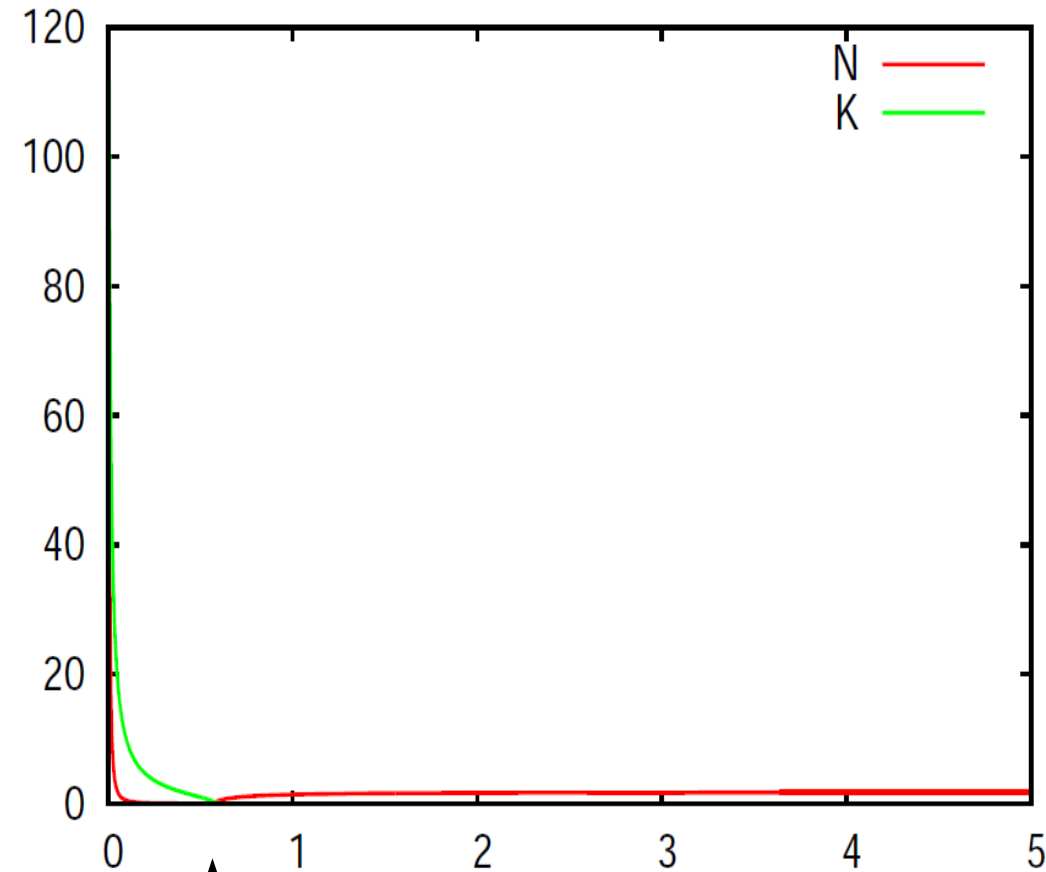
$$\epsilon_{\text{inf}}=3.0, \gamma=0.01, \omega_p=1.0$$



Drudeho model

$\epsilon_{\text{inf}}=3.0, \gamma=0.01, \omega_{\text{p}}=1.0$

$\epsilon_{\text{inf}}=3.0, \gamma=0.01, \omega_{\text{p}}=1.0$



$\omega_{\text{p}}/\sqrt{\epsilon_{\text{inf}}}$

$\omega_{\text{p}}/\sqrt{\epsilon_{\text{inf}}}$
 $\epsilon_1=0$

$\omega_{\text{p}}/\sqrt{\epsilon_{\text{inf}}}-1$
 $\epsilon_1=1$

Drudeho model

- ϵ real and > 0 . For ω real, K is real and a transverse electromagnetic wave propagates with the phase velocity $c/\epsilon^{1/2}$.
- ϵ real and < 0 . For ω real, K is imaginary and the wave is damped with a characteristic length $1/|K|$.
- ϵ complex. For ω real, K is complex and the waves are damped in space.
- $\epsilon = \infty$. This means the system has a finite response in the absence of an applied force; thus the poles of $\epsilon(\omega, K)$ define the frequencies of the free oscillations of the medium.
- $\epsilon = 0$. We shall see that longitudinally polarized waves are possible only at the zeros of ϵ .

(CGS)

$$\epsilon(\omega)\omega^2 = \epsilon(\infty)(\omega^2 - \tilde{\omega}_p^2)$$

(CGS)

$$\omega^2 = \tilde{\omega}_p^2 + c^2 K^2 / \epsilon(\infty)$$

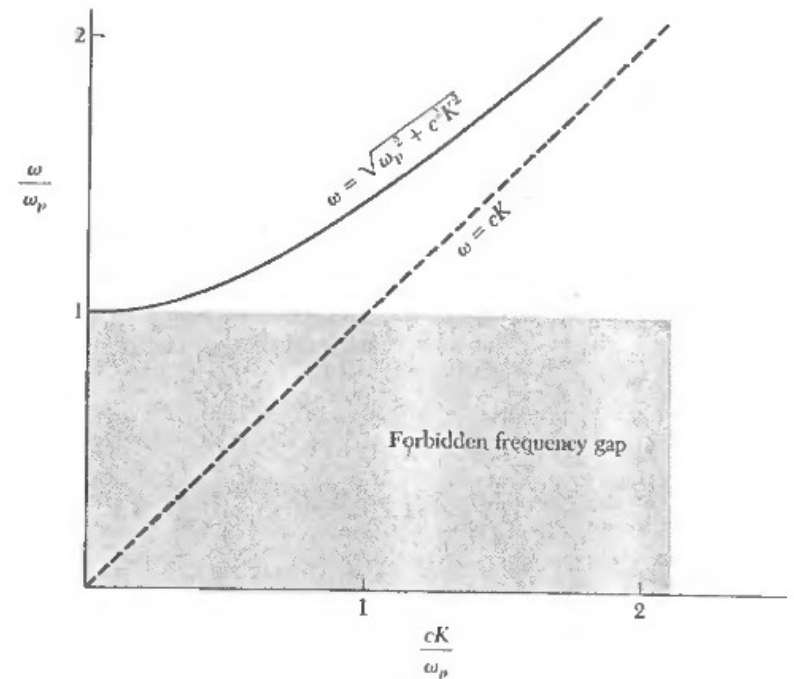


Figure 2 Dispersion relation for transverse electromagnetic waves in a plasma. The group velocity $v_g = d\omega/dK$ is the slope of the dispersion curve. Although the dielectric function is between zero and one, the group velocity is less than the velocity of light in vacuum.

Drudeho model

	$\hbar\omega$ (eV), $\varepsilon_1=0$
Al	11
Au	5.5
Ir	7.8
Mo	1.5
Ni	9.4
Ag	3.8
W	1.3

Drudeho parametry čistých kovů

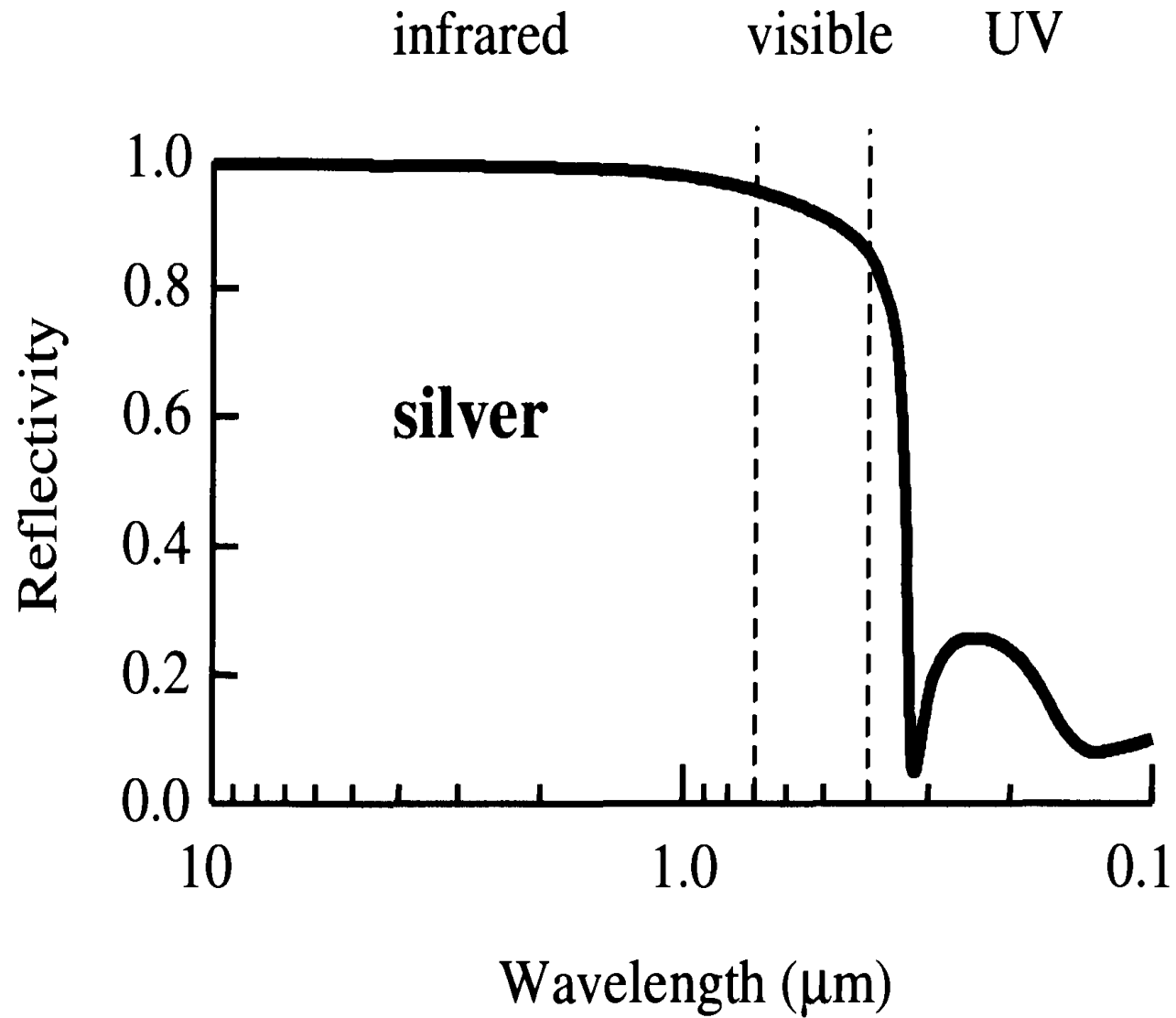
	$\hbar\omega_p$ (eV)	τ (10^{-14} s)	\hbar/τ (eV)
Al	7.5 – 13	0.3 – 2.1	1.4 – 0.2
Au	6.9 – 10.5	0.4 – 4.3	1 – 0.1
Ni	3.6 – 4.8	0.2 – 2.2	2.1 – 0.19
Ag	7.8 – 9.8	0.9 – 2.6	0.46 – 0.16

Drudeho parametry čistých kovů

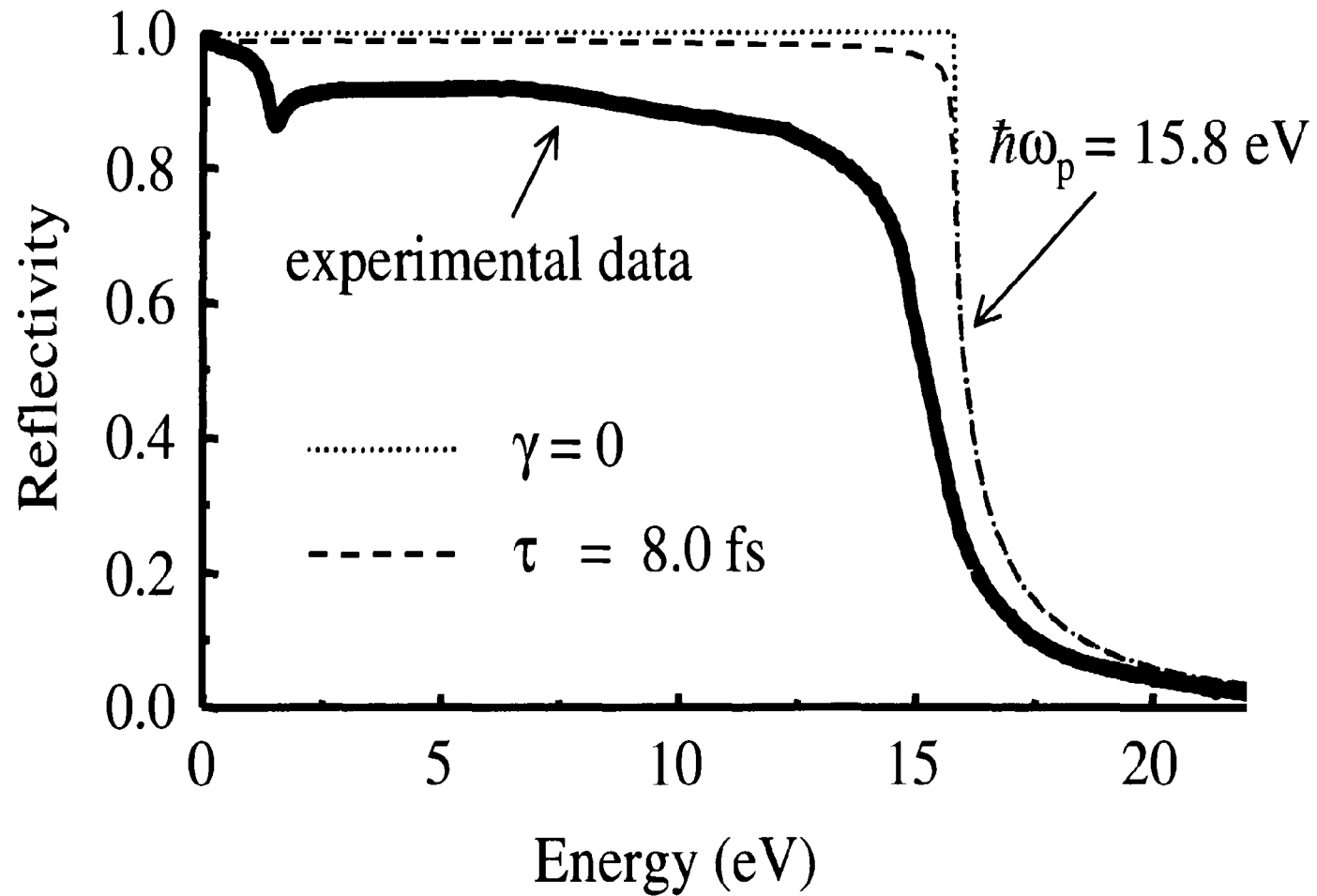
The plasma frequency ω_p is calculated from eqn 1.5, and λ_p is the wavelength corresponding frequency.

Metal	Valency	N (10^{28} m^{-3})	$\omega_p/2\pi$ (10^{15} Hz)	λ_p (nm)
Li (77 K)	1	4.70	1.95	154
Na (5 K)	1	2.65	1.46	205
K (5 K)	1	1.40	1.06	282
Rb (5 K)	1	1.15	0.96	312
Cs (5 K)	1	0.91	0.86	350
Cu	1	8.47	2.61	115
Ag	1	5.86	2.17	138
Au	1	5.90	2.18	138
Be	2	24.7	4.46	67
Mg	2	8.61	2.63	114
Ca	2	4.61	1.93	156
Al	3	18.1	3.82	79

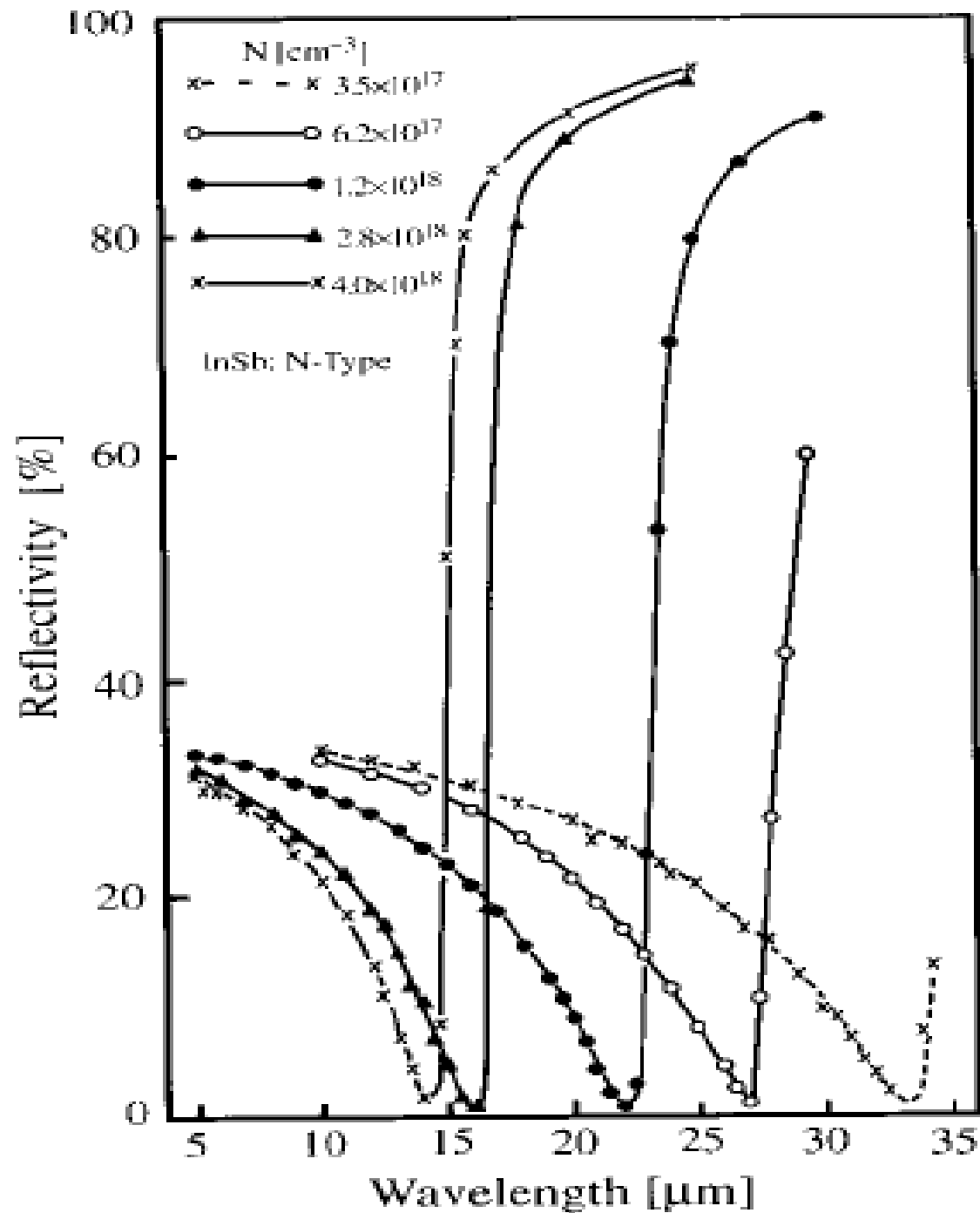
Odrazivost stříbra



Al



Dopovaný polovodič InSb



Yu, Cardona,
Fundamentals of
semiconductors,
Springer 1996.

Index lomua absorpce Al, odrazivost

390 D. Y. Smith, E. Shiles, and Mitio Inokuti

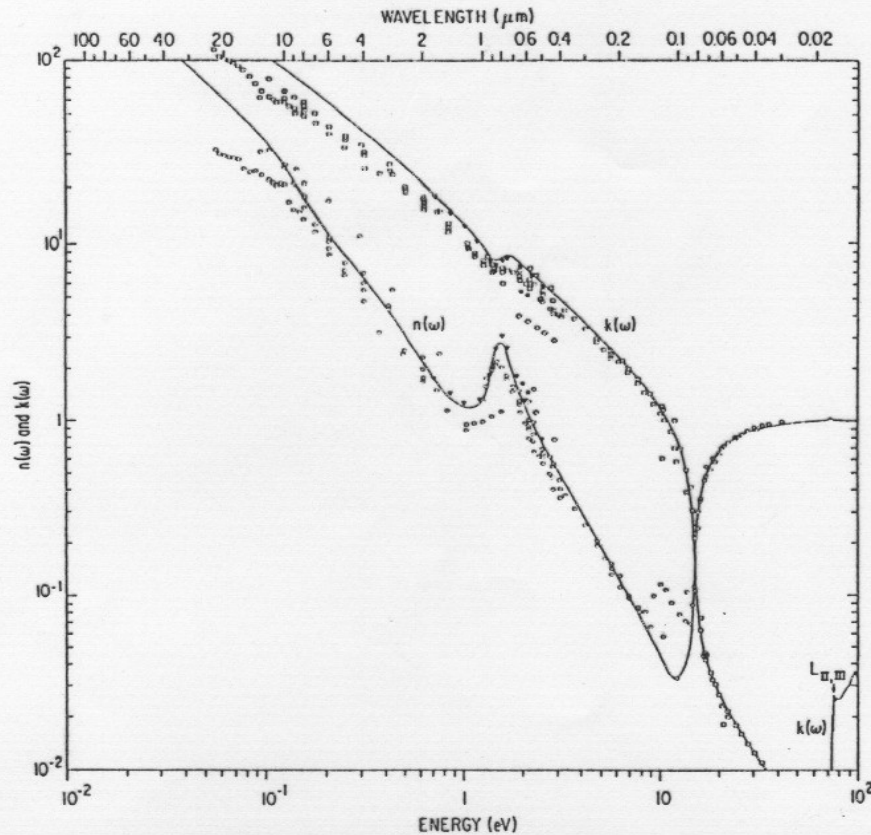


Fig. 14. The complex refractive index $n(\omega) + ik(\omega)$ for aluminum. The curves are taken from Shiles *et al.*'s [7] analysis of uhv reflectance data. A portion of the uhv ellipsometric data of Mathewson and Myers [100] is given for comparison. Quincke's [33] and Drude's [34] results for polished bulk samples are shown for historical interest; considering the materials and techniques available, these early measurements are remarkably good, especially for $n(\omega)$. The remainder of the data points are given to show the range of values of $n(\omega)$ ($^{\circ}$) and $k(\omega)$ ($^{\circ}$) reported in the literature. Most refer to evaporated films prepared in conventional or high vacuum and measured by using polarimetric, interferometric, and like methods. The sources of these data are given in the references [10, 11, 25, 26, 27, 51, 55, 56, 65, 66, 73, 75, 91, and 121-129]. Note that the curves for $n(\omega)$ and $k(\omega)$ curve cross each other at roughly 15 eV, the plasmon energy. This corresponds to the plasmon condition $\epsilon_1(\omega_p) = n^2(\omega_p) - k^2(\omega_p) \approx 0$. The onset of the L-shell absorption appears in the lower-right-hand corner. The corresponding dispersion

Quincke [33]. \odot : Drude [34], \ast .)

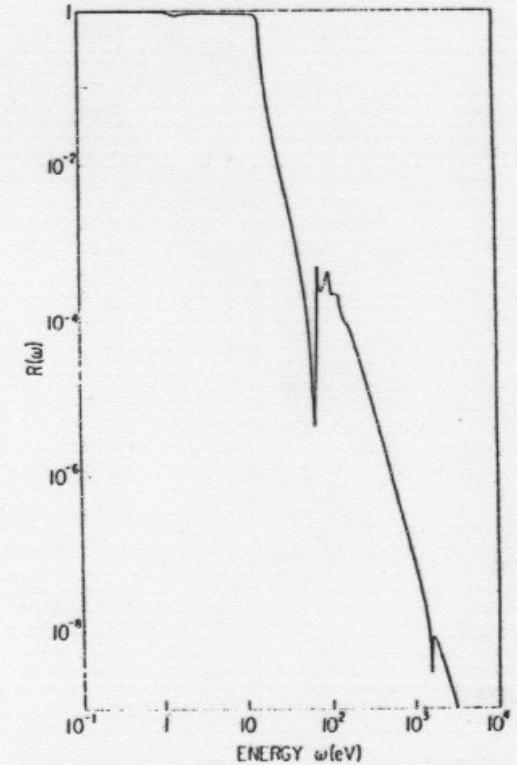
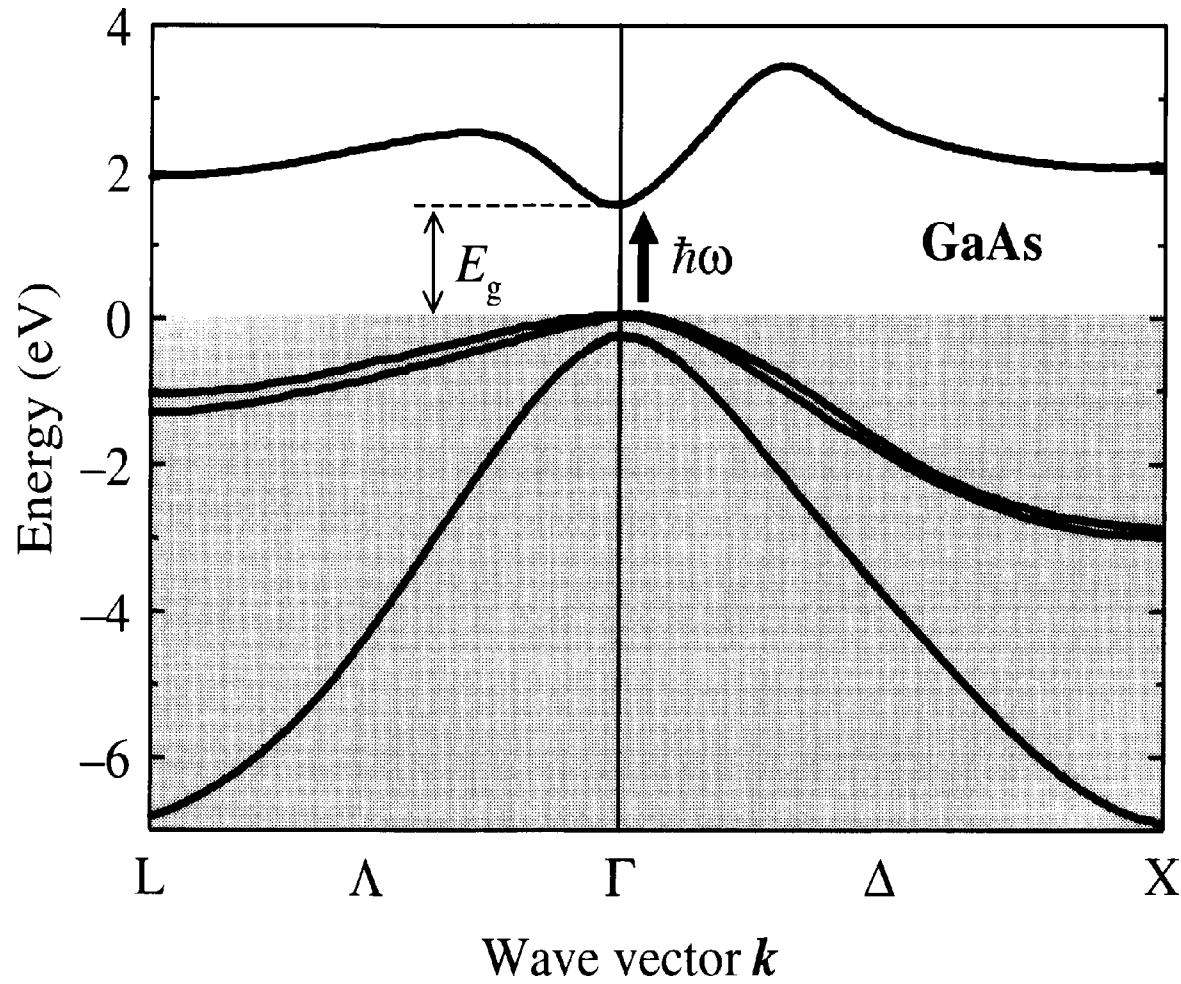
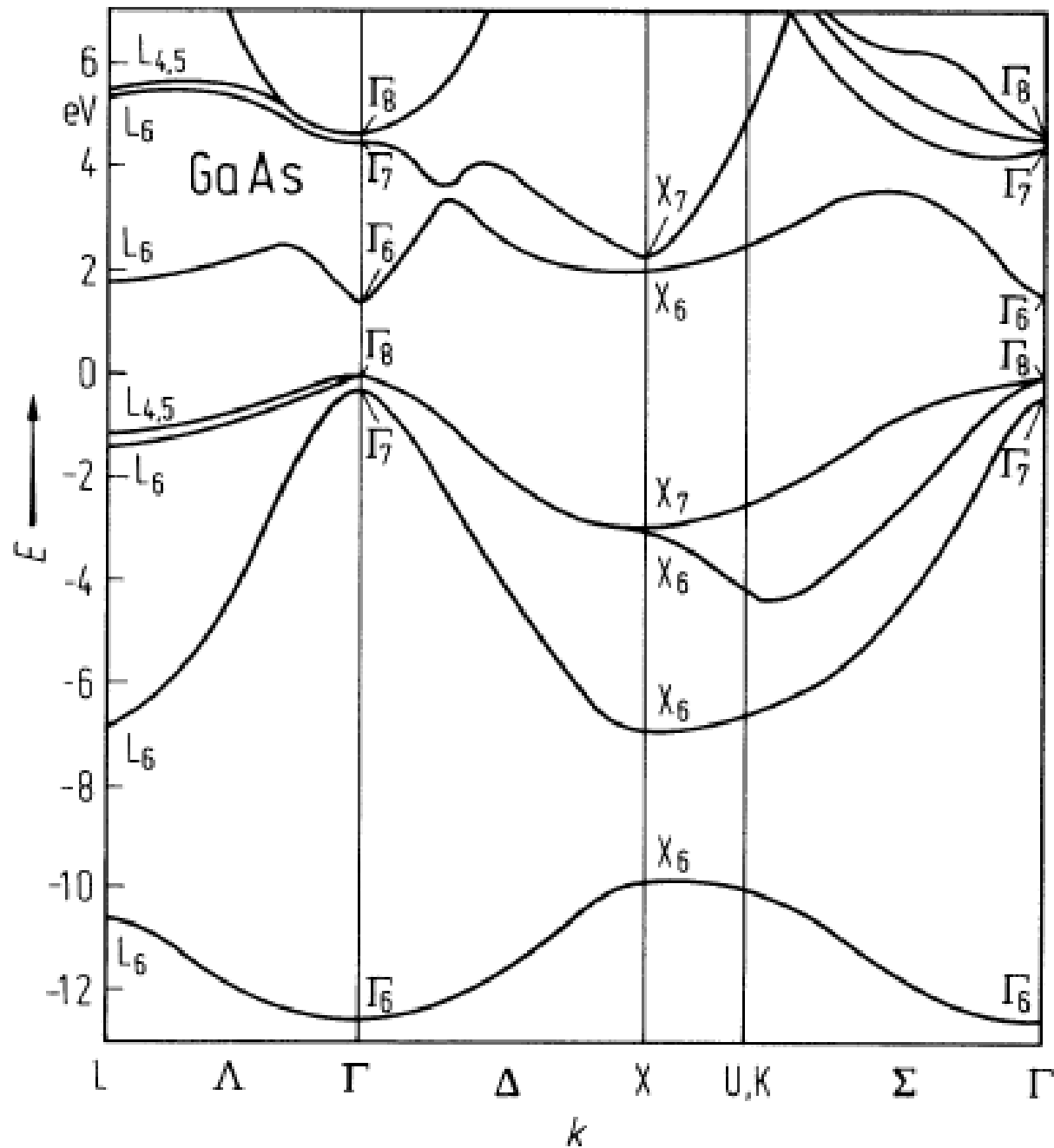


Fig. 15. The reflectance $R(\omega)$ at normal incidence of a smooth oxide-free metal surface in vacuum. (After Shiles *et al.* [7].)

GaAs



GaAs, pásová struktura



GaAs – dielektrická funkce

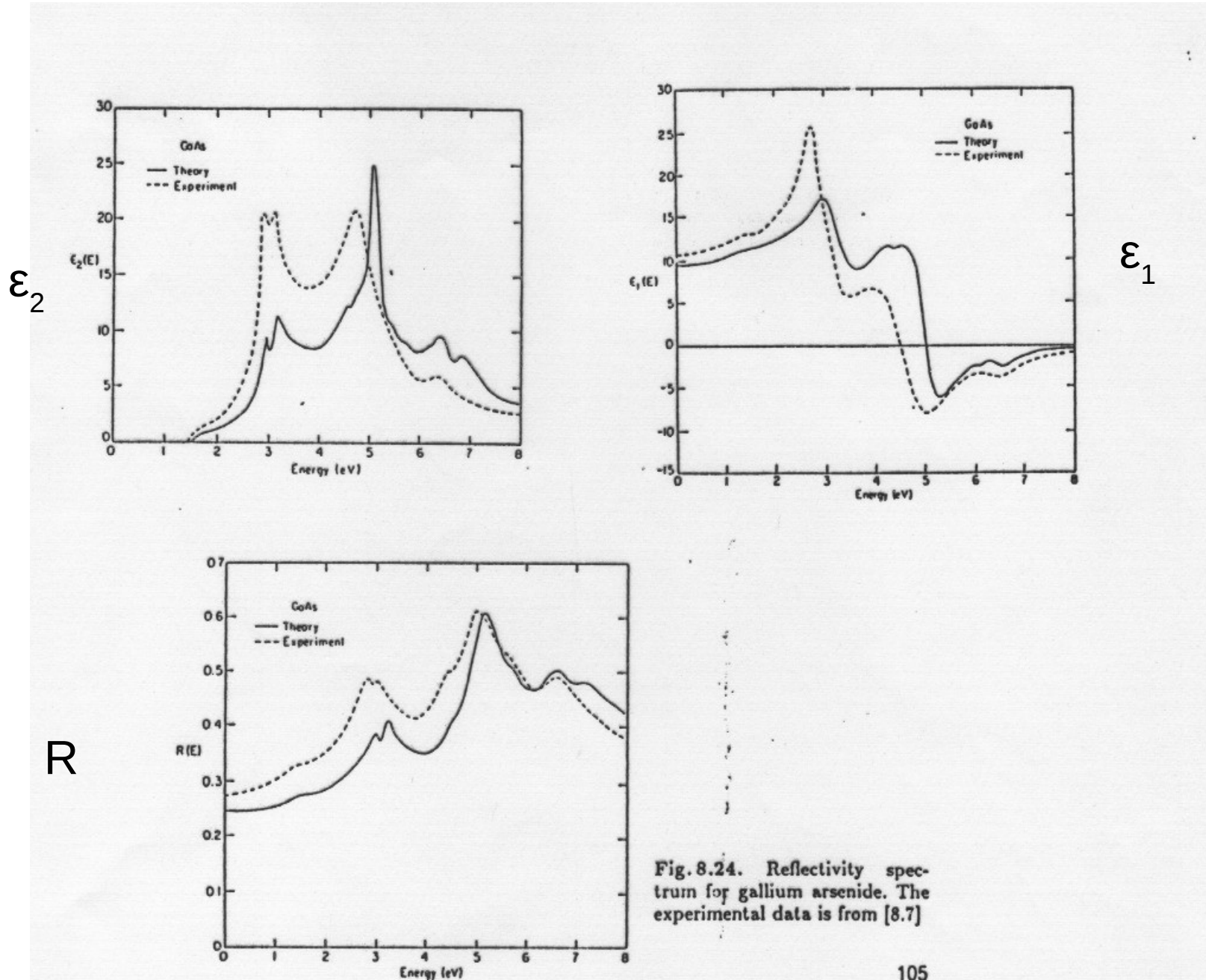
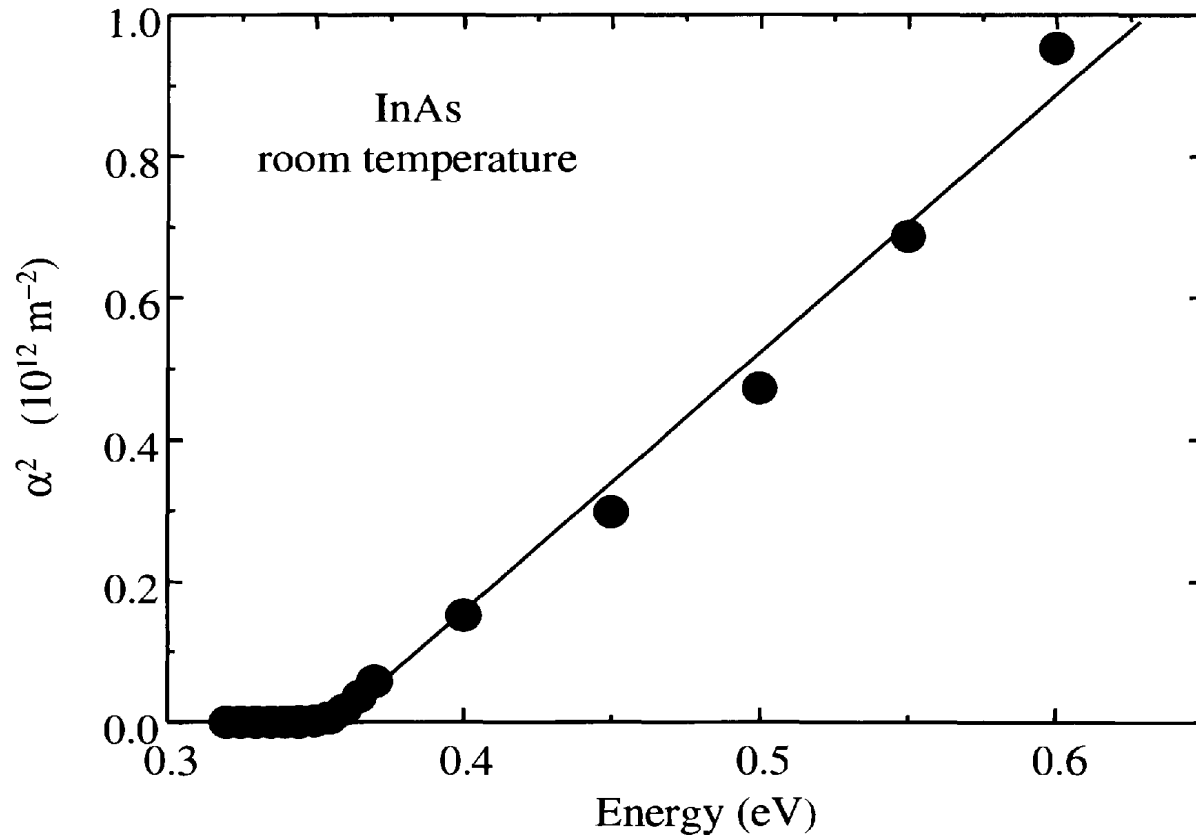


Fig. 8.24. Reflectivity spectrum for gallium arsenide. The experimental data is from [8.7]

InAs



states given by eqn 3.24. We therefore expect the following behaviour $\hbar\omega$):

$$\text{For } \hbar\omega < E_g, \quad \alpha(\hbar\omega) = 0.$$

$$\text{For } \hbar\omega \geq E_g, \quad \alpha(\hbar\omega) \propto (\hbar\omega - E_g)^{\frac{1}{2}}. \quad (3)$$

InSb

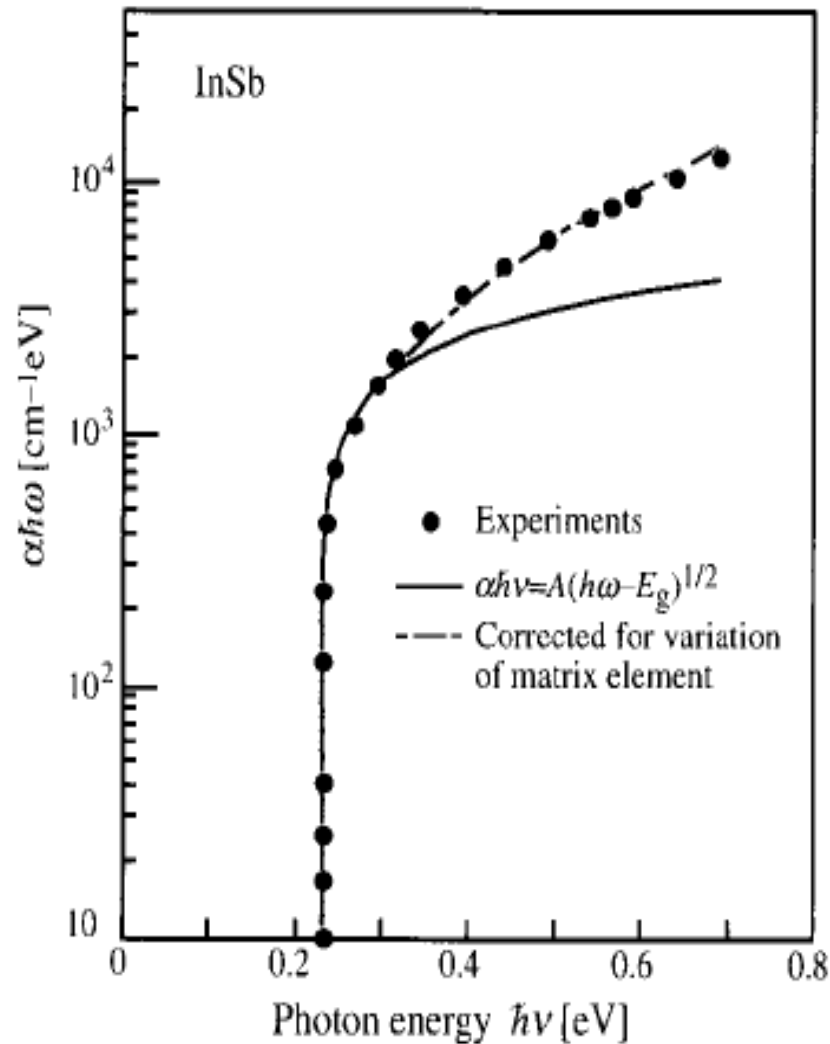
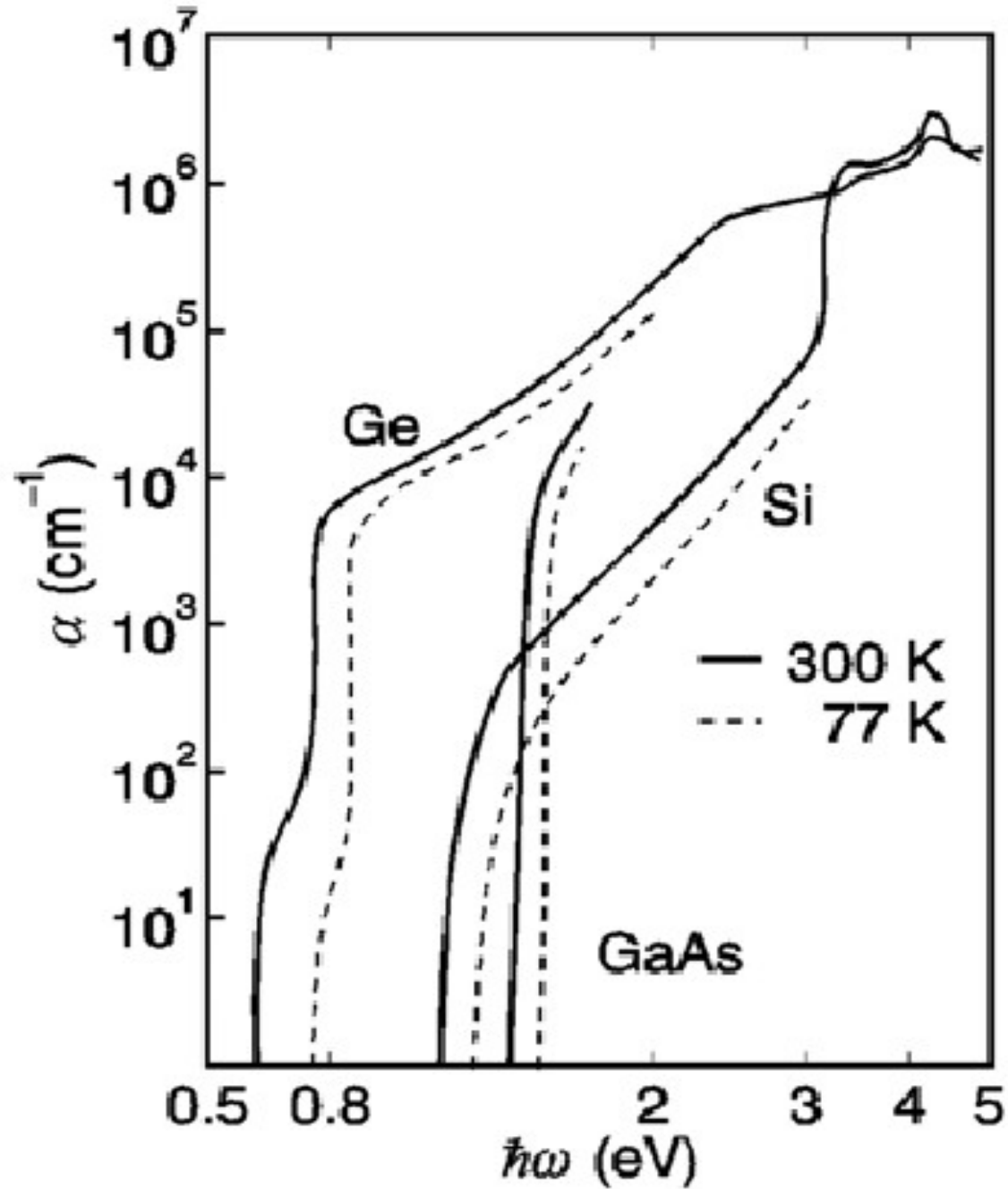


Fig. 6.15. Semilogarithmic plot of the absorption coefficient of InSb at 5 K as a function of photon energy. The *filled circles* represent experimental results from [6.24]. The *curves* have been calculated using various models. The intercept with the *x*-axis gives the direct bandgap of InSb [6.25]

GaAs, Ge a Si



Si

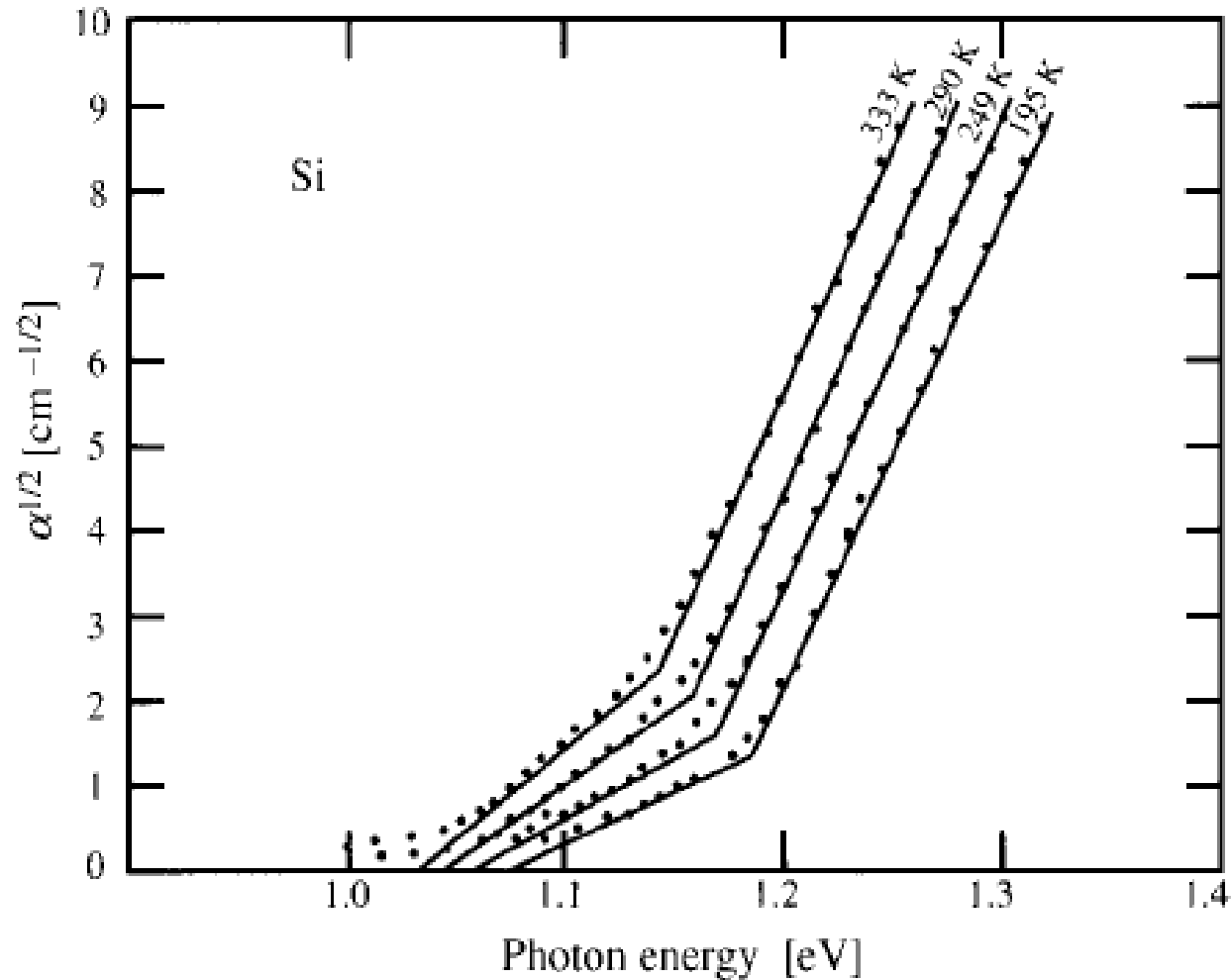
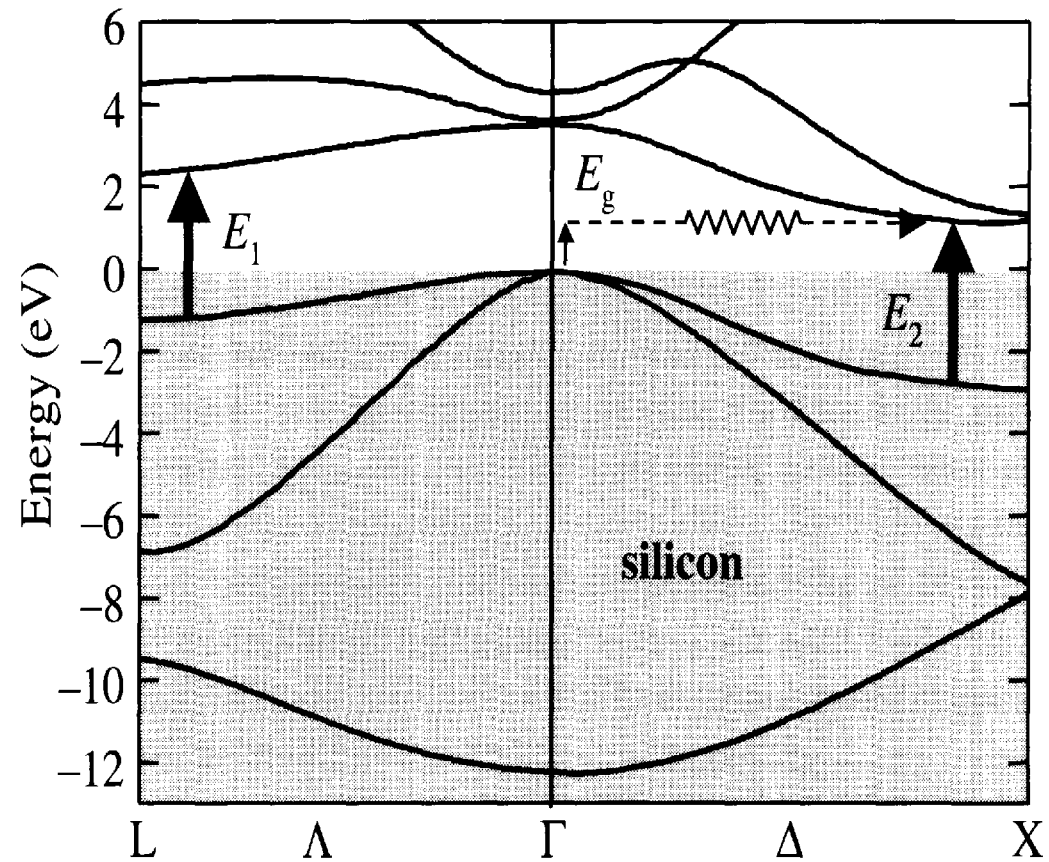
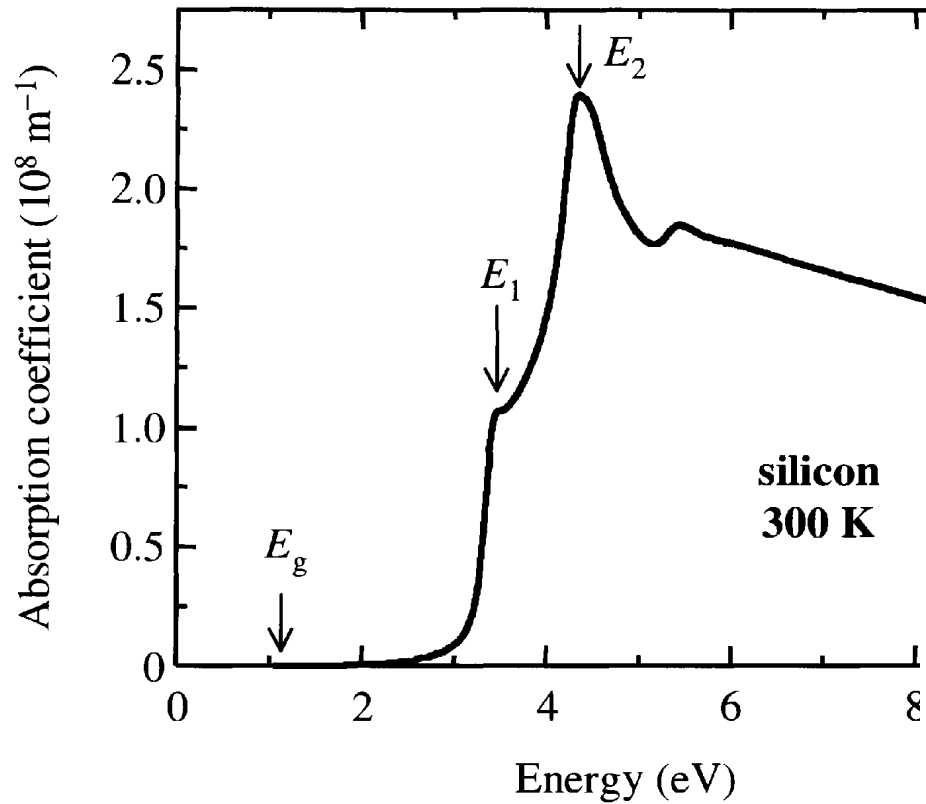
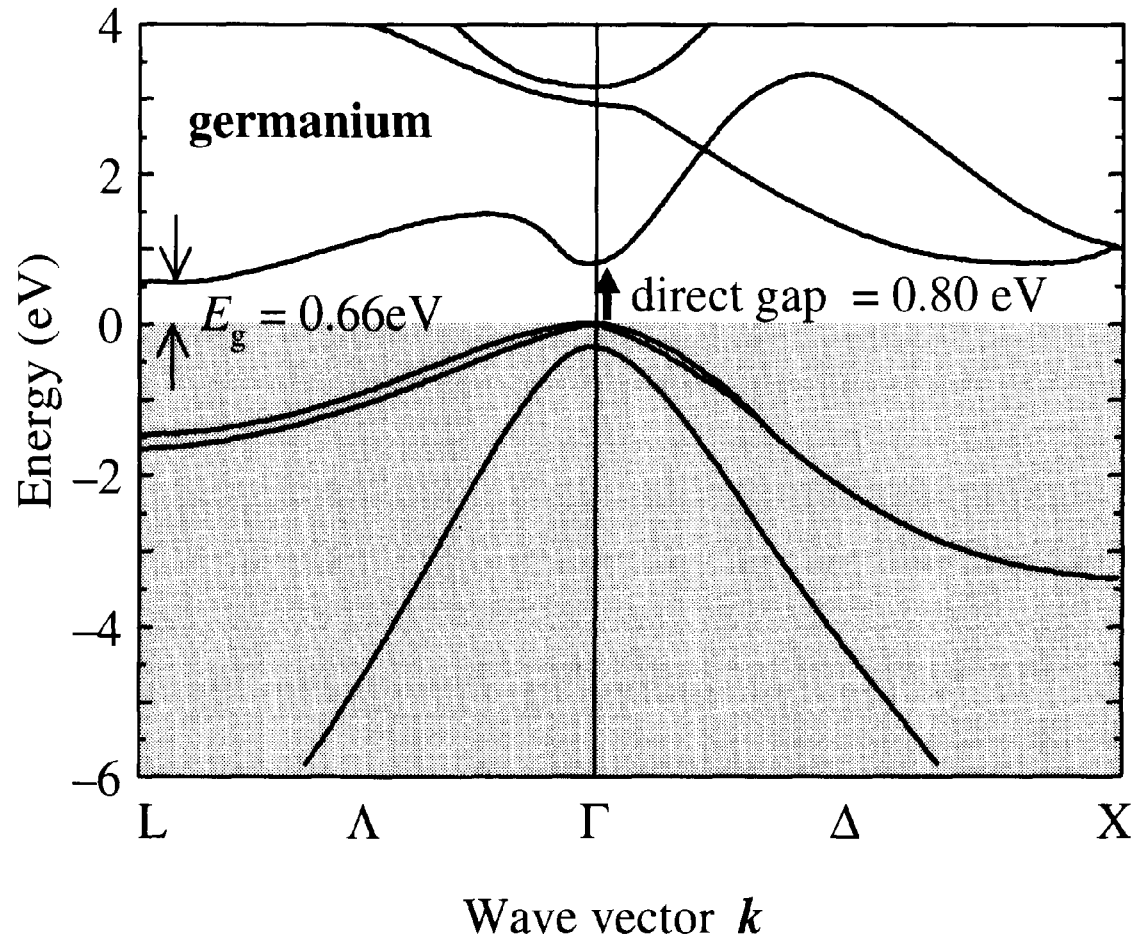


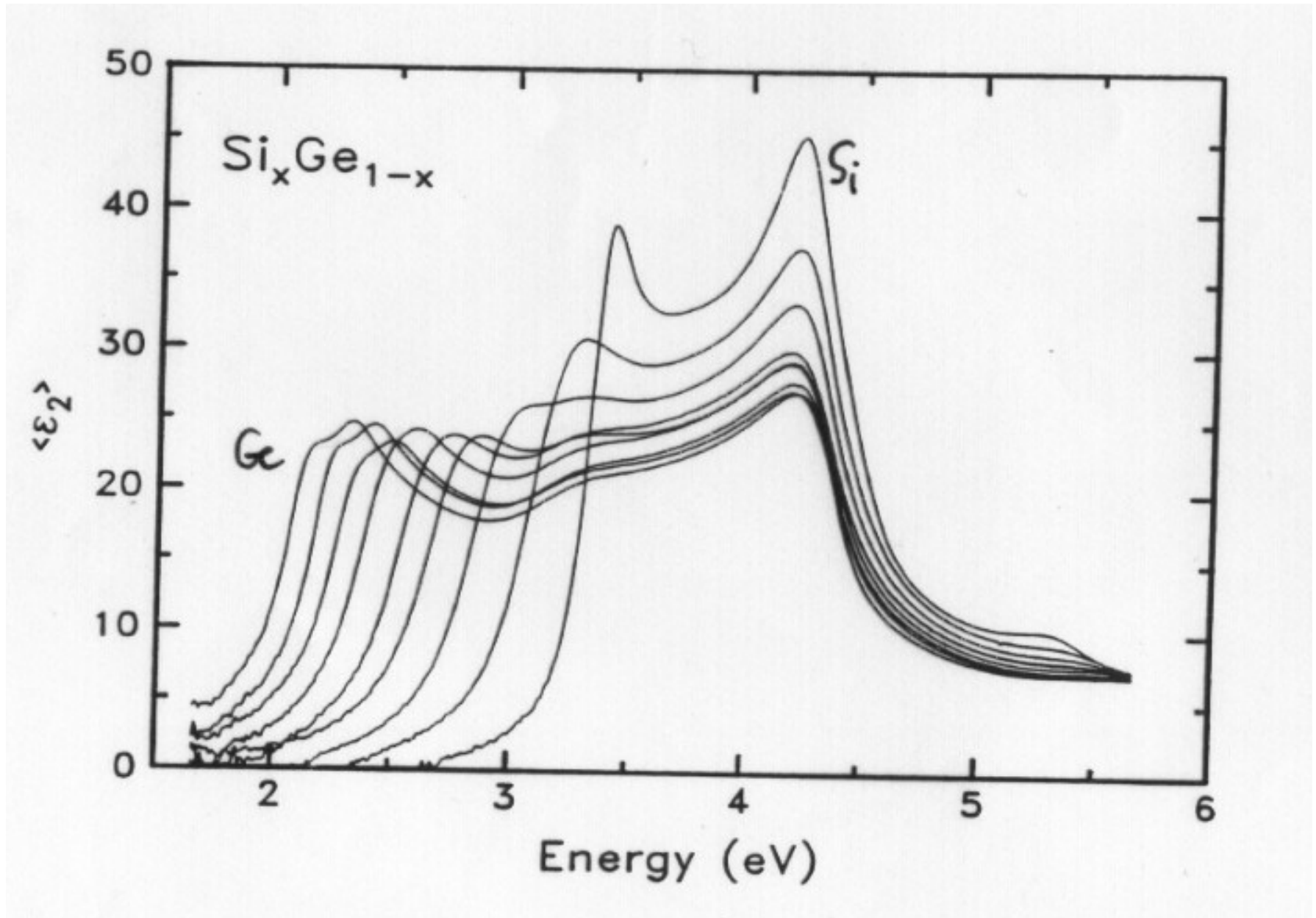
Fig. 6.17. Plots of the square root of the absorption coefficients of Si versus photon energy at several temperatures. The two segments of a straight line drawn through the experimental points represent the two contributions due to phonon absorption and emission [6.26]

Si



Ge





Parametry polovodičů

	a (Å)	E_g (eV)	ϵ_∞
C (diamant)	3.567	5.50	5.7
Si	5.431	1.2	11.6
Ge	5.657	0.7	16.0
α -Sn	6.491	0	

Parametry polovodičů

Table 1.2 Approximate transparency range, band gap wavelength λ_g , and refractive index n of a number of common semiconductors. n is measured at $10 \mu\text{m}$. After [1], [2] and [3].

Crystal	Transparency range (μm)	λ_g (μm)	n
Ge	1.8–23	1.8	4.00
Si	1.2–15	1.1	3.42
GaAs	1.0–20	0.87	3.16
CdTe	0.9–14	0.83	2.67
CdSe	0.75–24	0.71	2.50
ZnSe	0.45–20	0.44	2.41
ZnS	0.4–14	0.33	2.20

Amorfní polovodiče

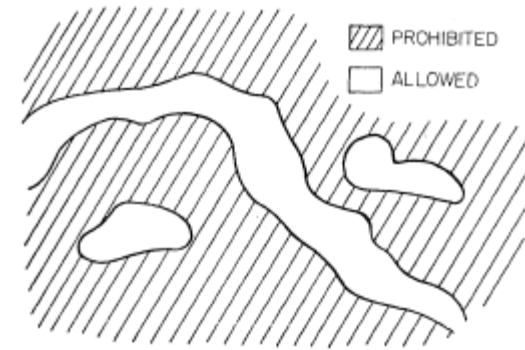
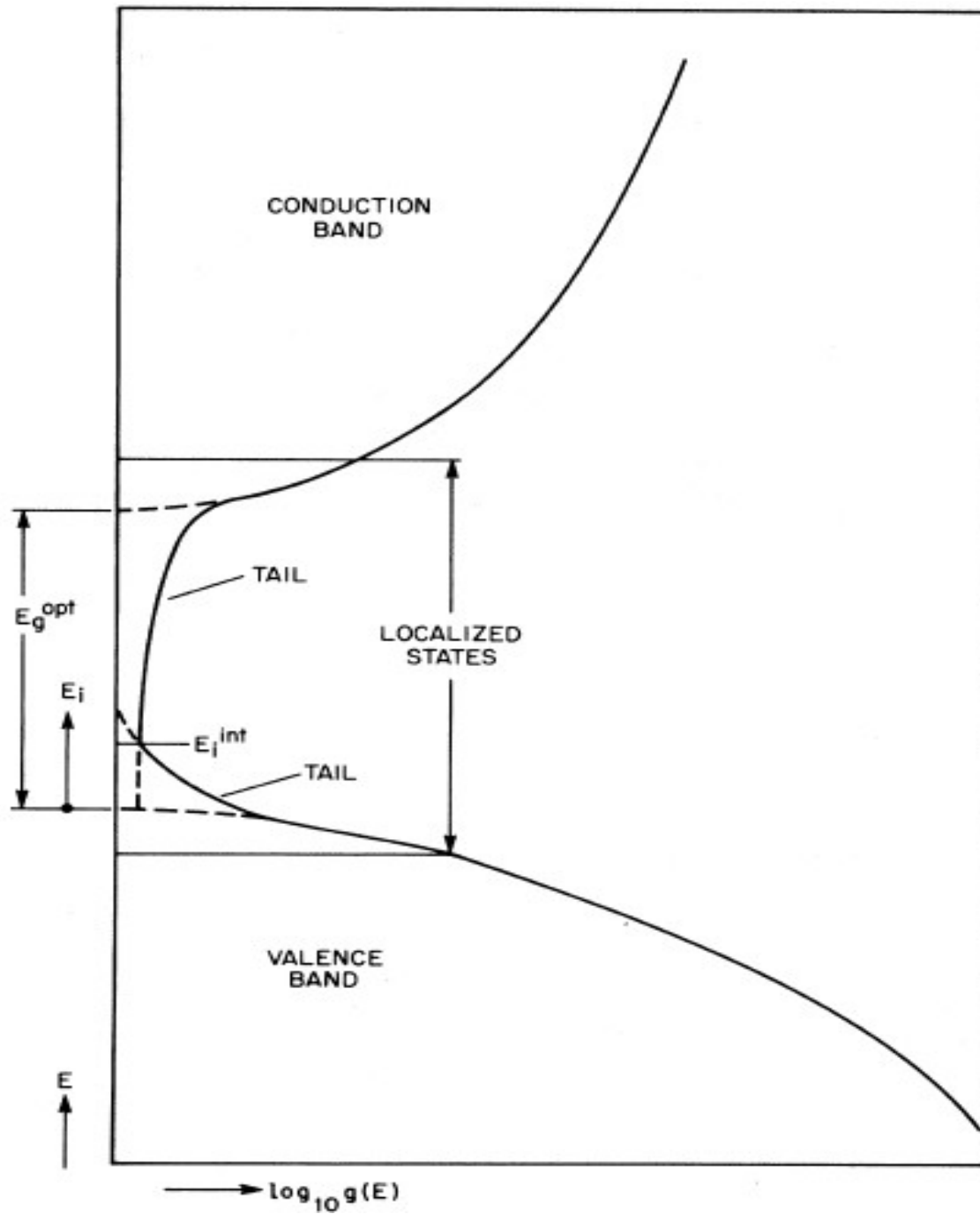
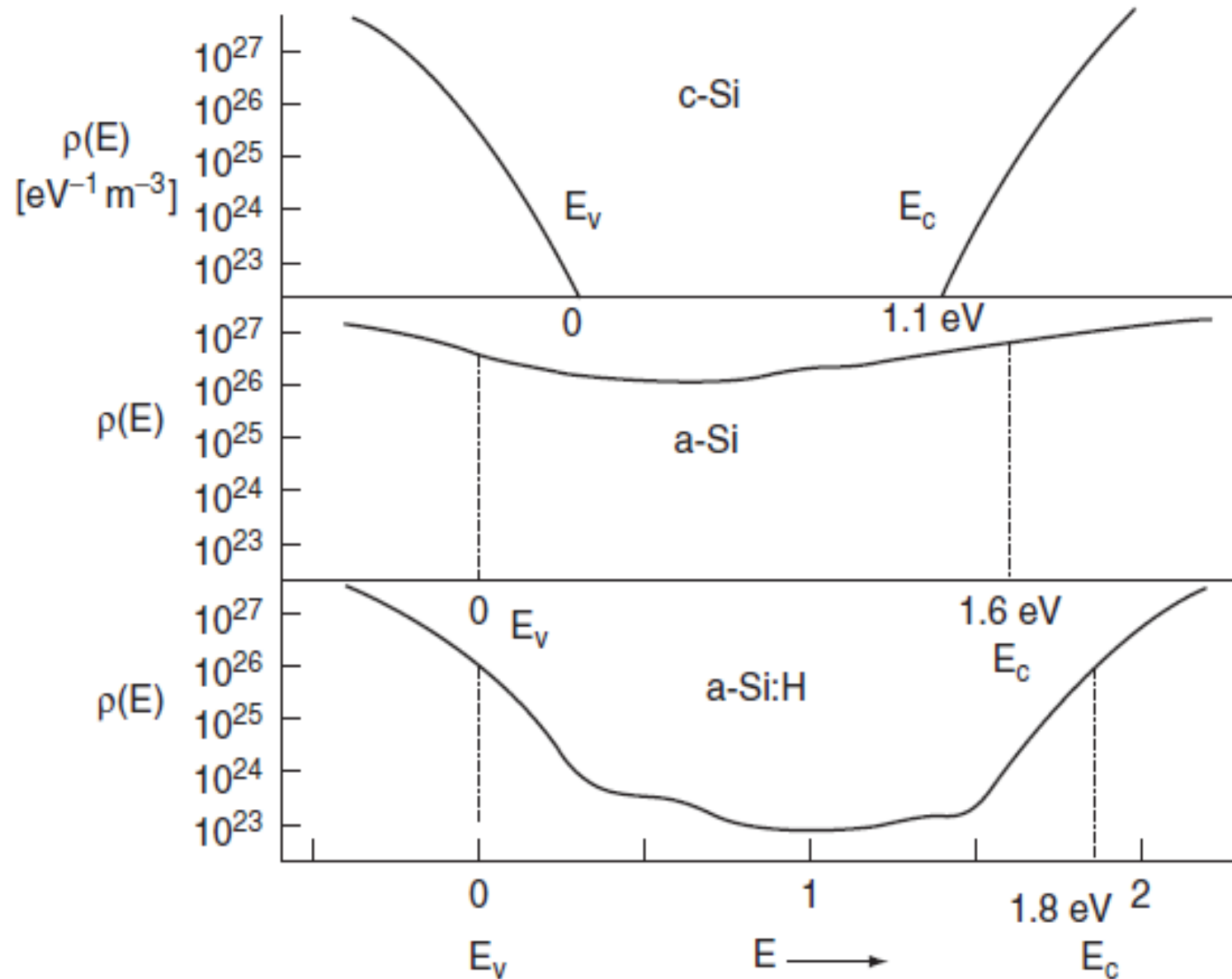
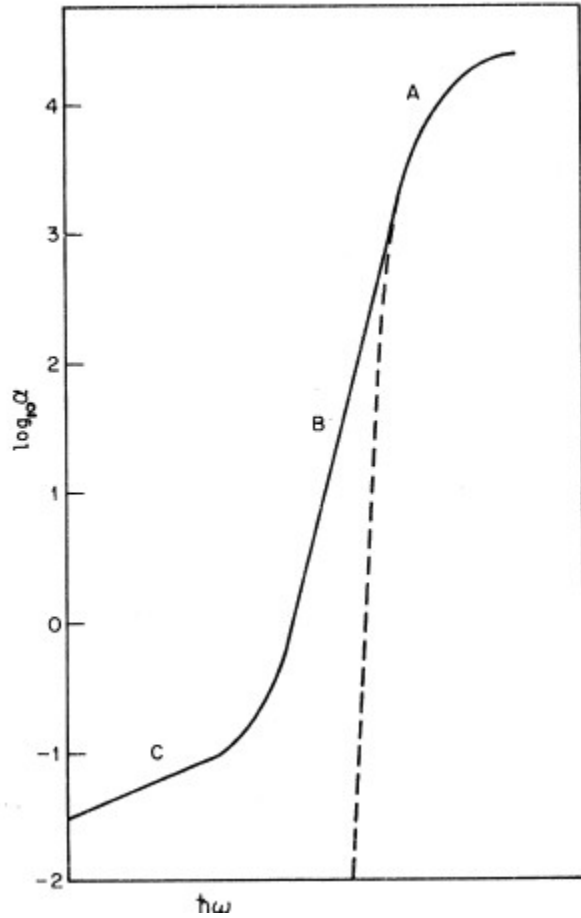


FIG. 5. Regions of allowed and prohibited states in an amorphous semiconductors just above the mobility edge.

Amorfní polovodiče – hustota stavů



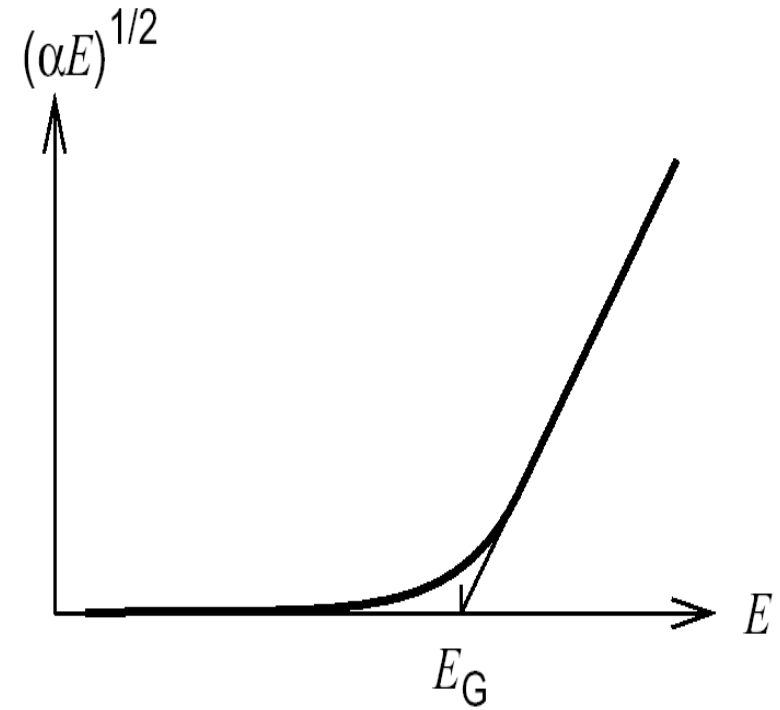
Amorfní polovodiče



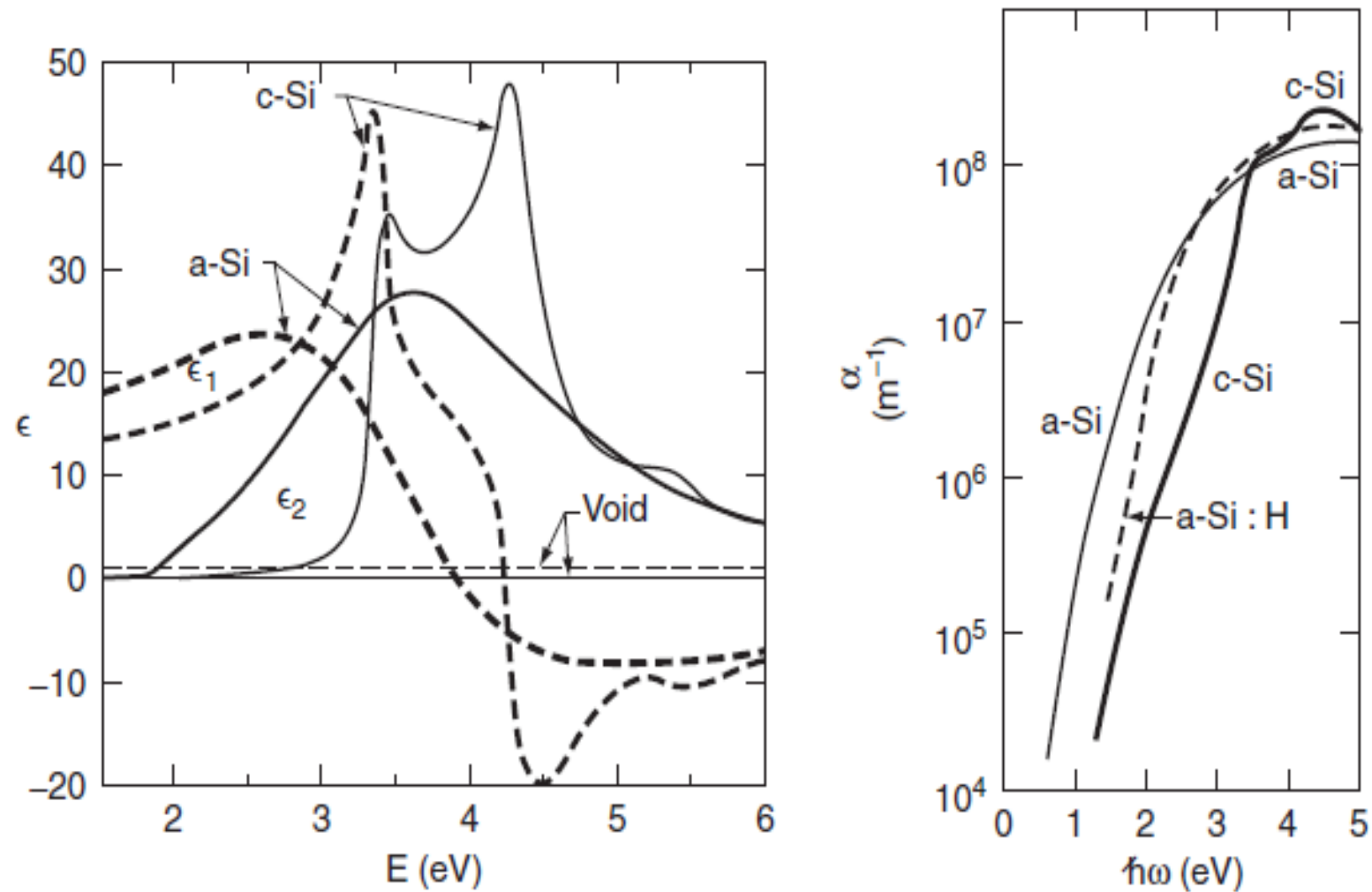
Region A:
 $\alpha \hbar\omega = B (\hbar\omega - E_g)^2$
Taucův gap

Region B:
 $\alpha(\hbar\omega) \sim \exp(\hbar\omega/E_G)$
Urbachova energie

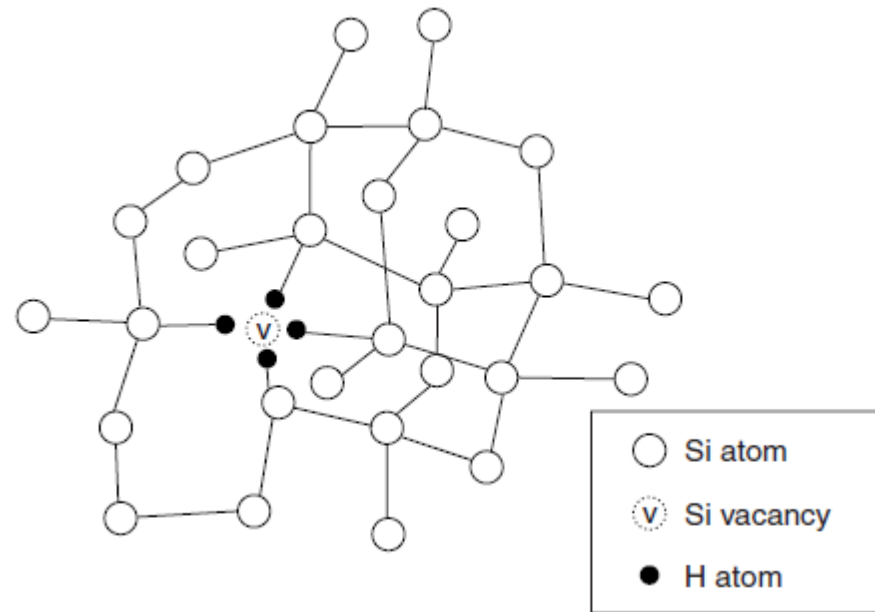
Region C:
 $\alpha(\hbar\omega) \sim \exp(\hbar\omega/E_d)$,
defekty



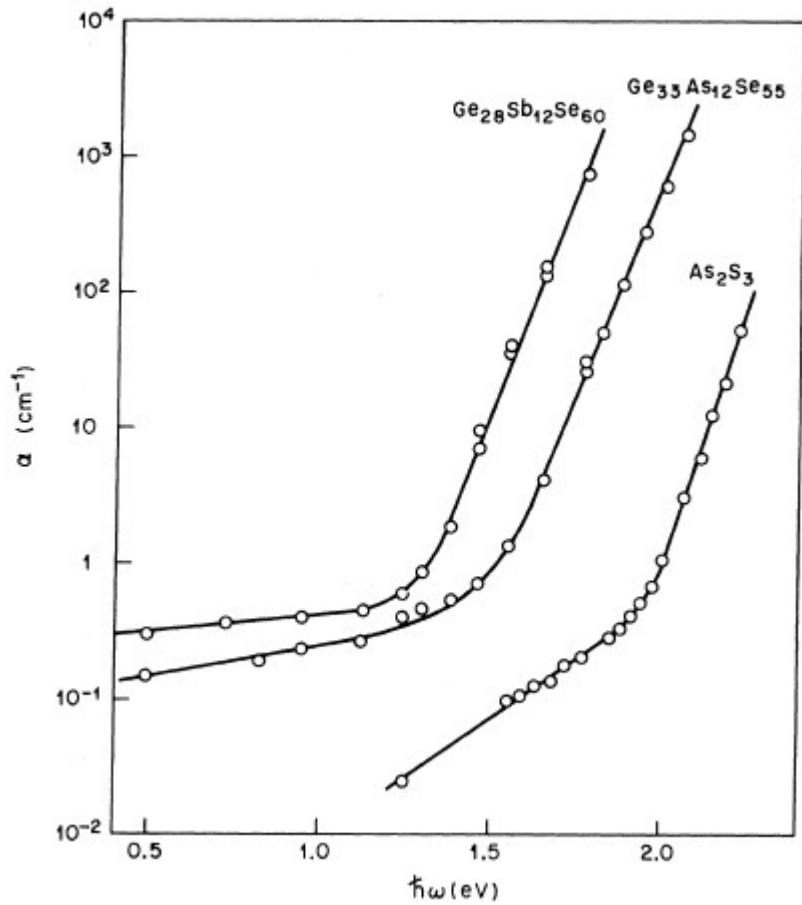
Amorfní křemík – dielektrická funkce



Amorfní polovodiče



Amorfní polovodiče



Chalkogenidová skla
Tauc 1972

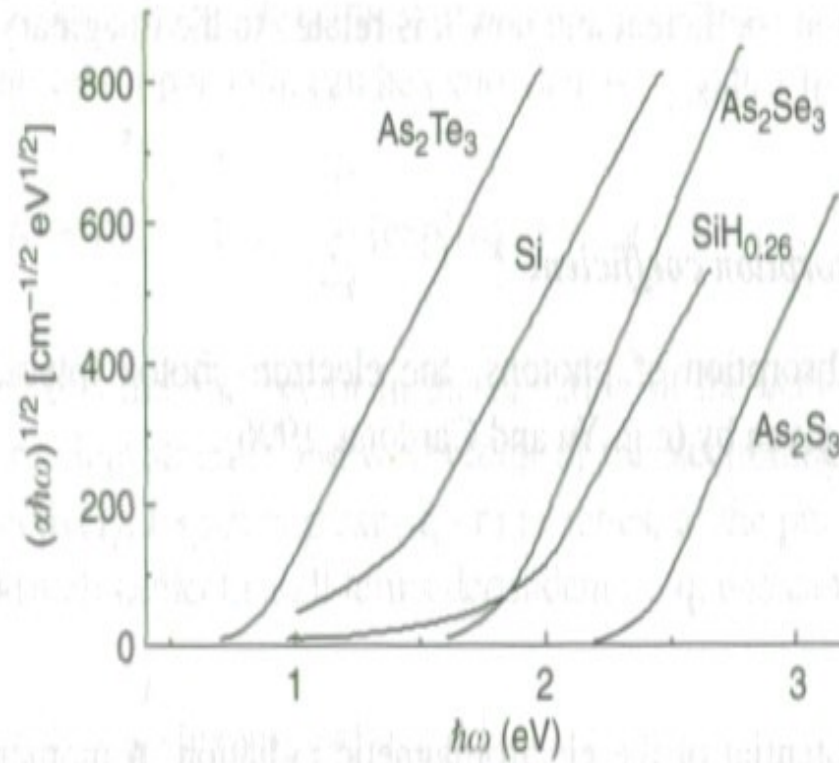


Figure 4.5 Tauc plots for different a-semiconductors (Morigaki, 1999).

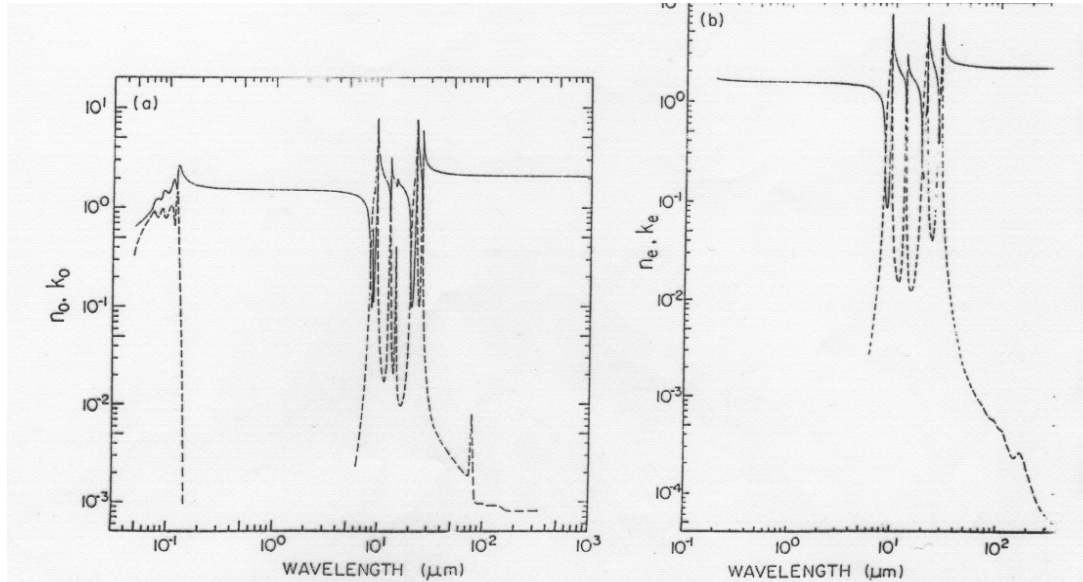


Fig. 9. (a) Log-log plot of n_0 (—) and (---) k_0 versus wavelength in micrometers for silicon dioxide (type z, crystalline). (b) Log-log plot of n_e (—) and (---) k_e versus wavelength in micrometers for silicon dioxide (type z, crystalline).

krystalický

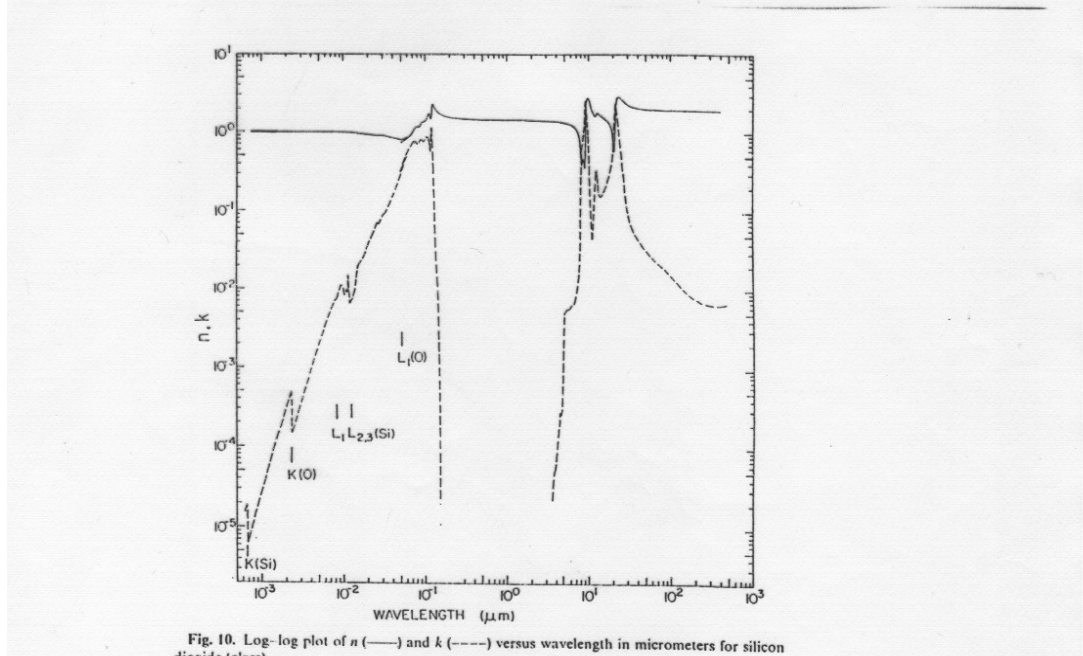


Fig. 10. Log-log plot of n (—) and k (---) versus wavelength in micrometers for silicon dioxide (amorphous).

amorfní

SiO₂, GeO₂

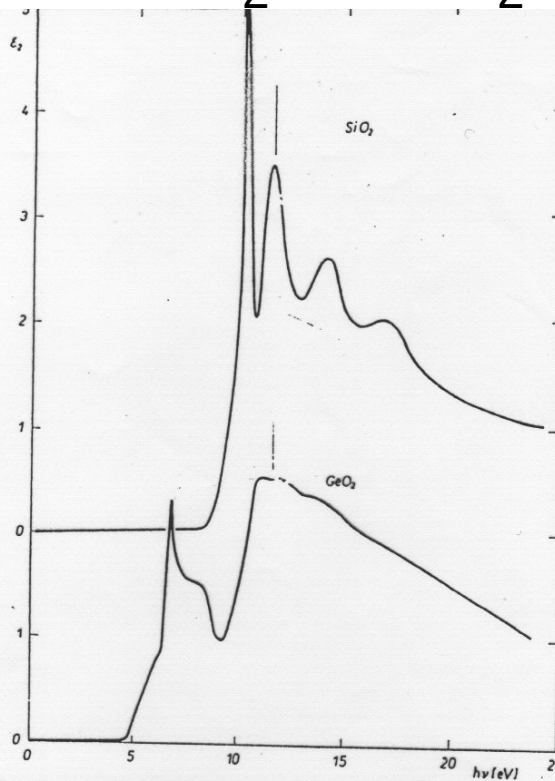


FIG. 18. Comparison of the fundamental optical spectra of g-SiO₂ and g-GeO₂ (from Ref. 51).

SiO₂

GeO₂

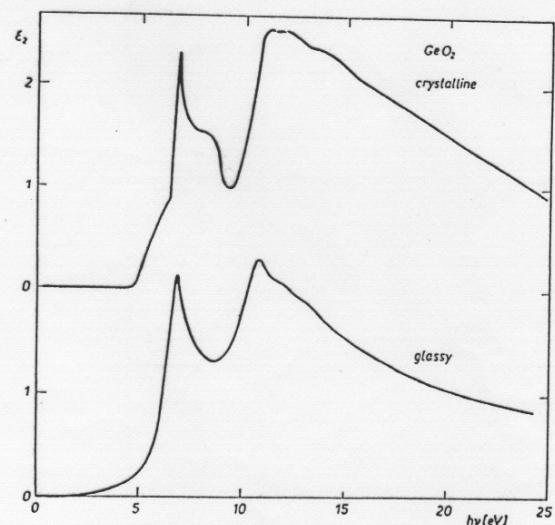
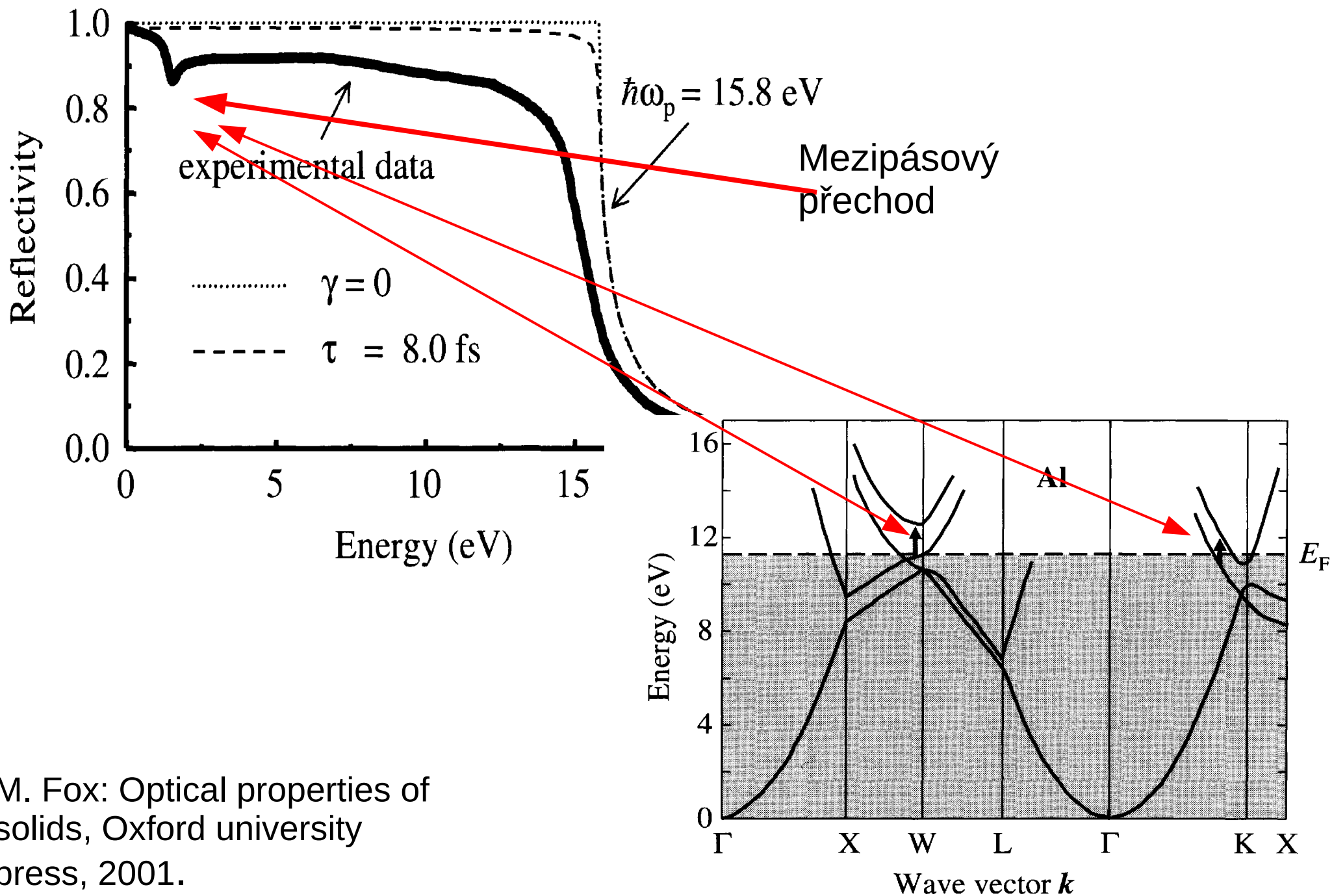


FIG. 19. Comparison of the fundamental optical spectra of c- and g-GeO₂. Note that c-GeO₂ is not only polycrystalline but also probably microcrystalline and contains "a few percent H₂O"; that is, the microcrystalline diameters are probably ≈ 100 Å (i.e., the same scale as observed by Zarzycki⁴⁹) (from Ref. 51).

Krystalický
a amorfní GeO₂

Palik, Handbook of
Optical Constants of
Solids, Elsevier 1998.

Mezipásový přechod v kovech – hliník



M. Fox: Optical properties of solids, Oxford university press, 2001.

Mezipásové přechody v kovech – měď

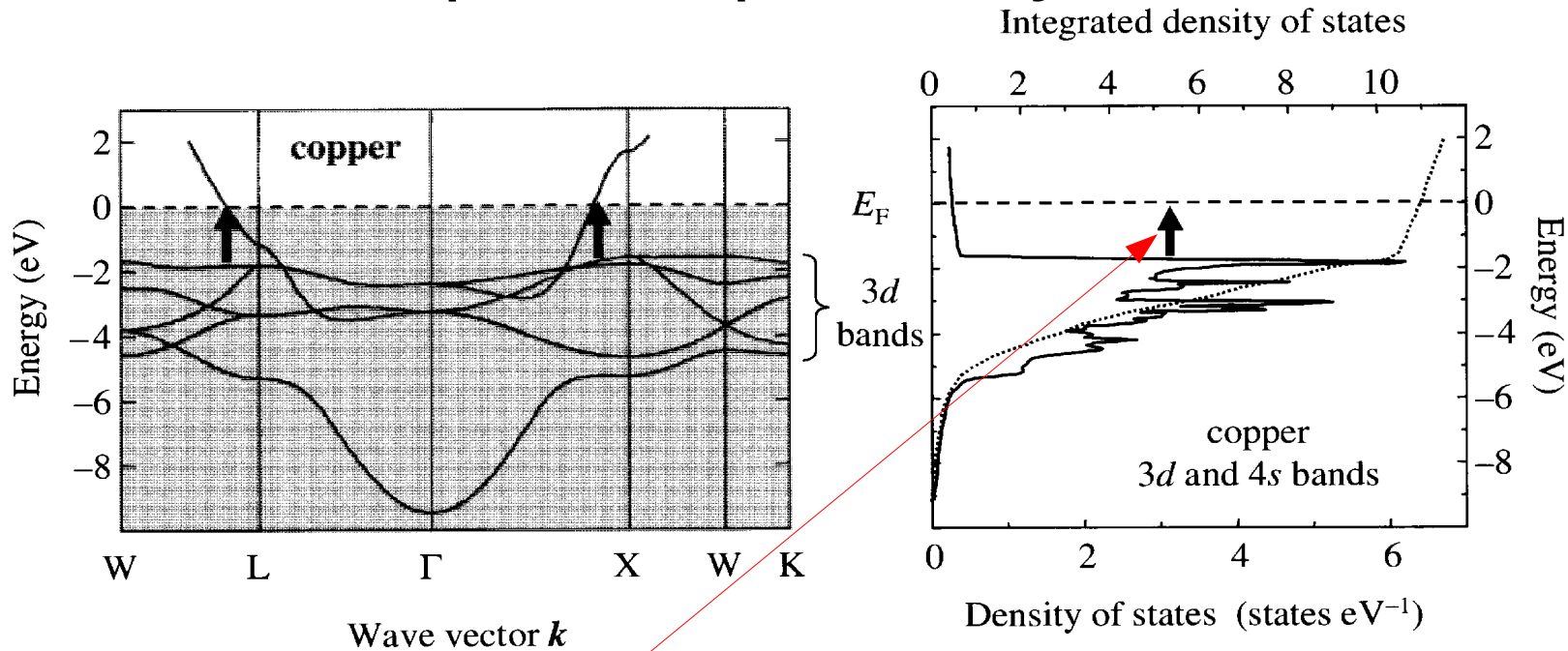


Fig. 7.5 Calculated band structure of copper. The transitions from the 3d bands responsible for the interband transitions around 2 eV are identified. The right hand side of the figure shows the density of states calculated from the band structure. The strongly peaked features between about -2 eV and -5 eV are due to the 3d bands. The dotted line is the integrated density of states. The Fermi level corresponds to the energy where the integrated density of states is equal to 11. After [5].

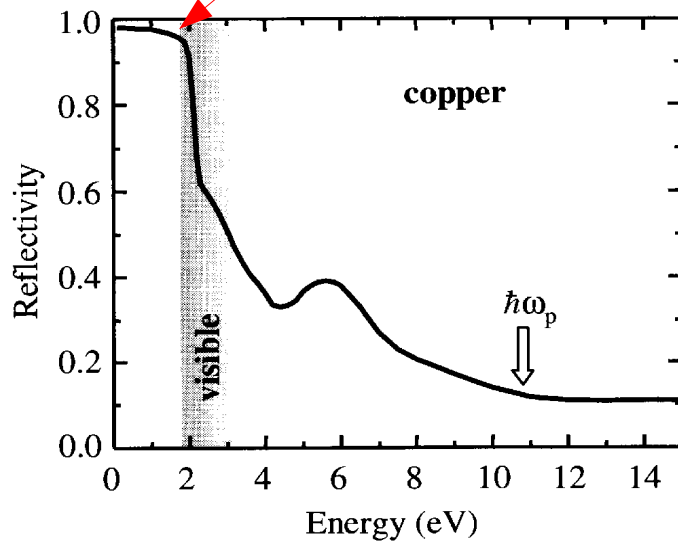
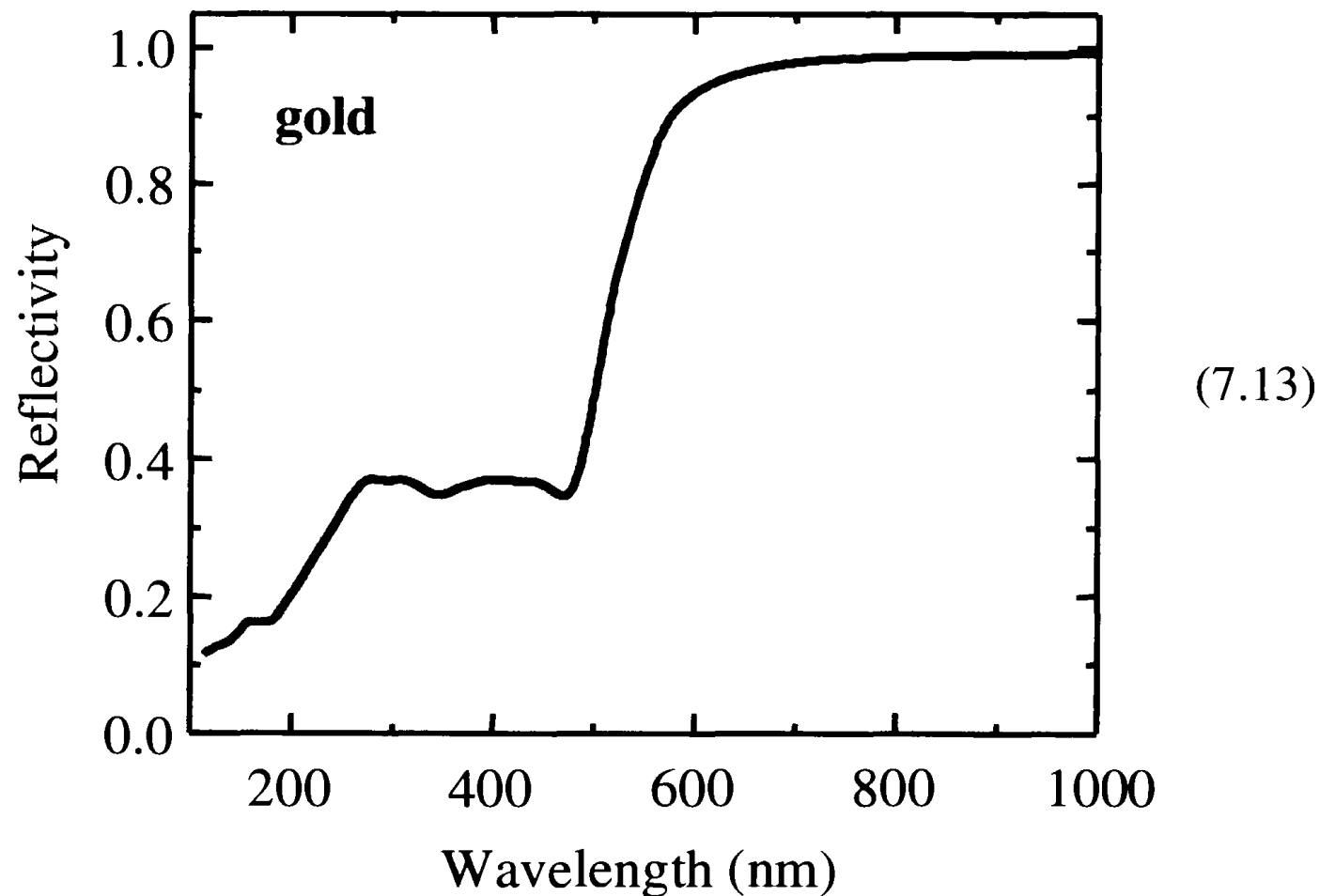


Fig. 7.6 Reflectivity of copper from the infrared to the ultraviolet spectral region. The reflectivity drops sharply above 2 eV due to interband transitions. After [6].

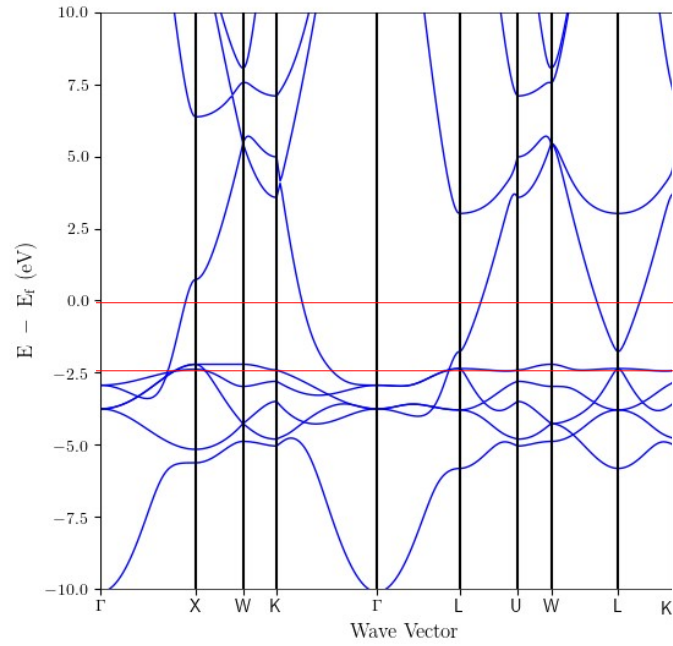
M. Fox: Optical properties of solids, Oxford university press, 2001.

Mezipásové přechody v kovech – zlato

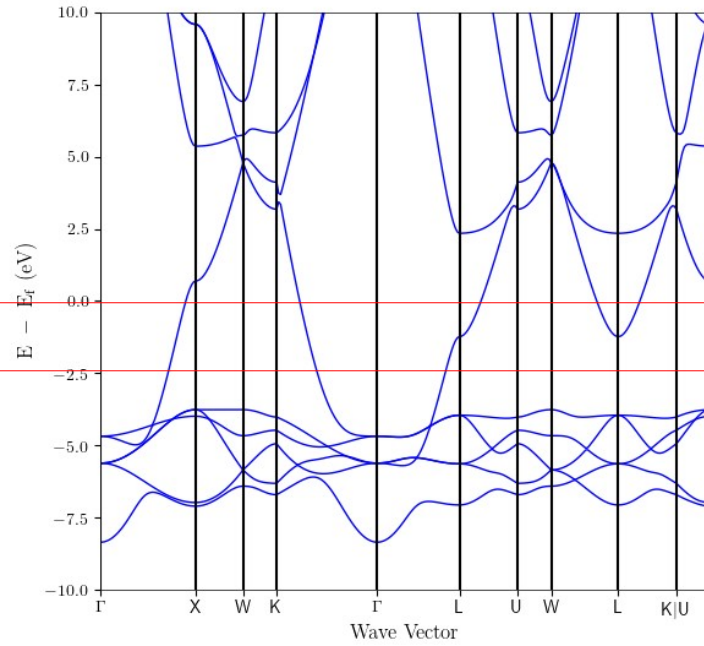


Mezipásové přechody v kovech – Cu, Au, Ag

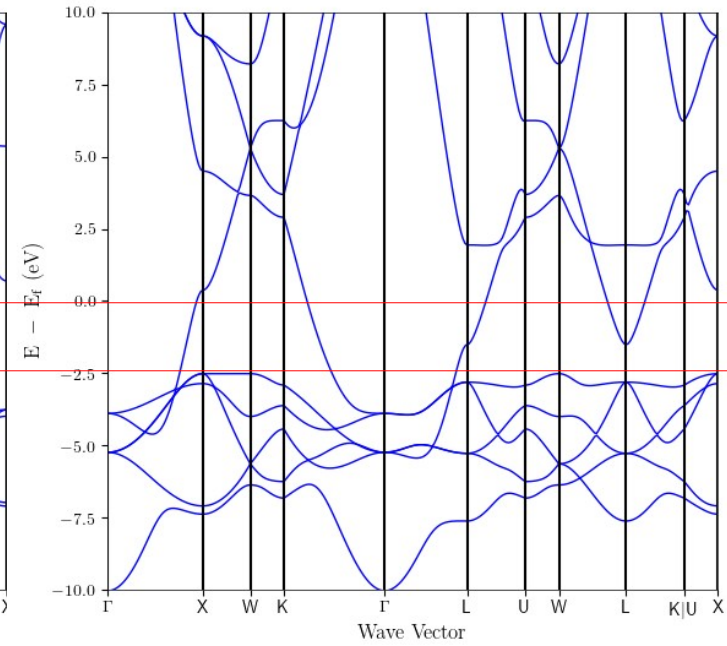
Cu



Ag



Au



Polovodičové nanostruktury

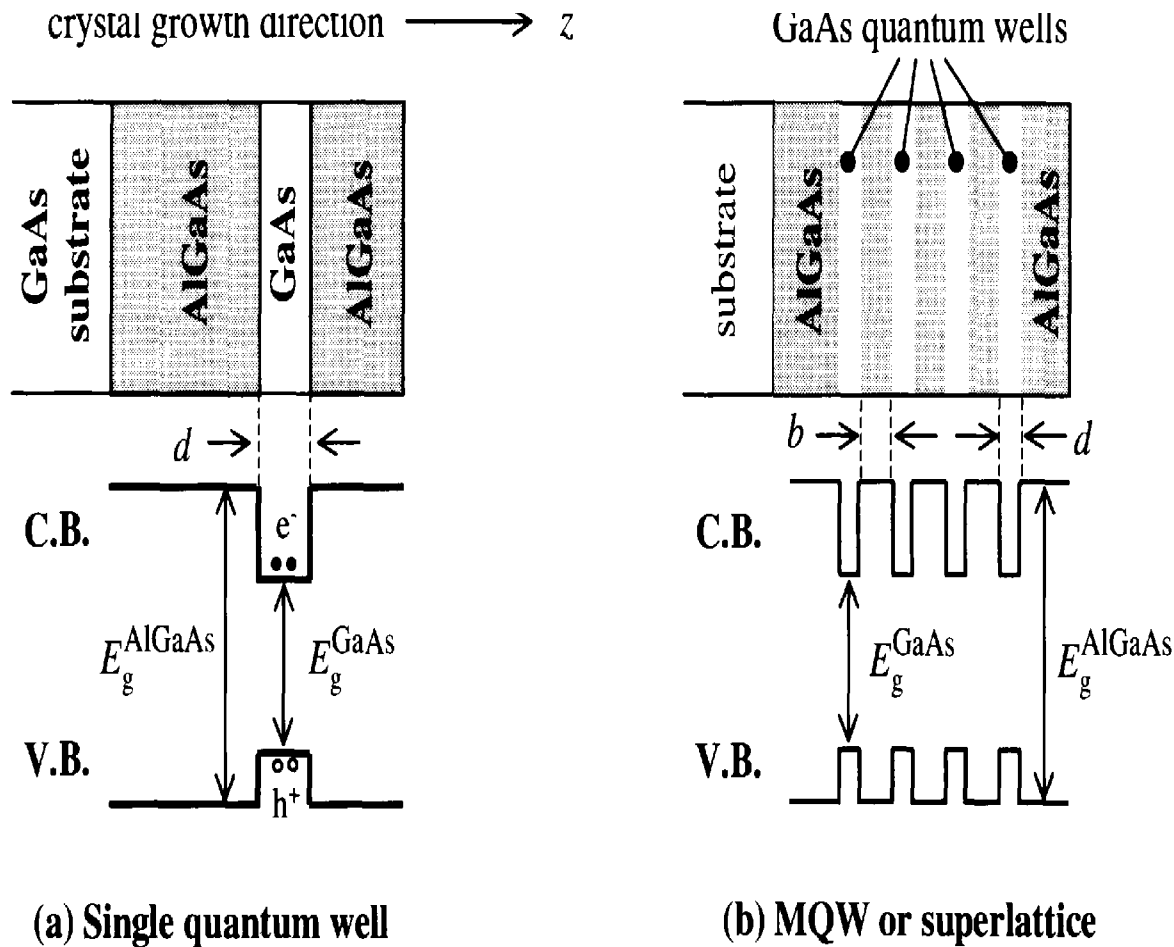


Fig. 6.1 (a) Schematic diagram of a single GaAs/AlGaAs quantum well. The quantum well is formed in the thin GaAs layer sandwiched between AlGaAs layers which have a larger band gap. The lower half of the figure shows the spatial variation of the conduction band (C.B.) and the valence band (V.B.). (b) Schematic diagram of a GaAs/AlGaAs multiple quantum well (MQW) or superlattice structure. The distinction between an MQW and a superlattice depends on the thickness b of the barrier separating the quantum wells.

Polovodičové nanostruktury

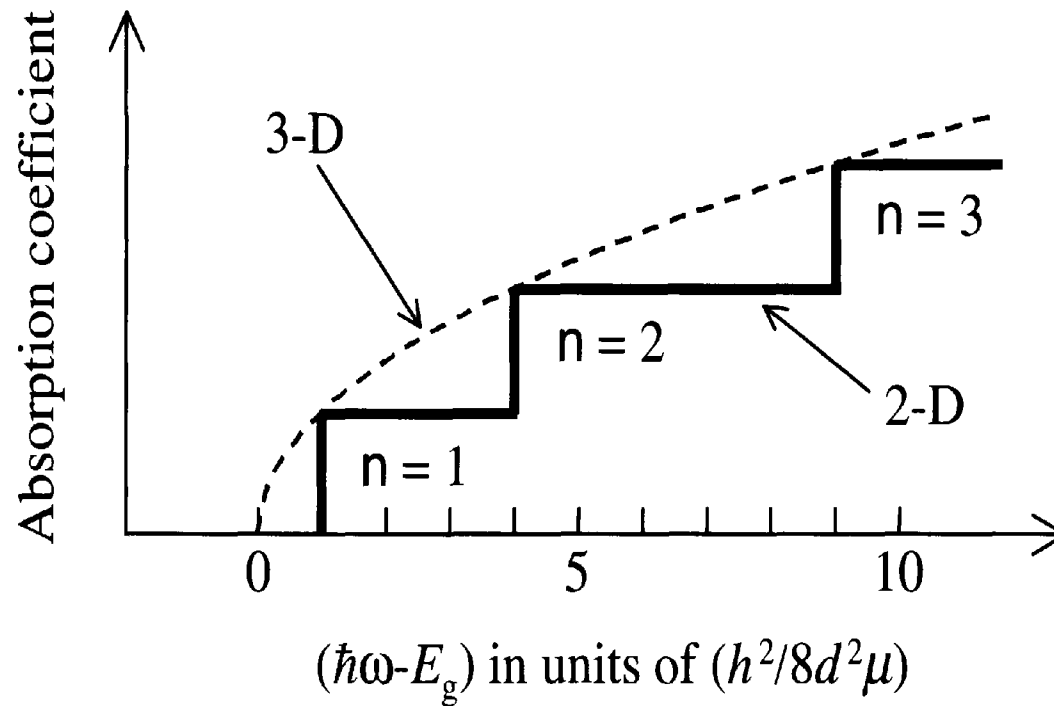
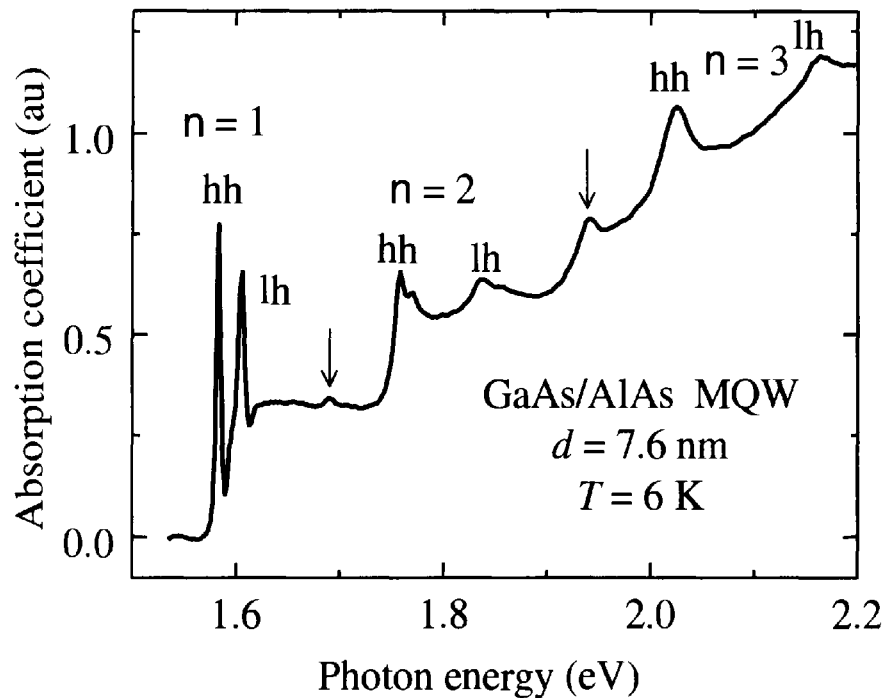


Fig. 6.9 Absorption coefficient of a 40 period GaAs/AlAs MQW structure with 7.6 nm quantum wells at 6 K. After [1], copyright 1996 Taylor & Francis Ltd., reprinted with permission.

Polovodičové nanostruktury

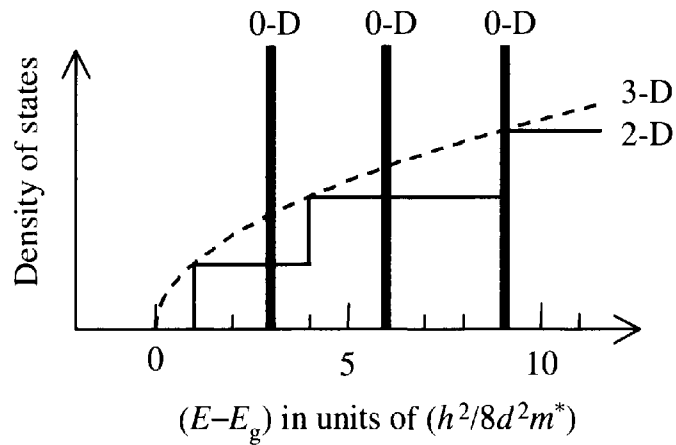


Fig. 6.15 Variation of the electron density of states with dimensionality. The dashed line is for a bulk semiconductor with a band gap of E_g . The thin solid line is for a quantum well of width d with infinite barriers. The thick solid lines are for a cubic quantum dot of dimension d with infinite barriers.

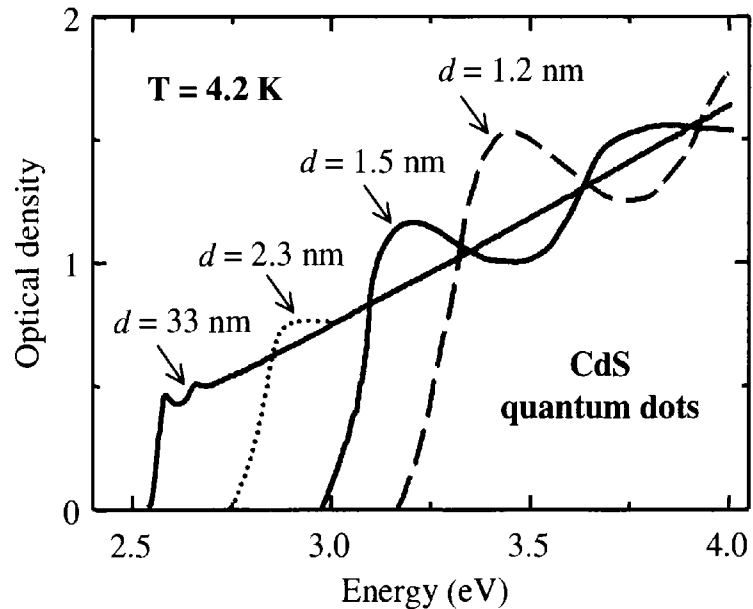
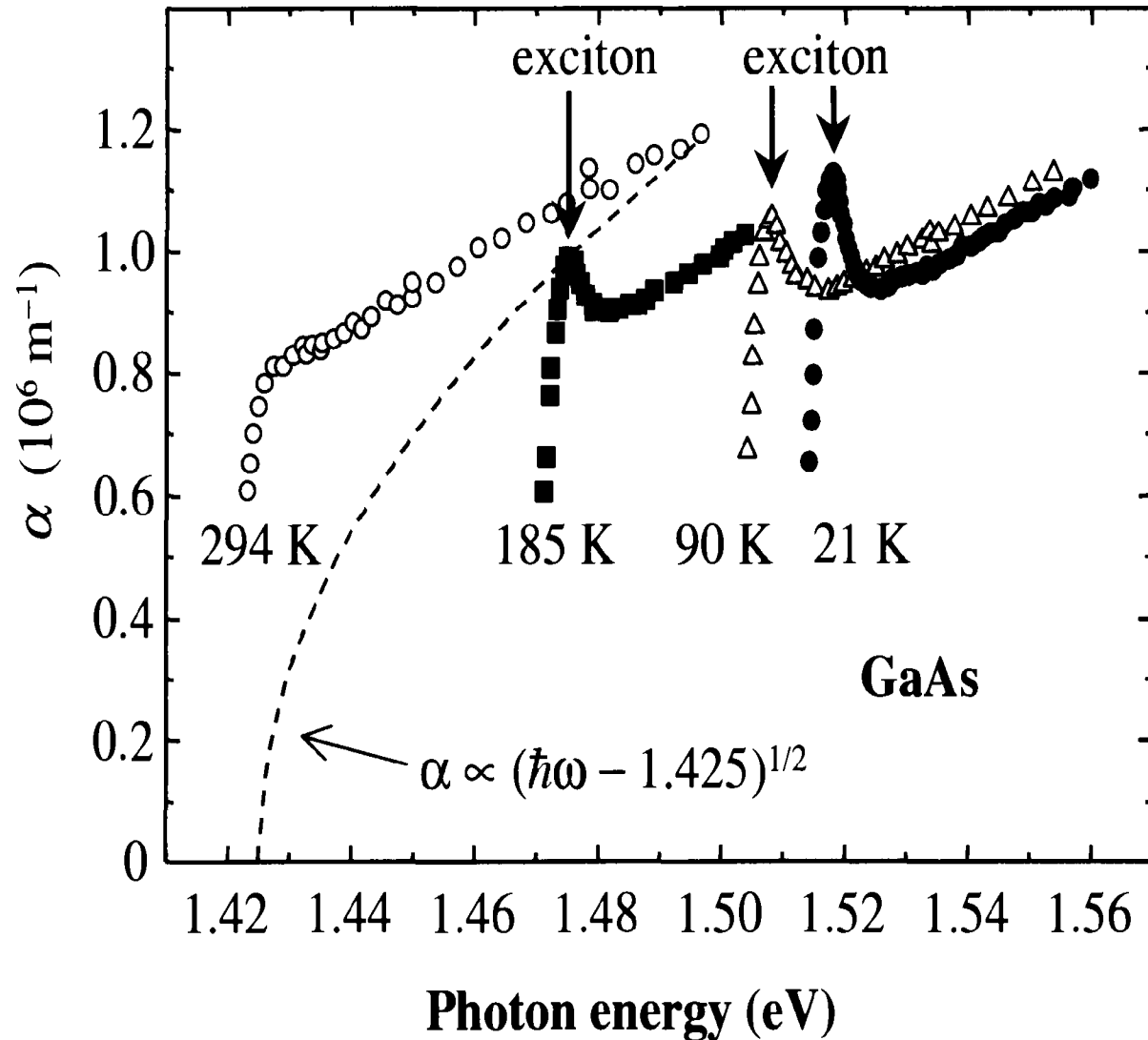
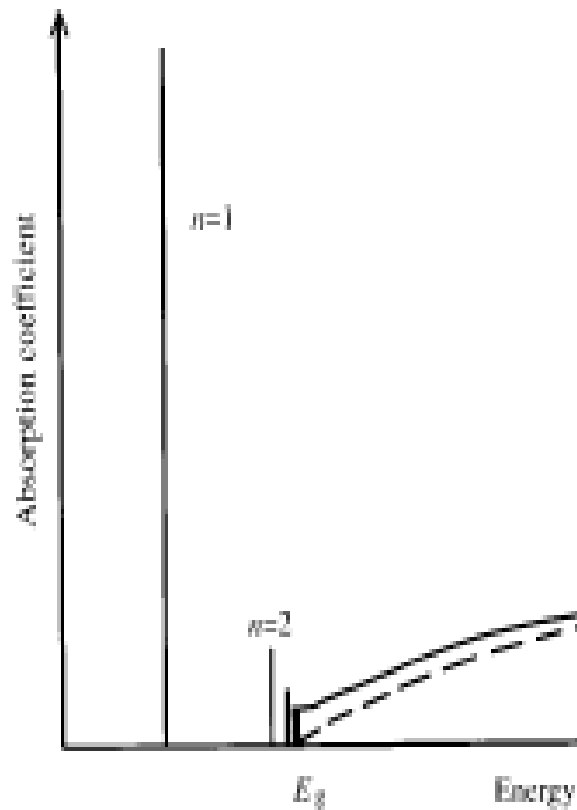


Fig. 6.16 Absorption spectra of glasses with CdS microcrystals of varying sizes at 4.2 K. The sample with $d = 33$ nm effectively represents the properties of bulk CdS. After [3], reprinted with permission.

Excitony v GaAs



Optická skla

	Corning	Schott	n_d (587.56nm)	v_d
517 642 korunové	B1764	BK7	1.517	64.2
805 254 flintové	E0525	SF6	1.805	25.4
křemenné			1.458	67.8

	SiO_2	B_2O_3	Al_2O_3	Na_2O K_2O	BaO	CaO	PbO
517 642 korunové	68	11	1	16	1	2	-
805 254 flintové	27	-	-	2	-	-	71

Abbeho číslo

$$V_d = (n_d - 1) / (n_F - n_C)$$

D: 587.56 nm (Yellow helium line)

F: 486.13 nm (Blue hydrogen line)

C: 656.27 nm (Red hydrogen line)

$$V_e = (n_e - 1) / (n_{F'} - n_{C'})$$

E: 546.07 nm (Green mercury line)

F': 479.99 nm (Blue cadmium line)

C': 643.85 nm (Red cadmium line)

<http://refractiveindex.info/>

Tavený křemen

Table 1.3 Refractive index of synthetic fused silica versus wavelength. After [2].

Wavelength (nm)	Refractive index
213.9	1.53430
239.9	1.51336
275.3	1.49591
334.2	1.47977
404.7	1.46962
467.8	1.46429
508.6	1.46186
546.1	1.46008
632.8	1.45702
706.5	1.45515
780.0	1.45367
1060	1.44968
1395	1.44583
1530	1.44427
1970	1.43853
2325	1.43293

Optická skla

Table 1.4 Composition, refractive index and ultraviolet transmission of common glasses. The letters after the names give the abbreviations used to identify the glass type. The composition figures are the percentage by mass. The refractive index is measured at 546.1 nm, and the transmission is for a 1 cm plate at 310 nm. After [1], [4].

Name	SiO ₂	B ₂ O ₃	Al ₂ O ₃	Na ₂ O	K ₂ O	CaO	BaO	PbO	P ₂ O ₅	<i>n</i>	<i>T</i>
Fused silica	100									1.460	0.91
Crown (K)	74			9	11	6				1.513	0.4
Borosilicate crown (BK)	70	10		8	8	1	3			1.519	0.35
Phosphate crown (PK)		3	10		12	5			70	1.527	0.46
Light flint (LF)	53			5	8			34		1.585	0.008
Flint (F)	47			2	7			44		1.607	–
Dense flint (SF)	33				5			62		1.746	–

Optická skla – vliv 1% at. příměsi na index lomu

OX	$\Delta n (10^{-4})$	Δv
B_2O_3	0	0
Al_2O_3	+4	-0.25
Na_2O	+15	-0.2
K_2O	+10	-0.2
BaO	+30	-0.3
CaO	+24	-0.4
PbO	+30	-0.65
La_2O_3	+42	-0.3
TiO_2	+54	-1.45

Optická skla, index lomu vs. Abbeho číslo

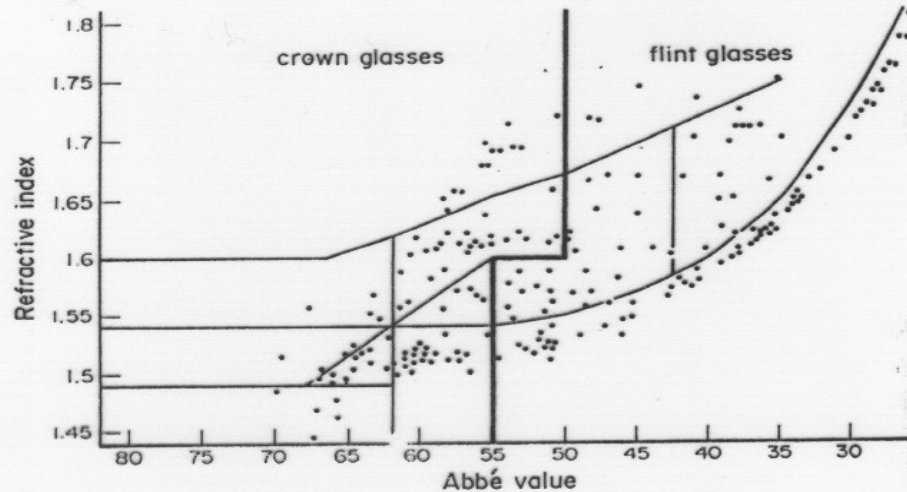


Figure 1
Refractive index against Abbe value diagram

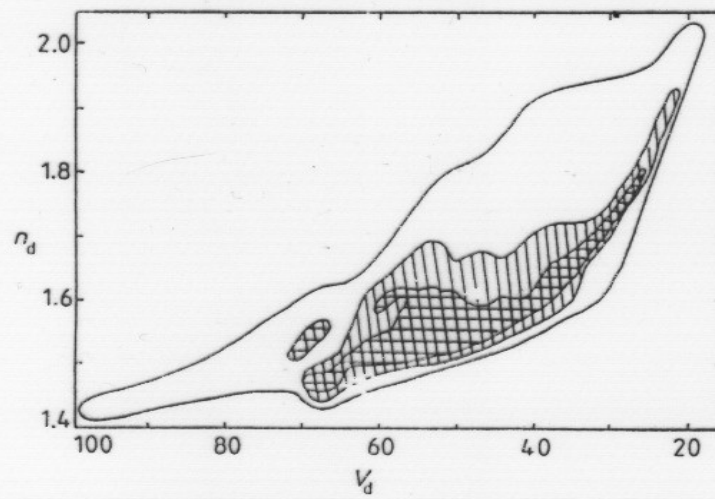



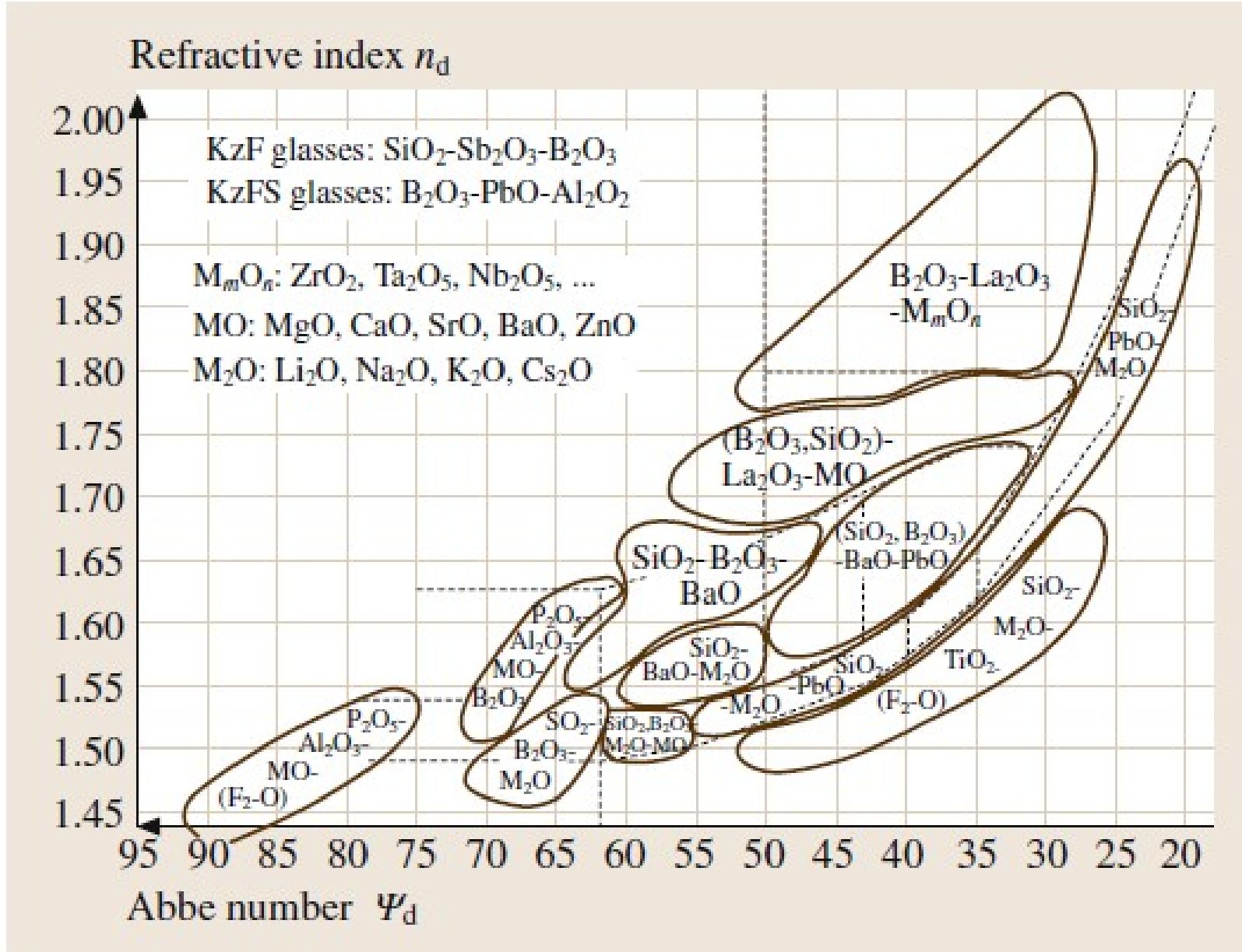


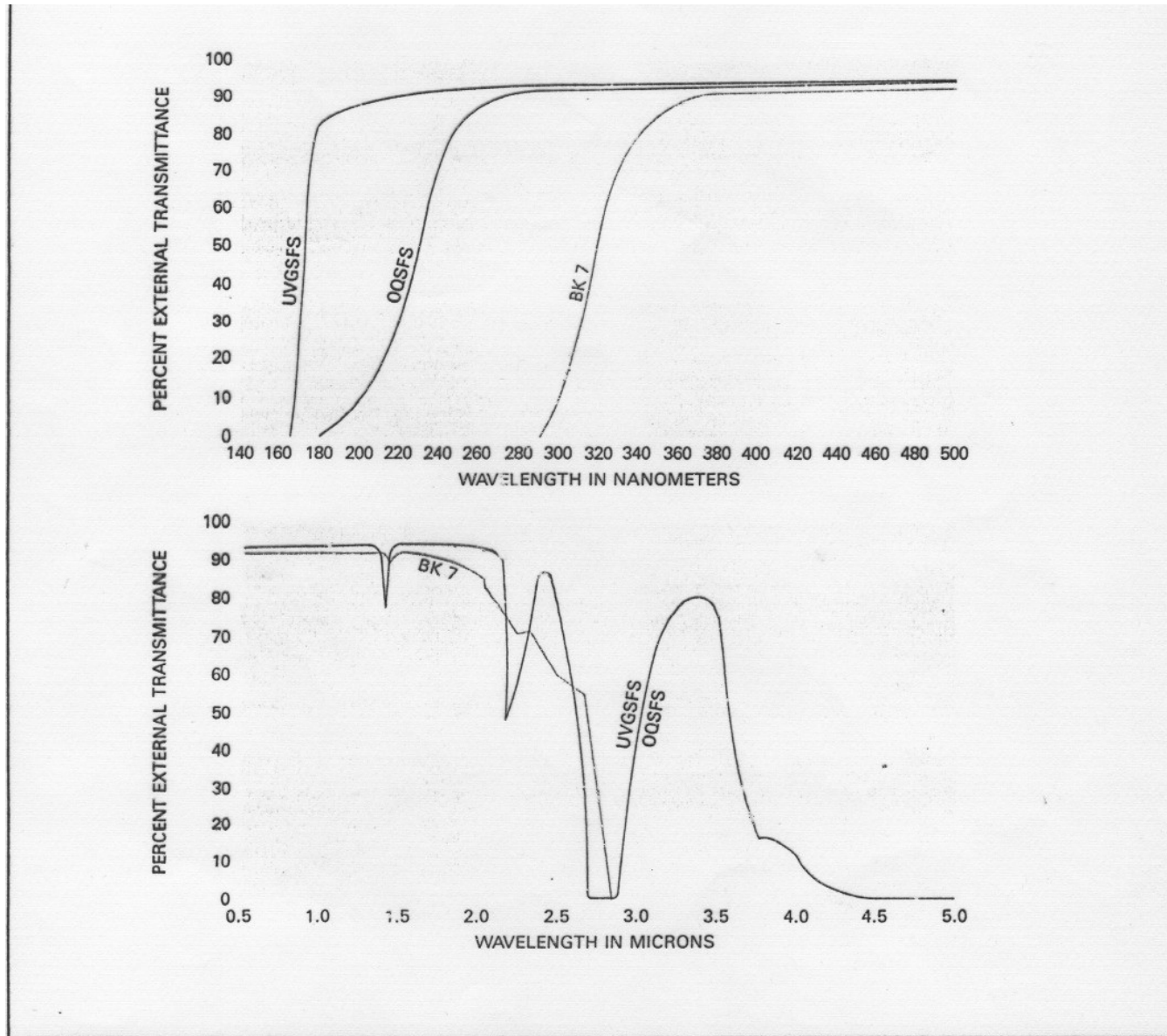
Figure 3.2 Reciprocal dispersive power $(n_d - 1)/(n_f - n_c)$ plotted against n_d for commercial optical glasses (Gliemeroth 1982). 1881 , 1939 , 1981 .

Optická skla, index lomu vs. Abbeho číslo



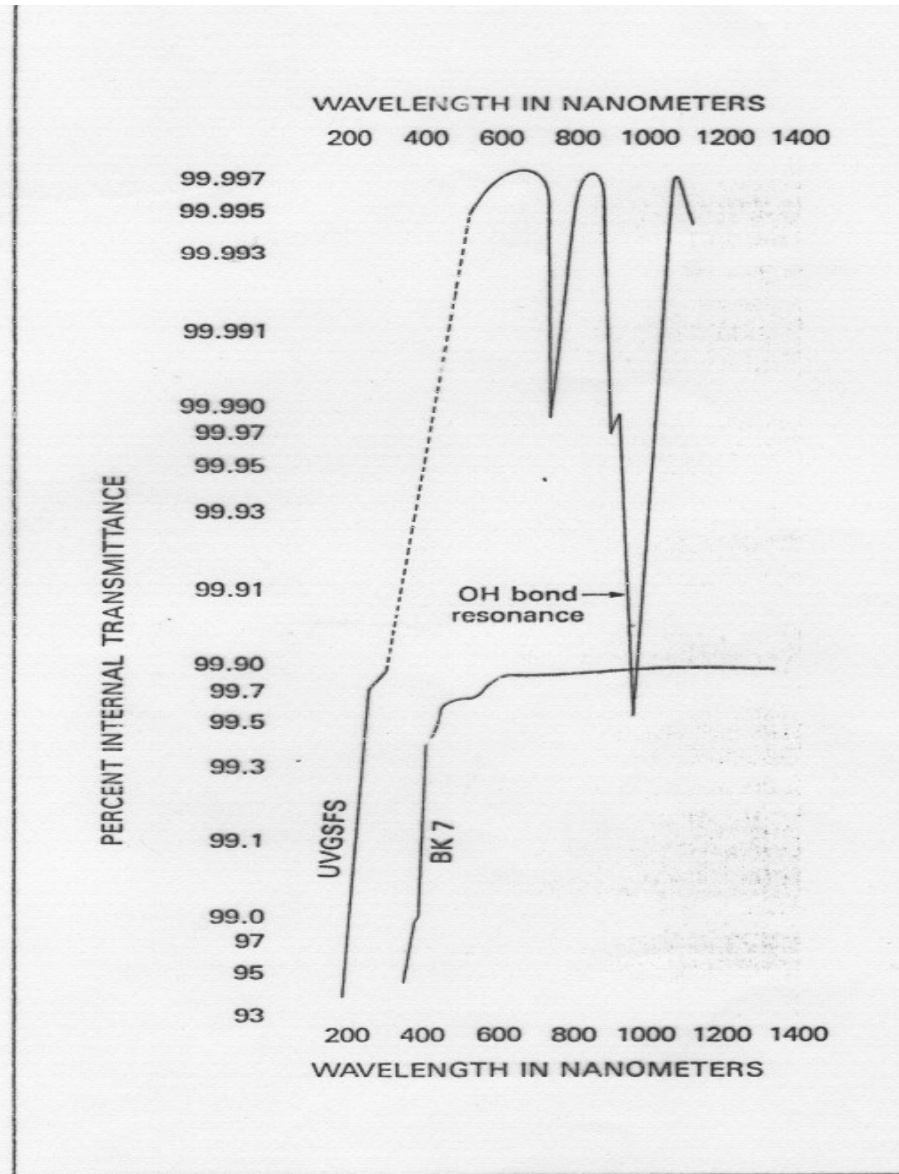
Martienssen, Warlimont, Springer Handbook of condensed matter materials data, Springer, 2004.

Optická skla – propustnost 10mm



COMPARISON OF UNCOATED EXTERNAL TRANSMITTANCES for ultraviolet grade synthetic fused silica (UVGSFS), optical quality synthetic fused silica (OQSFS) and a common optical glass (BK 7), all of 10mm thickness.

Optická skla



SEMILOGARITHMIC COMPARISON OF INTERNAL TRANSMITTANCES of UV grade synthetic fused silica and BK 7.

Korunové sklo

OPTICAL CROWN GLASS

Optical crown glass is a low index, commercial quality glass in which index of refraction, transmittance and homogeneity are not controlled as carefully as in optical quality glasses such as BK 7. Optical crown is a suitable material in applications where component tolerances are fairly loose or as a substrate material for mirrors. Transmittance characteristics for optical crown are shown in the graph; relevant properties of optical crown are tabulated below.

Refractive Index of Optical Crown Glass

Wavelength (nm)	Refractive Index, n	Fraunhofer Designation	Source	Spectral Region
435.8	1.53394	g	mercury arc	blue
480.0	1.52960	F'	cadmium arc	blue
486.1	1.52908	F	hydrogen arc	blue
546.1	1.52501	e	mercury arc	green
587.6	1.52288	d	helium arc	yellow
589.0	1.52280	D ₂	sodium arc	yellow
643.8	1.52059	C'	cadmium arc	red
656.3	1.52015	C	hydrogen arc	red

OPTICAL CROWN GLASS CONSTANTS

Abbe Factor:

$$v_e = \frac{n_c - 1}{n_F - n_C} = 58.3 \quad v_d = \frac{n_d - 1}{n_F - n_C} = 58.8$$

Dispersion: $(n_F - n_C) = 0.0089$

Glass type designation: B270

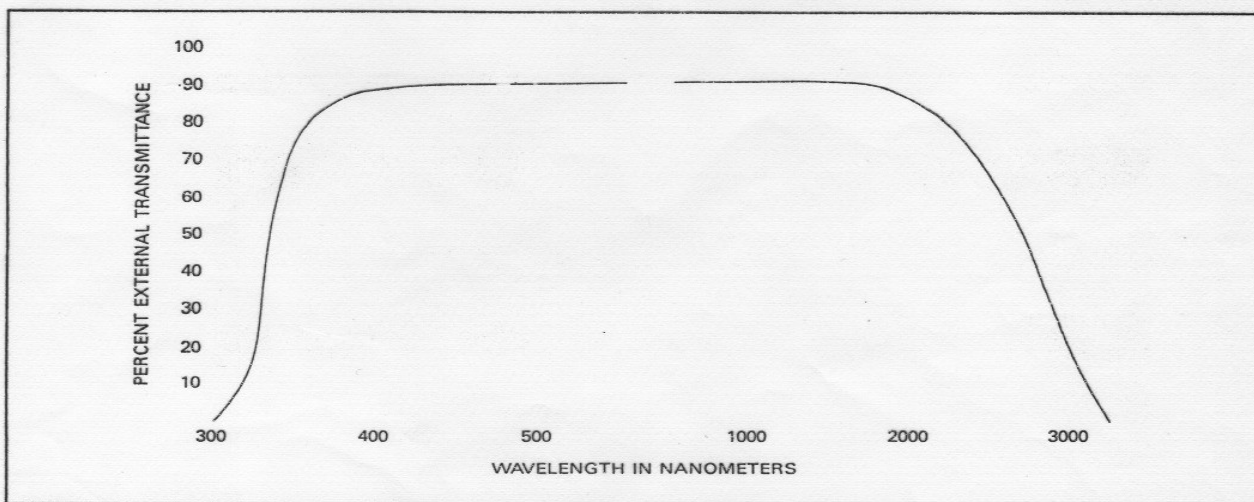
Density: 2.55 g cm⁻³ at 23 °C

Transformation temperature: 521 °C

Softening temperature: 708 °C

Coefficient of linear expansion:
(20 to 300 °C) = $93.3 \times 10^{-7} \text{ } ^\circ\text{C}^{-1}$

Specific heat: C_p (20 to 100 °C) = 0.184 cal. g⁻¹ °C⁻¹



EXTERNAL TRANSMITTANCE FOR OPTICAL CROWN GLASS of 10mm thickness.

Diamant

Propustná oblast 0.3 – 100 μm (typ Ia)

λ (μm)	n
3	2.3818
4	2.3812
5	2.3809
8	2.3806
10	2.3805
12	2.3805

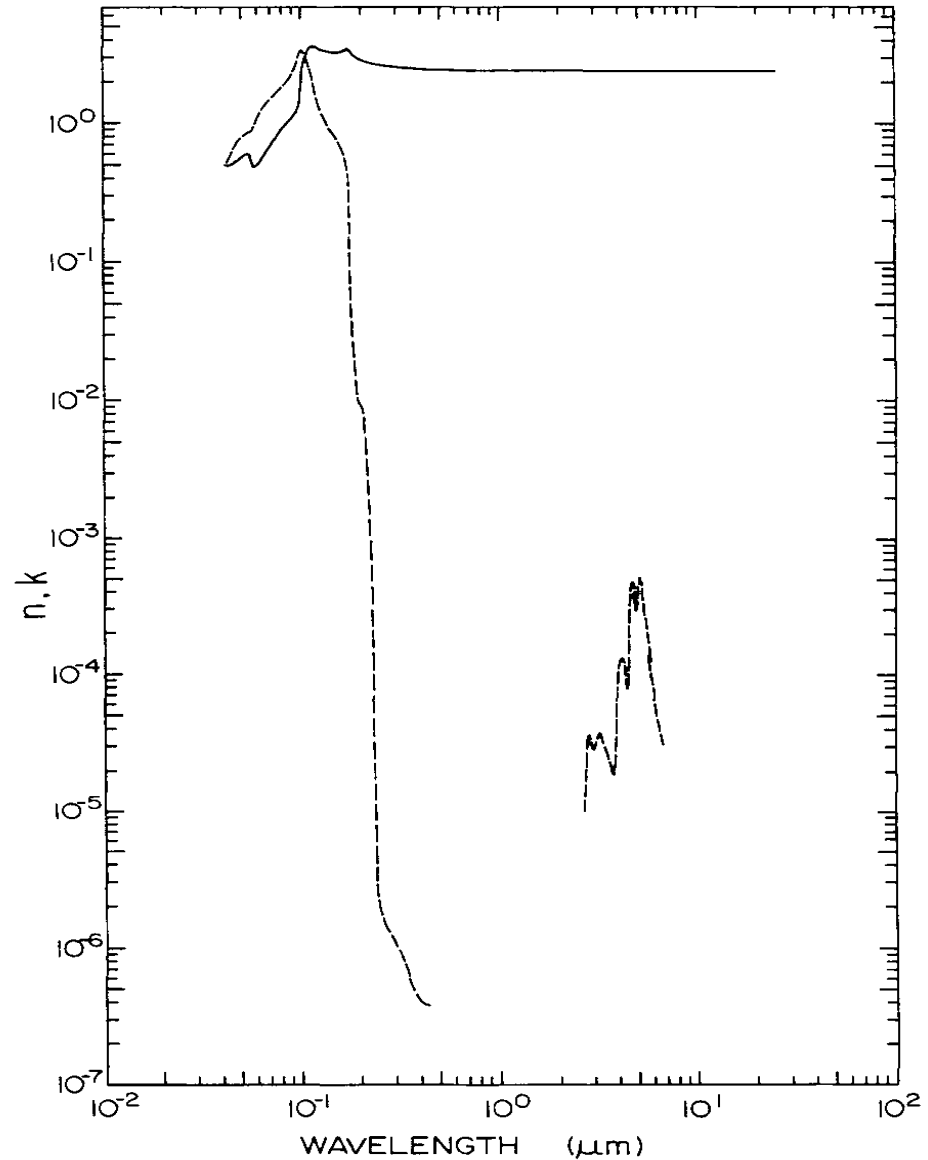
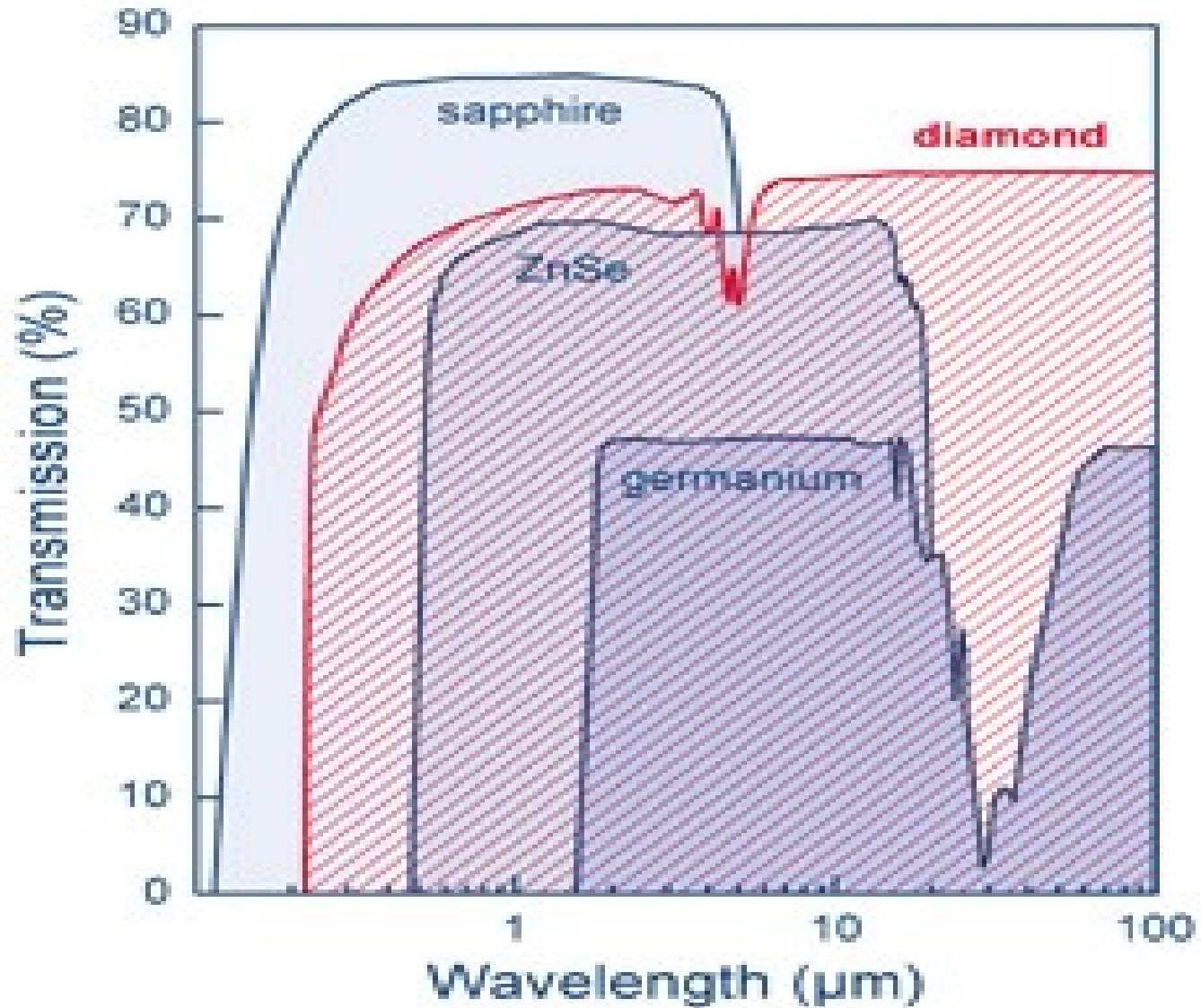


Fig. 5. Log-log plot of n (—) and k (---) versus wavelength in micrometers for cut carbon.

Diamant

Propustnost v IR oboru, cca 1mm

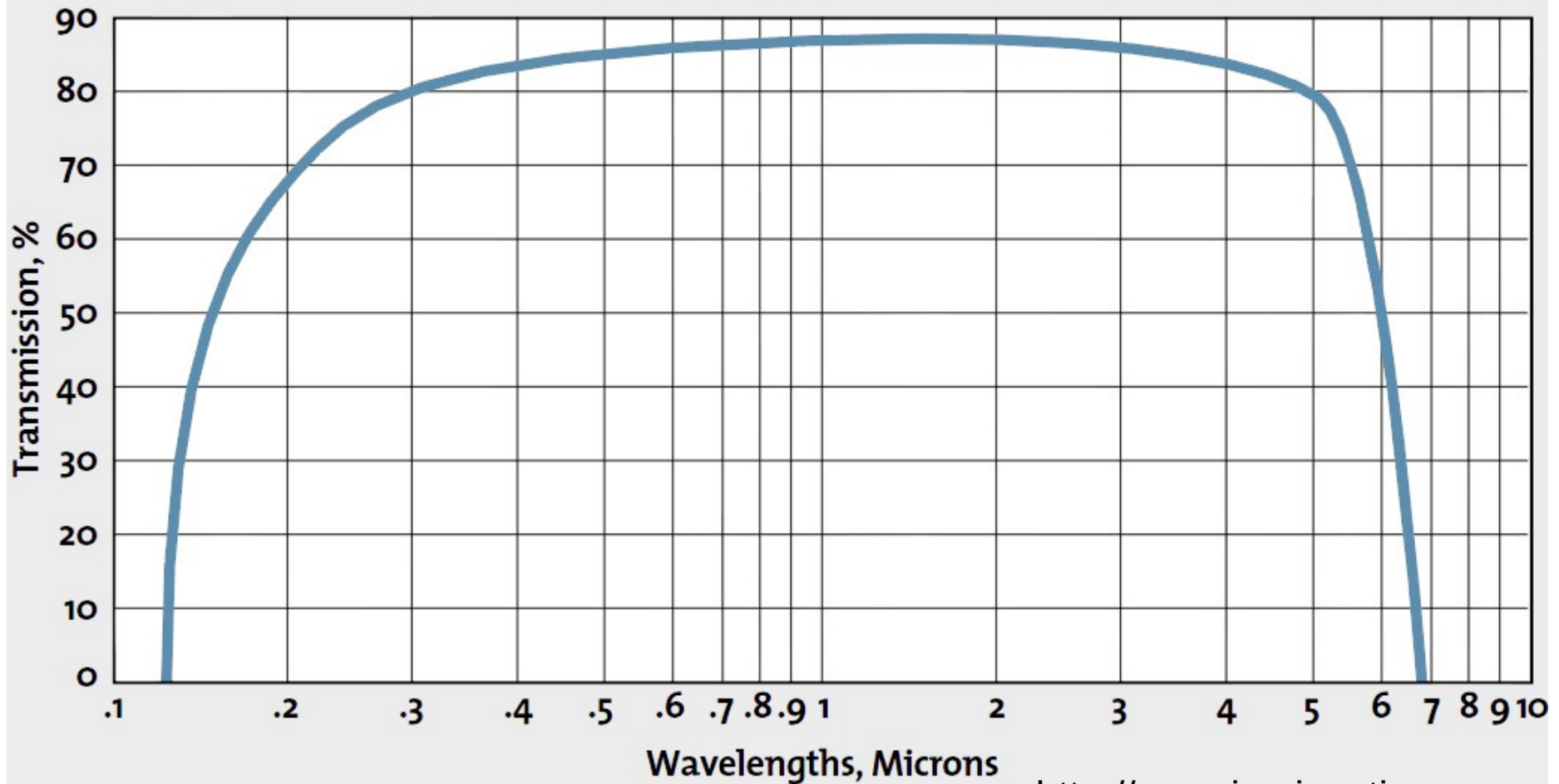


Safír – Al_2O_3

SAPPHIRE* CONSTANTS

Density: 3.98 g cm^{-3} at 25°C
Young's Modulus: $*3.7 \times 10^{10} \text{ dynes/mm}^2$
Poisson's Ratio: $*-0.02$
Moh hardness: 9 (by definition)
Softening Point: 1800°C
Specific Heat at 25°C : $0.18 \text{ cal/g } ^\circ\text{C}$
Coefficient of linear expansion:
(0°C to 500°C) $\circ 7.7 \times 10^{-6}^\circ\text{C}$

Transmission Graph at 0.8mm thickness



Safír – Al_2O_3 , Rubín – $\text{Al}_2\text{O}_3 + \text{Cr}$

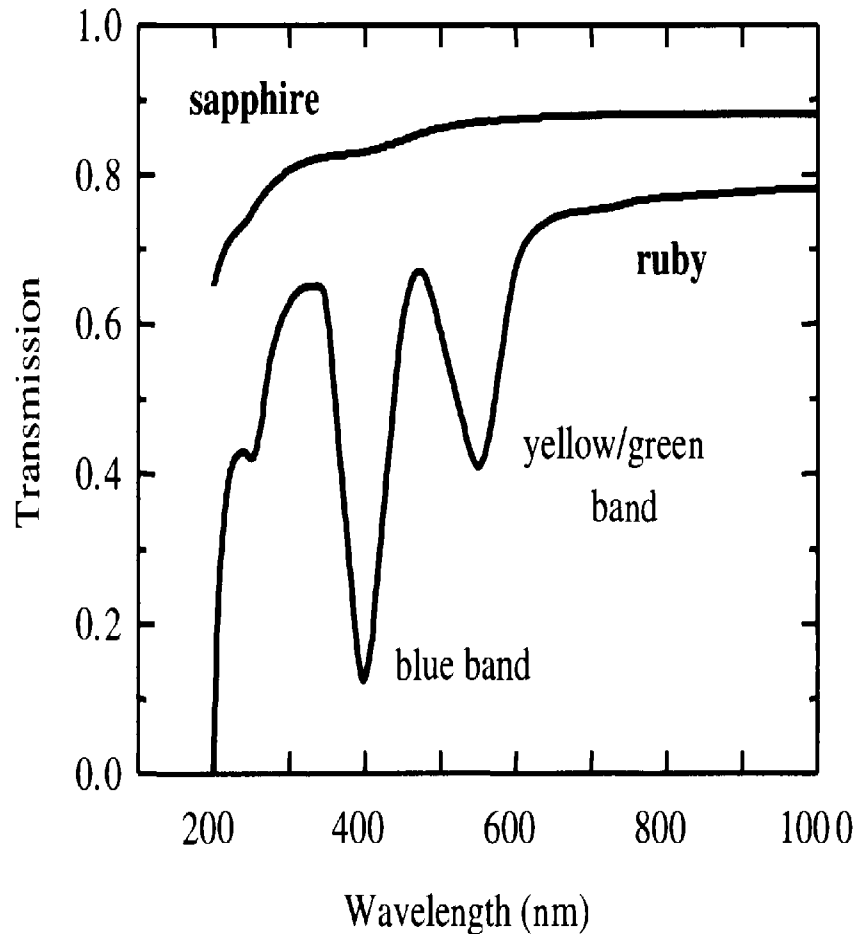


Fig. 1.7 Transmission spectrum of ruby (Al_2O_3 with 0.05 % Cr^{3+}) compared to sapphire (pure Al_2O_3). The thicknesses of the two crystals were 6.1 mm and 3.0 mm respectively. After [6], reprinted with permission.

Safír, CdSe

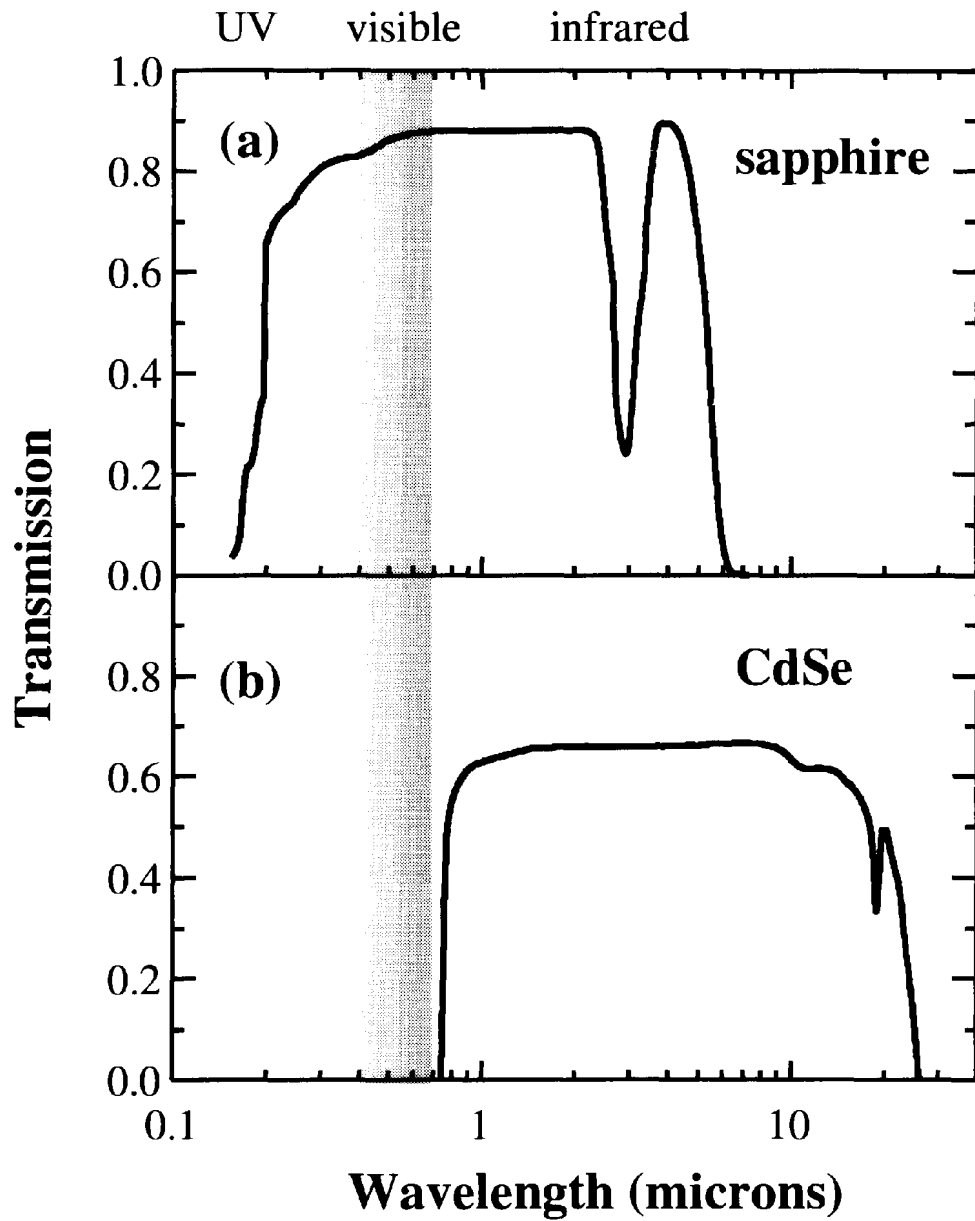


Fig. 1.4 (a) Transmission spectrum of a sapphire (Al_2O_3) crystal of thickness 3 mm. (b) Transmission spectrum of a CdSe crystal of thickness 1.67 mm. After [1].

Propustné materiály

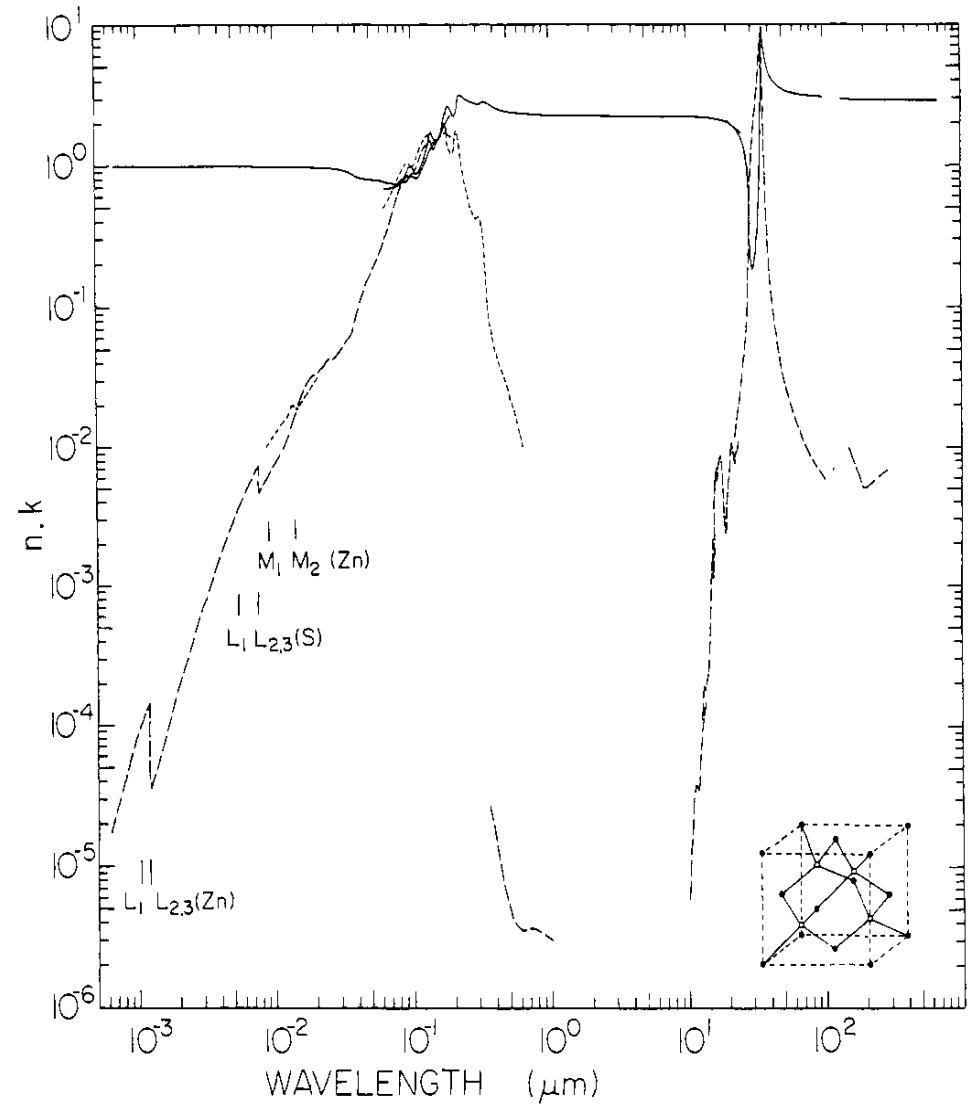
Table 1.1 Approximate transparency range and refractive index n of a number of crystalline insulators. n is measured at 546 nm. Values of n are given both for the o-ray and e-ray of birefringent materials. After [1] and [2].

Crystal	Transparency range (μm)	n
Al ₂ O ₃ (sapphire)	0.2–6	1.771 (o)
		1.763 (e)
BaF ₂	0.2–12	1.476
Diamond	0.25–> 80	2.424
KBr	0.3–30	1.564
KCl	0.21–25	1.493
KI	0.3–40	1.673
MgF ₂	0.12–8	1.379 (o)
		1.390 (e)
NaCl	0.21–20	1.55
NaF	0.19–15	1.326
SiO ₂ (quartz)	0.2–3	1.546 (o)
		1.555 (e)
TiO ₂ (rutile)	0.45–5	2.652 (o)
		2.958 (e)

ZnS

Propustná oblast 0.4 – 12 μm

λ (μm)	n
0.4	2.5452
1	2.2917
5	2.2466
12	2.1710



ZnSe

Propustná oblast 0.5 – 17 μm

λ (μm)	n
0.7	2.5568
1	2.4892
5	2.4295
12	2.3930

Halogenidy

	E_g (eV)	n	při λ (μm)
NaCl	8.97	1.3822	20
KCl	8.50	1.3947	20
KBr	7.6	1.2978	40
AgCl	3.0	1.9069	20
CsBr	7.5	1.5587	40
CsI	5.1	1.5797	60
KRS5 54% TlI_3 + 46% TlBr_3	2.4	2.2105	40

Halogenidy

NaCl

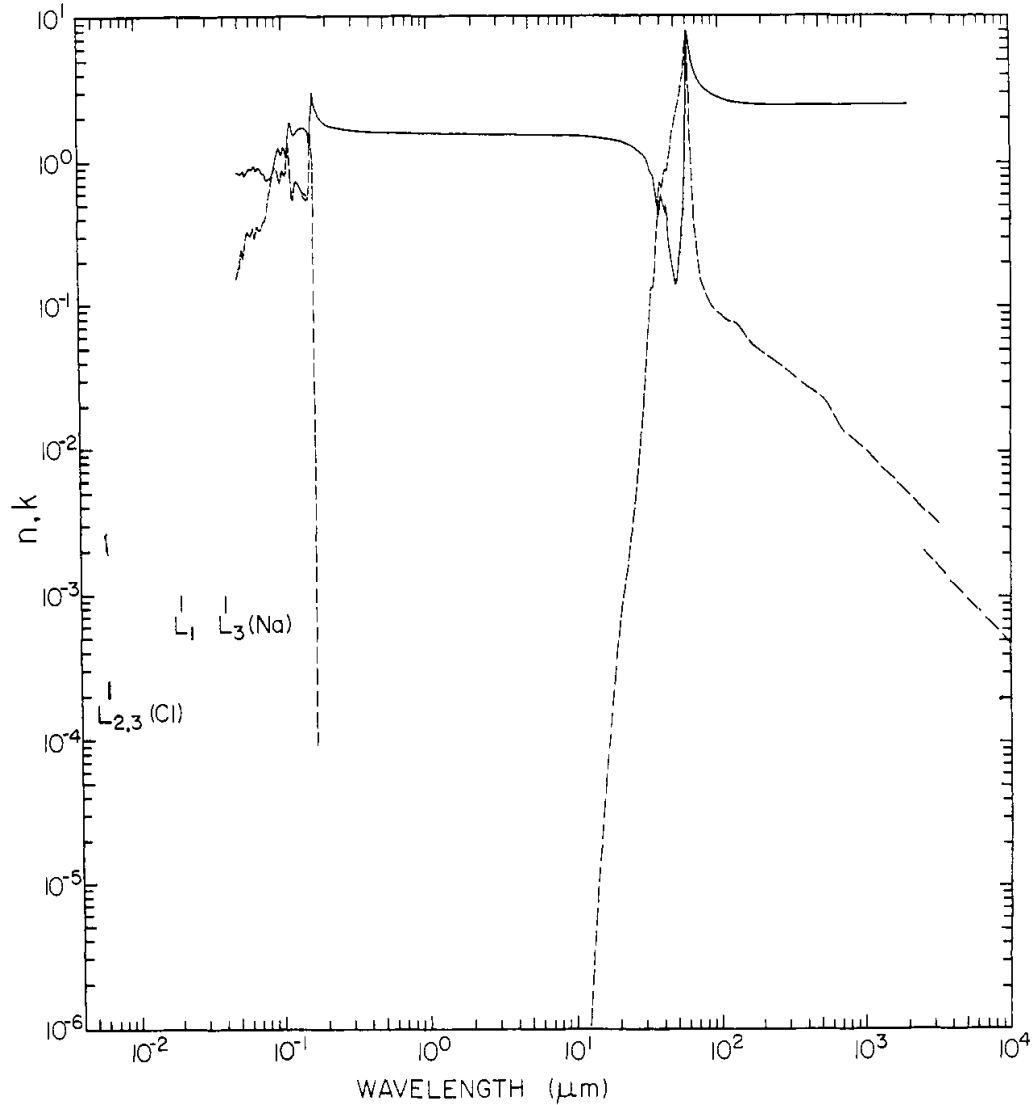


Fig. 13. Log-log plot of n (—) and k (----) versus wavelength in micrometers for sodium chloride.

LiF

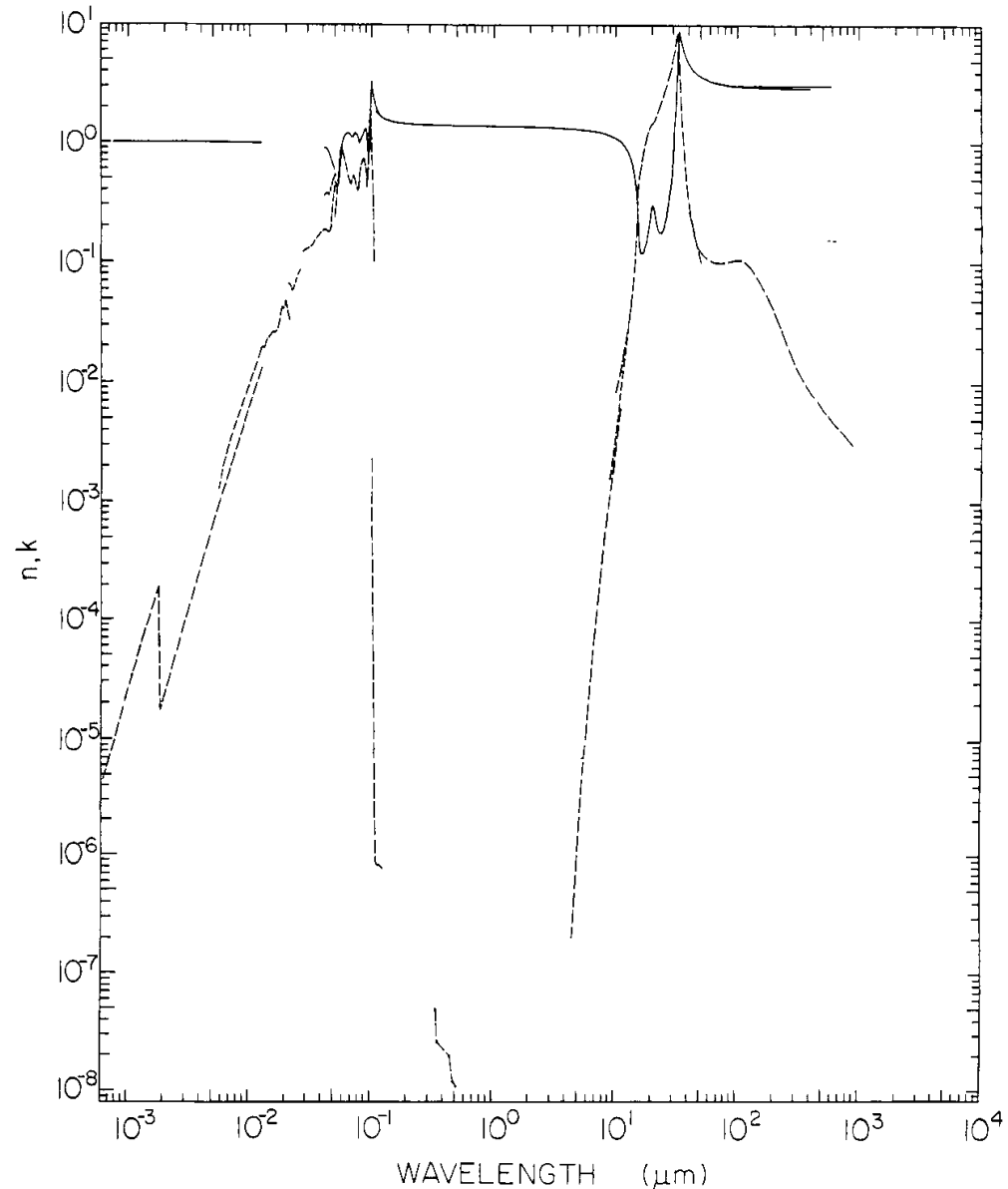


Fig. 6. Log-log plot of n (—) and k (----) versus wavelength in micrometers for lithium fluoride. Note the incredibly small values of k in the transparent region centered near $1 \mu\text{m}$.

Halogenidy

	$3\nu_{\text{LO}}$ (cm^{-1})
NaCl	795
KCl	615
KBr	489
AgCl	597
CsBr	342
CsI	270

Laserové poškození

Pulsy 1.06 μm (NdYAG)

	Pt (J/cm^2)
BK7	cca 50
SF6	cca 7

10.6 μm (CO_2)

	P (MW/cm^2)
Ge	600
GaAs	100
ZnSe	800
KCl	100 – 1000

Fluoridová skla

ZBLA:
 56% ZrF_4
 34% BaF_2
 6% LaF_3
 4% AlF_3

BIZYbT:
 30% Ba
 30% In
 20% Zn
 10% Yb
 10% Th

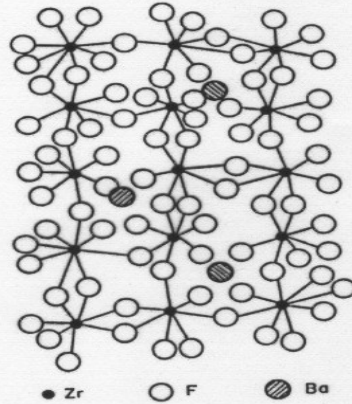


Figure 4
 A structural model for fluorozirconate glass

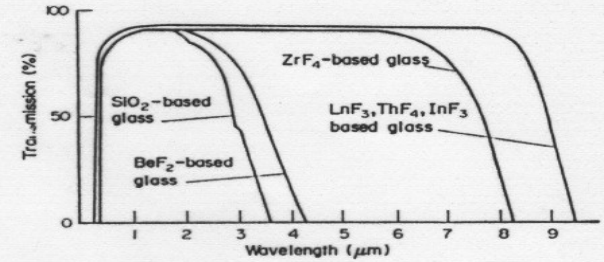


Figure 5
 Optical transmission range for fluoride glasses and SiO_2 (sample thickness 4 mm)

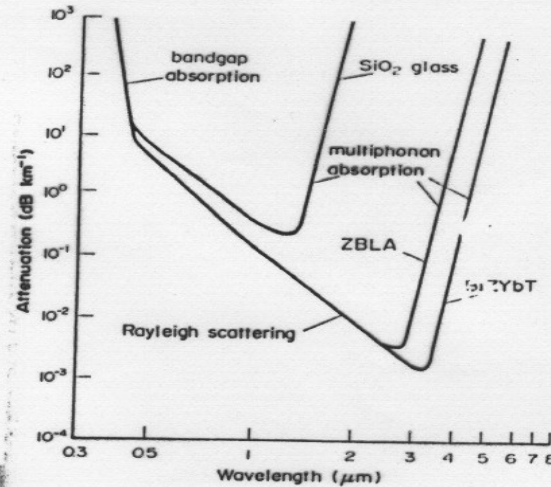


Figure 6
 Ultratransparency region (very low absorption) for fluoride and SiO_2 glasses

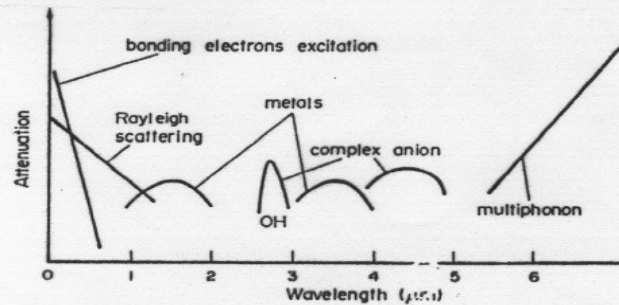
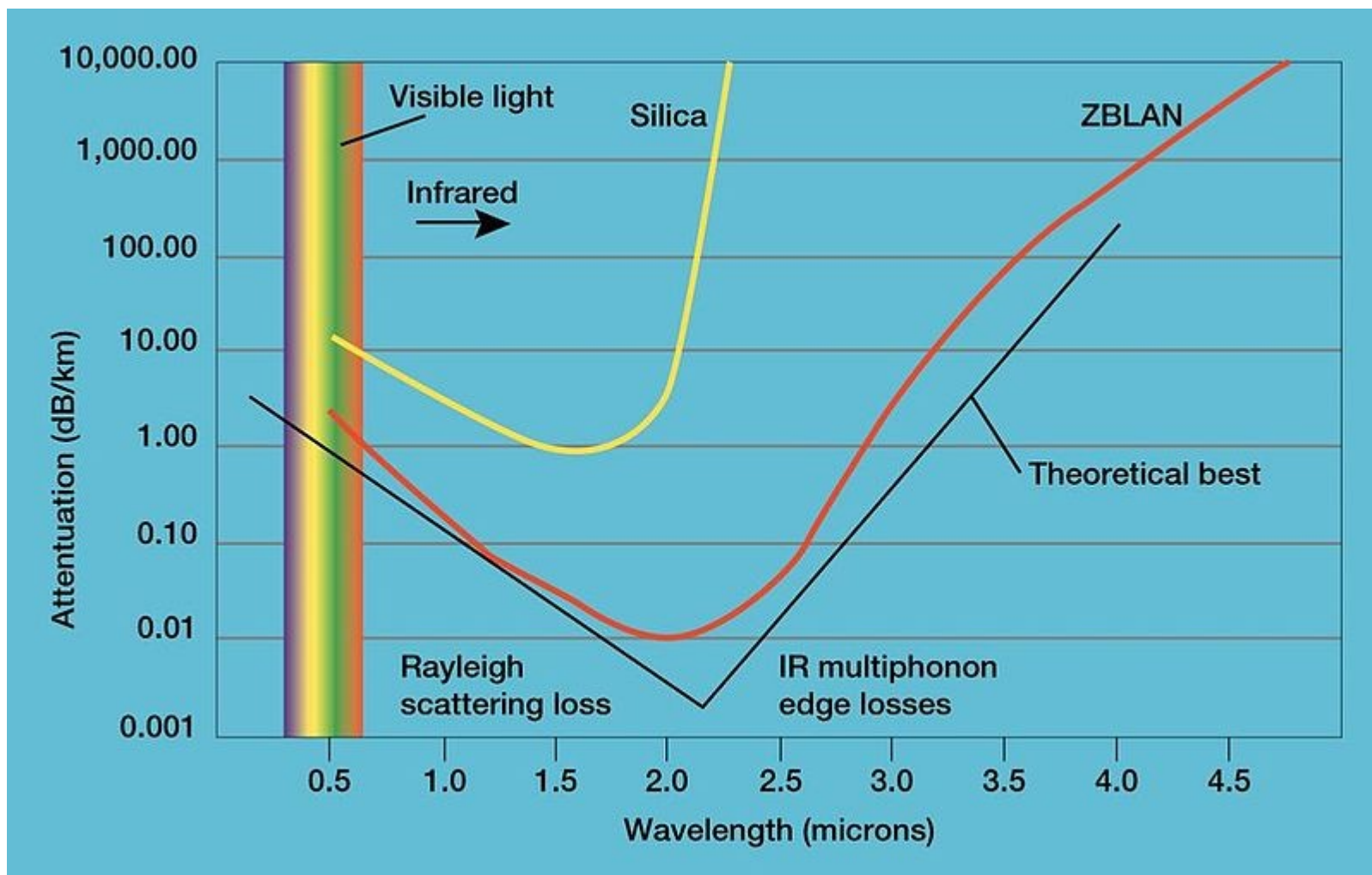


Figure 7
 Extrinsic absorption mechanisms in fluoride glasses:
 electronic excitation of 3d electrons in Fe^{2+} , Co^{2+} , Ni^{2+} ,

Fluoridová skla

ZBLAN útlum na 1km



Vodivé průhledné materiály

ITO – indium tin oxide

Typicky cca In_2O_3 90%, SnO_2 10%, hmotnostně

Gap cca 4eV

Další materiály:

AZO – aluminium zinc oxide

Nevýhoda nižší životnost a odolnost proti vlhkosti

ITO také může být leptáno na jemnější strukturu.

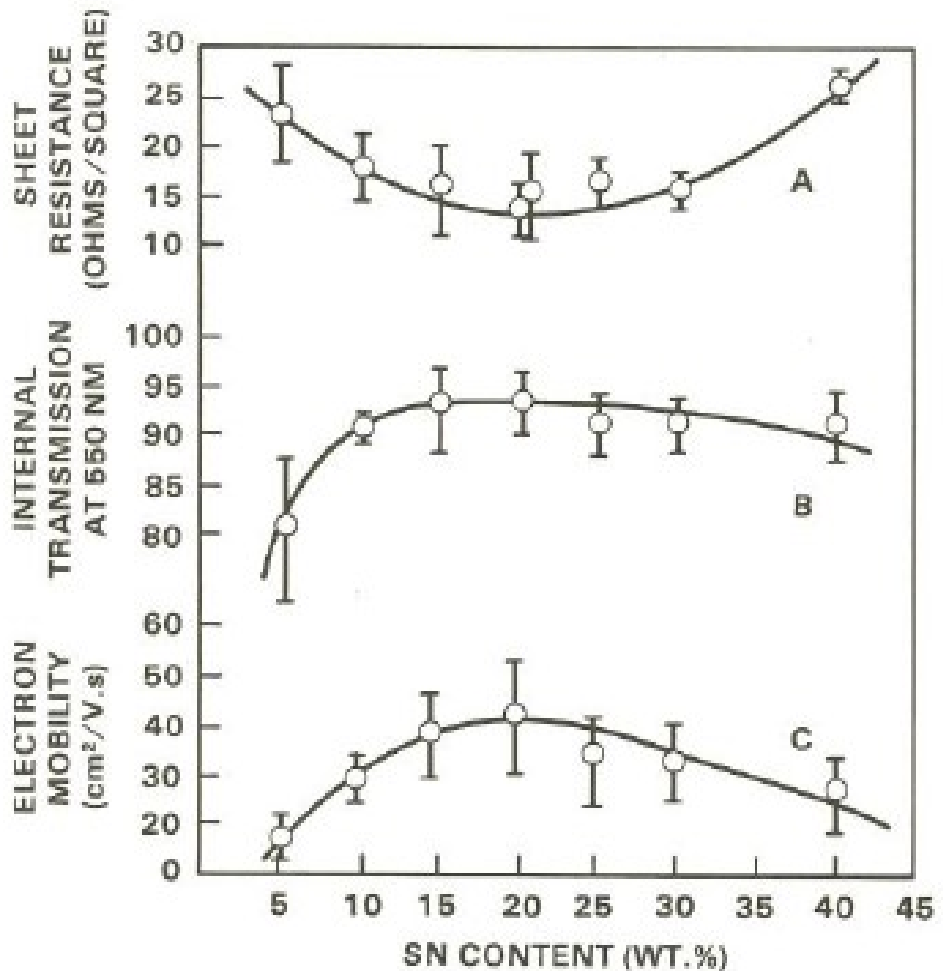
GZO (Ga), IZO (In)

Vodivé polymery

Grafen, uhlíkové nanotrubky

Použití:

Displeje, solární panely, etc.



Vrstva cca 140nm

Materion.com

materiál	minimální odpor
$\mu\Omega\cdot\text{cm}$	
ITO	114
In_2O_3	100
SnO_2	400
ZnO	120
ZnO:Al	1300
CdSnO_2	130

Propustnost vzduchu a záření černého tělesa

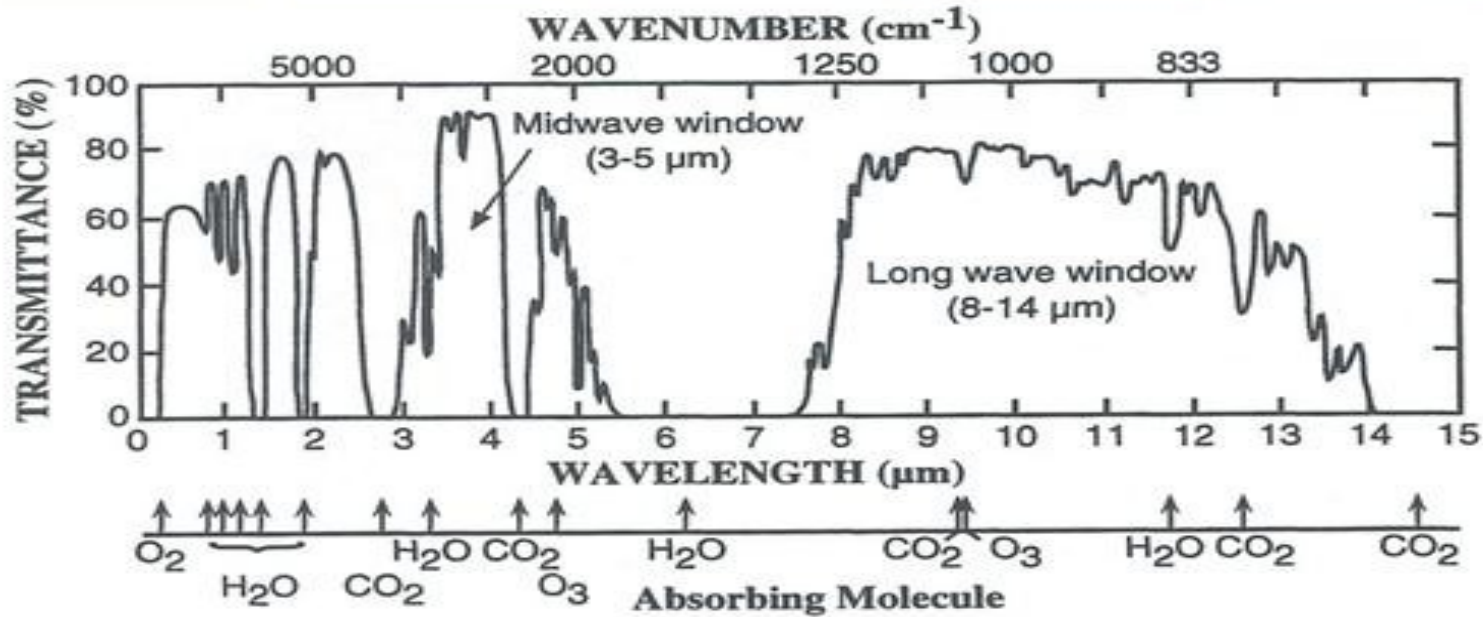
NIR (0.7-1.4 μm)

SWIR (1.4-3 μm)

MWIR (3-5 μm)

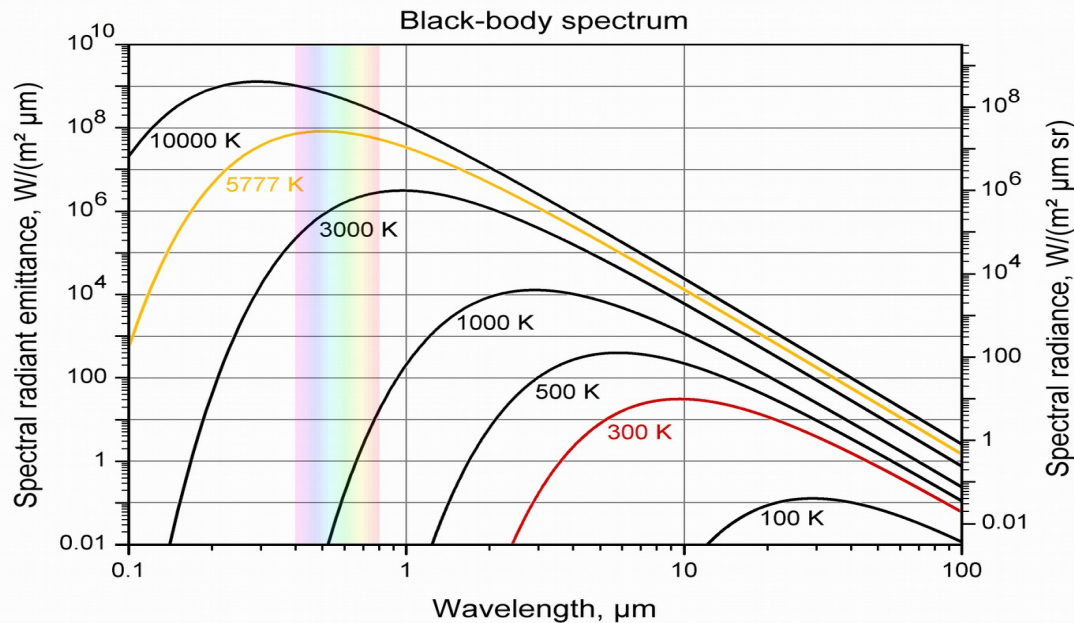
LWIR (8-14 μm)

FWIR (>14 μm)



Dráha 1 km

www.schott.com



www.scienceblogs.com

Propustné oblasti a indexy lomu pro 4 μm

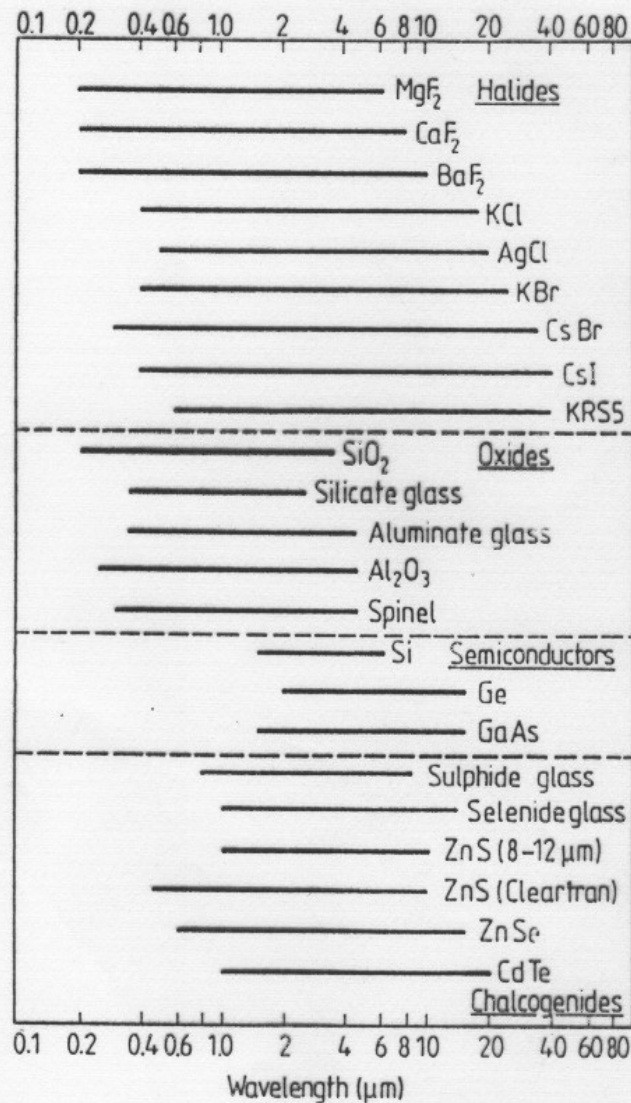


Figure 2.2 The relative transmittance ranges of some halide, oxide, semiconductor and chalcogenide materials.

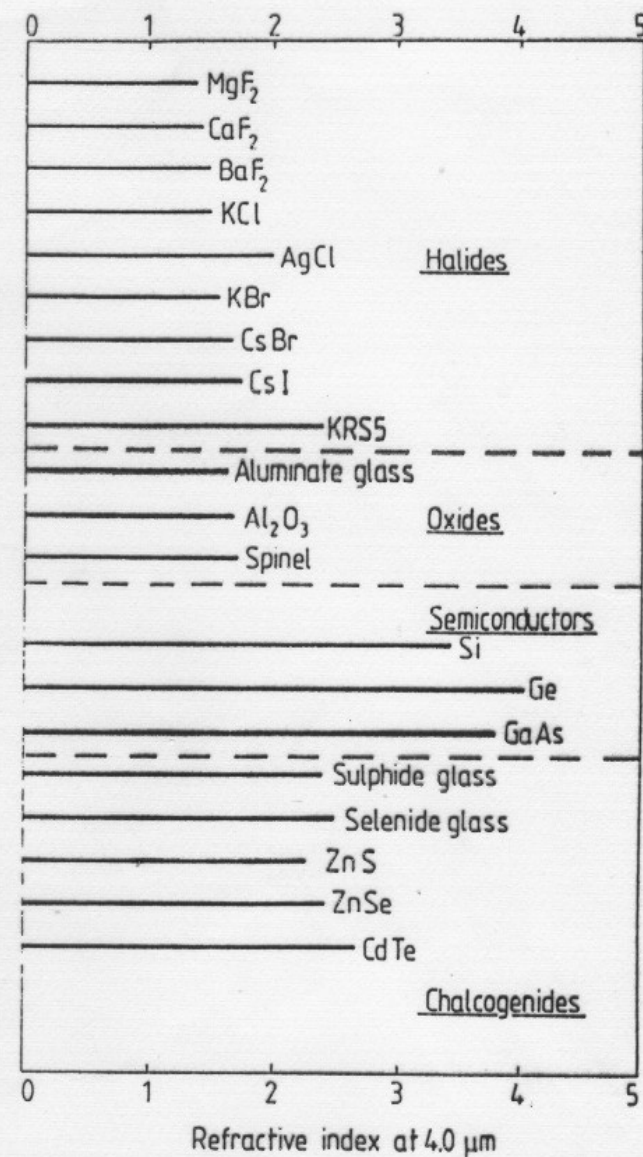


Figure 2.3 The relative refractive indices at 4.0 μm for some halide, oxide, semiconductor and chalcogenide materials.

Propustnost

Sulfidové sklo 1.9 mm
Ge 30%, S 50%, As 20%

Selenidové sklo 1.8 mm
Ge 34%, As 8%, Se 58%

Selenidové – teluridové
2.3 mm
Ge 30%, As 13%, Se 27%,
Te 30%

Teluridové sklo 1.6 mm
Ge 10%, As 50%, Te 40%

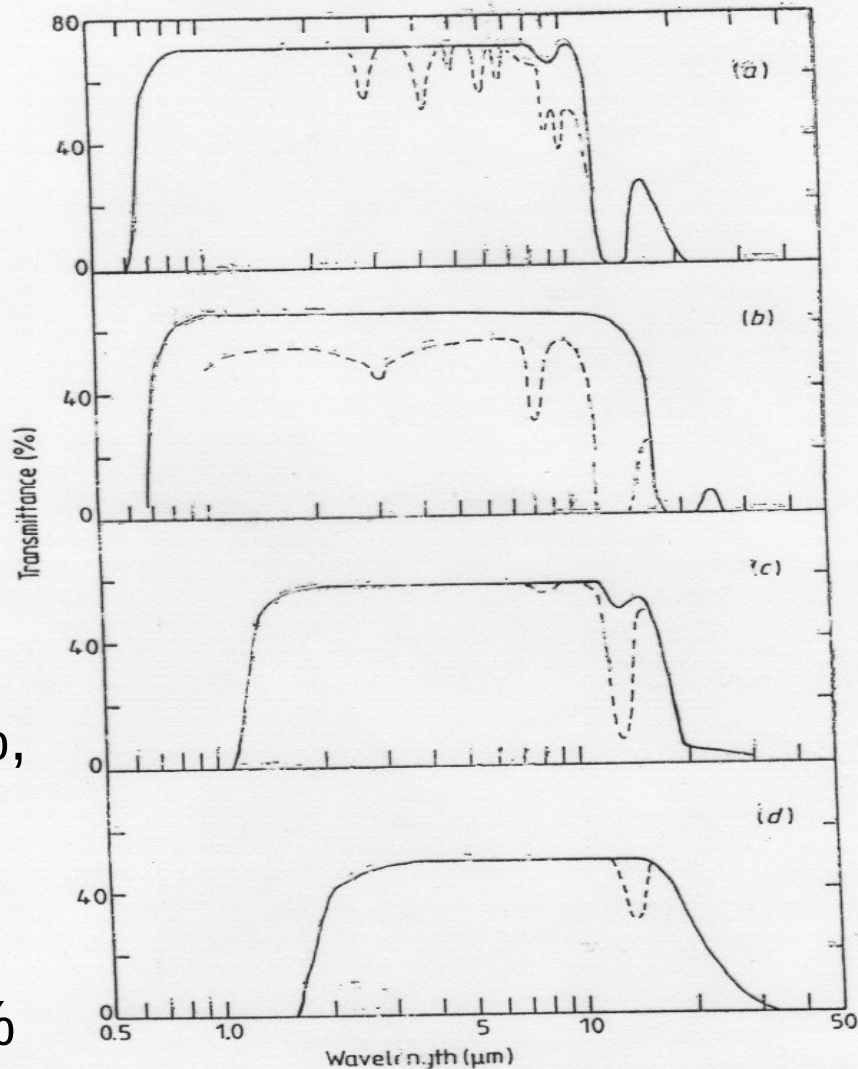


Figure 4.10 Transmittance of : (a) sulphide glass atomic % Ge 30, As 20, S 50, 1.9 mm thick (full curve), extrinsic impurity absorptions due to H₂O, H₂S oxide and carbon (broken curve); (b) selenide glass atomic % Ge 34, As 8, Se 58, 1.8 mm thick (full curve), extrinsic impurity absorptions due to oxide (broken curve); (c) Selenide-telluride glass atomic % Ge 30, As 13, Se 27, Te 30, 2.3 mm thick (full curve), extrinsic impurity absorptions due to oxide (broken curve); (d) telluride glass atomic % Ge 10, As 50, Te 40, 1.6 mm thick (full curve), extrinsic impurity absorptions due to oxide (broken curve).

Index lomů vs. disperze a propustnosti v IR

$$v = (n_{10} - 1) / (n_8 - n_{12})$$

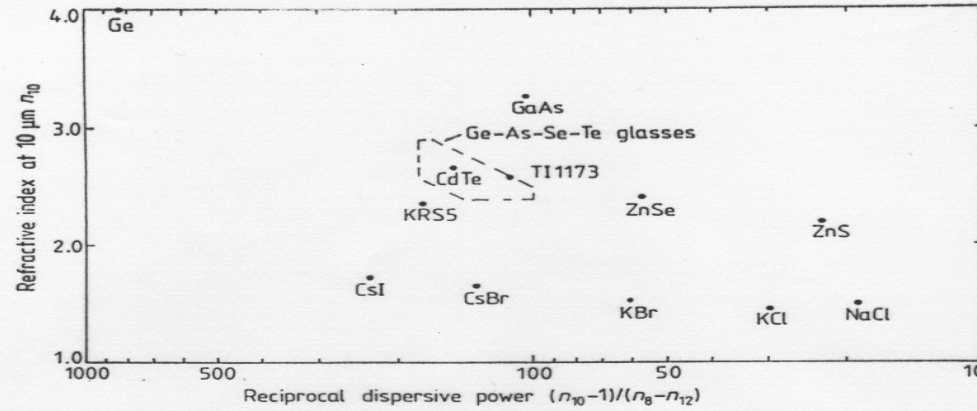


Figure 4.1 Reciprocal dispersive power $(n_{10} - 1) / (n_8 - n_{12})$ plotted against n_{10} at $10 \mu\text{m}$ for a number of optical materials useful in the far (8–12 μm) infrared.

Ge 3mm (A),
GaAs 3mm (B)

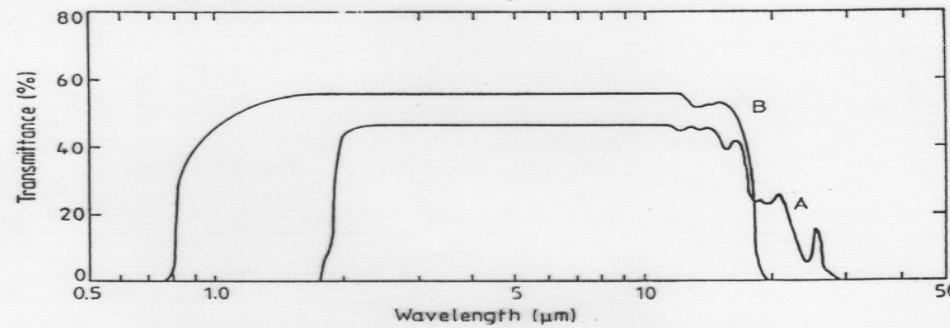


Figure 4.2 Transmittance of germanium 3 mm thick (A) and gallium arsenide 3 mm thick (B).

A) NaCl 10mm
B) KCl 10mm
C) AgCl 1mm
D) KRS5 1mm
E) CsI 5mm

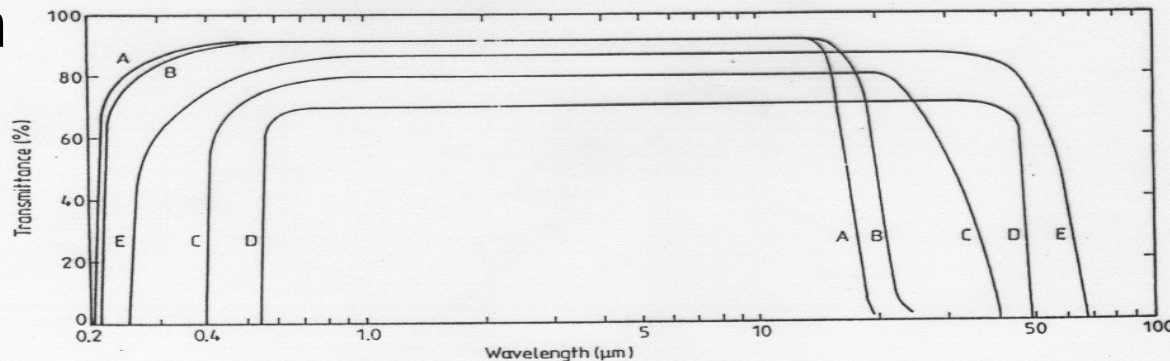


Figure 5.5 An illustration of the transmittance capability of several halides: A, NaCl 10 mm thick; B, KCl 10 mm thick; C, AgCl 1 mm thick; D, KRS5 1 mm thick; E, CsI 5 mm thick.

Tepelná roztažnost a tvrdost

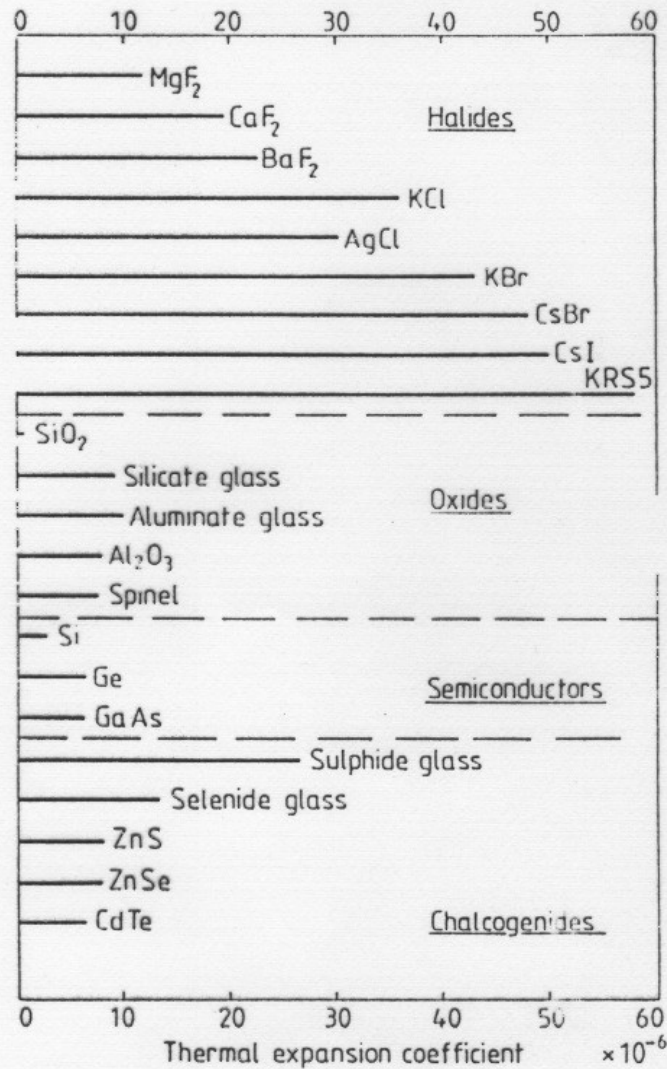


Figure 2.4 The relative thermal expansion coefficients of some halide, oxide, semiconductor and chalcogenide

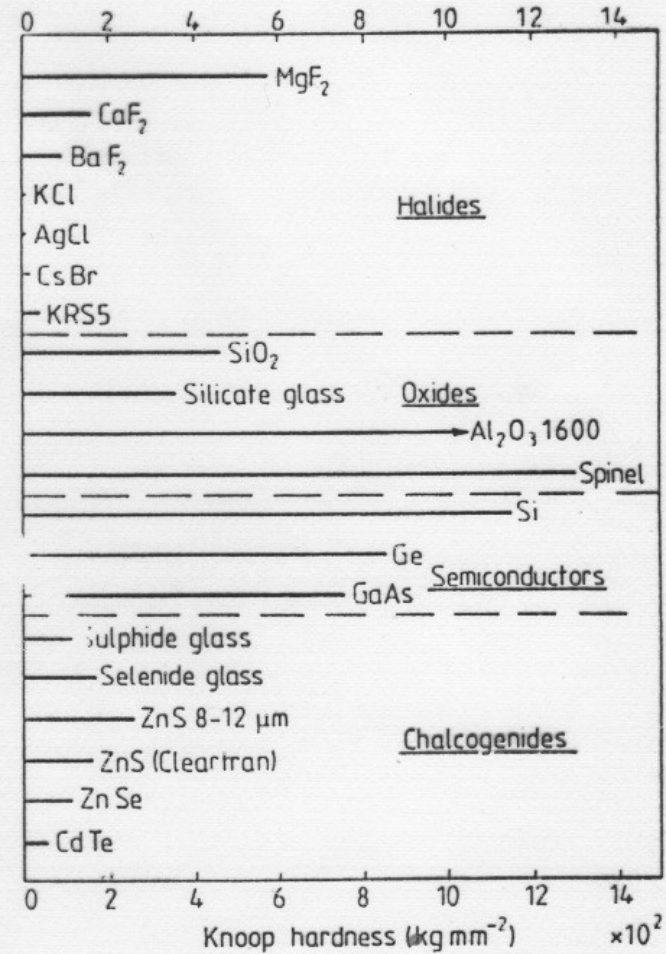


Figure 2.5 The relative hardness of some halide, oxide, semiconductor and chalcogenide materials.

Dvojlomné materiály

Table 2.1 Refractive indices of some common uniaxial crystals at 589.3 nm. After [2].

Crystal	Chemical structure	Symmetry class	type	n_o	n_e
Ice	H ₂ O	trigonal	positive	1.309	1.313
Quartz	SiO ₂	trigonal	positive	1.544	1.553
Beryl	Be ₃ Al ₂ (SiO ₃) ₆	hexagonal	negative	1.581	1.575
Sodium nitrate	NaNO ₃	trigonal	negative	1.584	1.336
Calcite	CaCO ₃	trigonal	negative	1.658	1.486
Tourmaline	complex silicate	trigonal	negative	1.669	1.638
Sapphire	Al ₂ O ₃	trigonal	negative	1.768	1.760
Zircon	ZrSiO ₄	tetragonal	positive	1.923	1.968
Rutile	TiO ₂	tetragonal	positive	2.616	2.903

Rtg oblast

Dielektrická funkce (Drude):

$$\varepsilon(\omega) = 1 - ne^2 / [\varepsilon_0 m \omega (\omega + i/\tau)]$$

Limita vysokých frekvencí

$$\varepsilon(\omega) \approx 1 - ne^2 / [\varepsilon_0 m_e \omega^2]$$

$$\varepsilon(\omega) \approx 1 - NZr_e \lambda^2 / \pi < 1$$

$$r_e = e^2 / [4\pi\varepsilon_0 m_e c^2] = 2.8179 \cdot 10^{-15} \text{ m}$$

$$n = 1 - \delta + i\beta = 1 - (\delta_0 - i\beta_0) \rho_{\text{rel}}$$

$$\delta \approx -NZr_e \lambda^2 / \pi$$

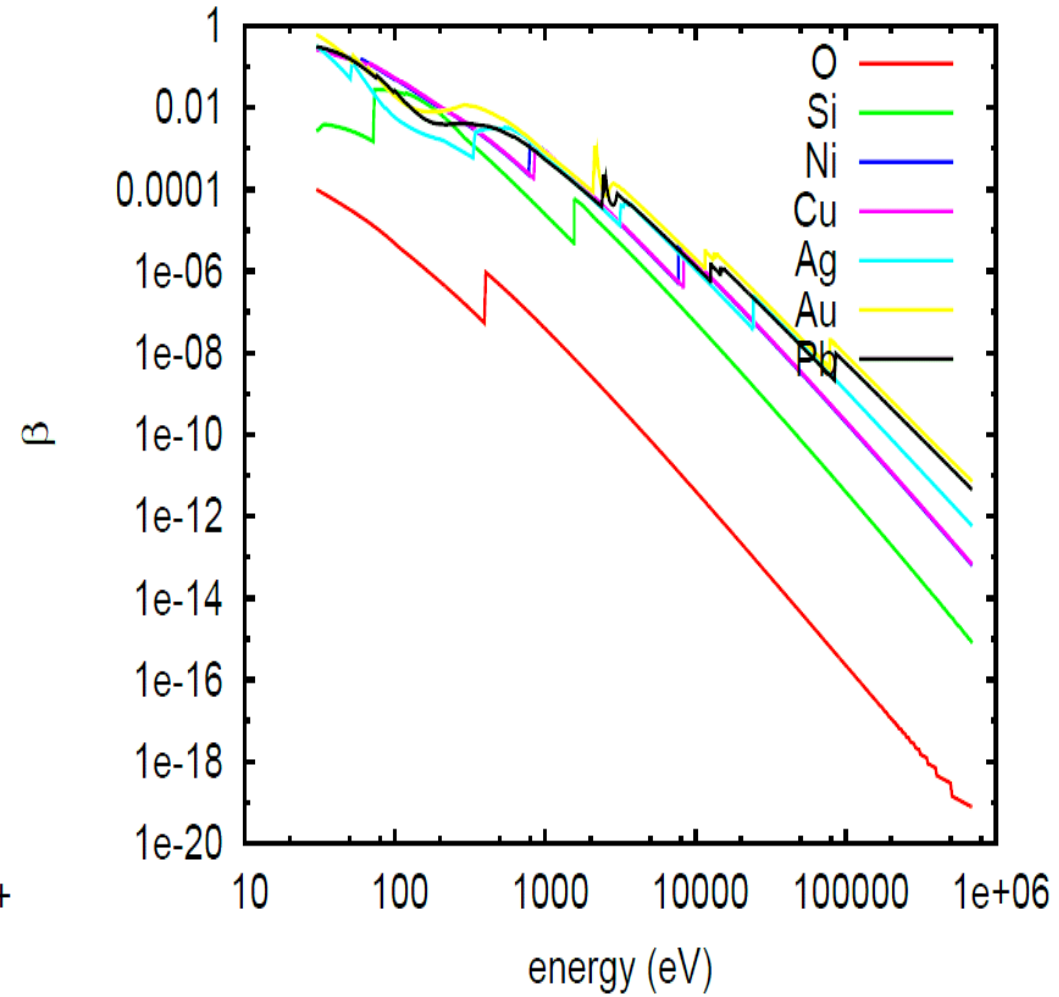
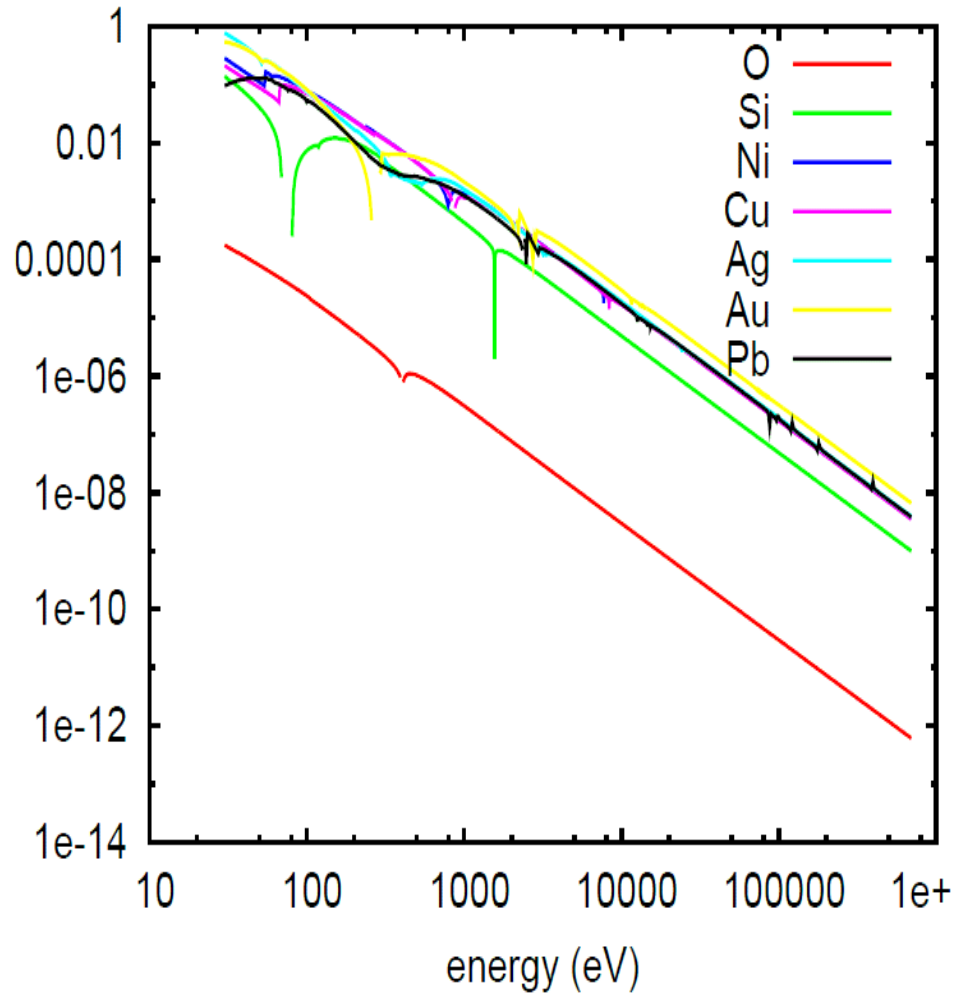
Electron density = proton density \sim mass density

$$\delta = -N(Z + f_1)r_e \lambda^2 / \pi$$

$$\beta = Nf_2 r_e \lambda^2 / \pi$$

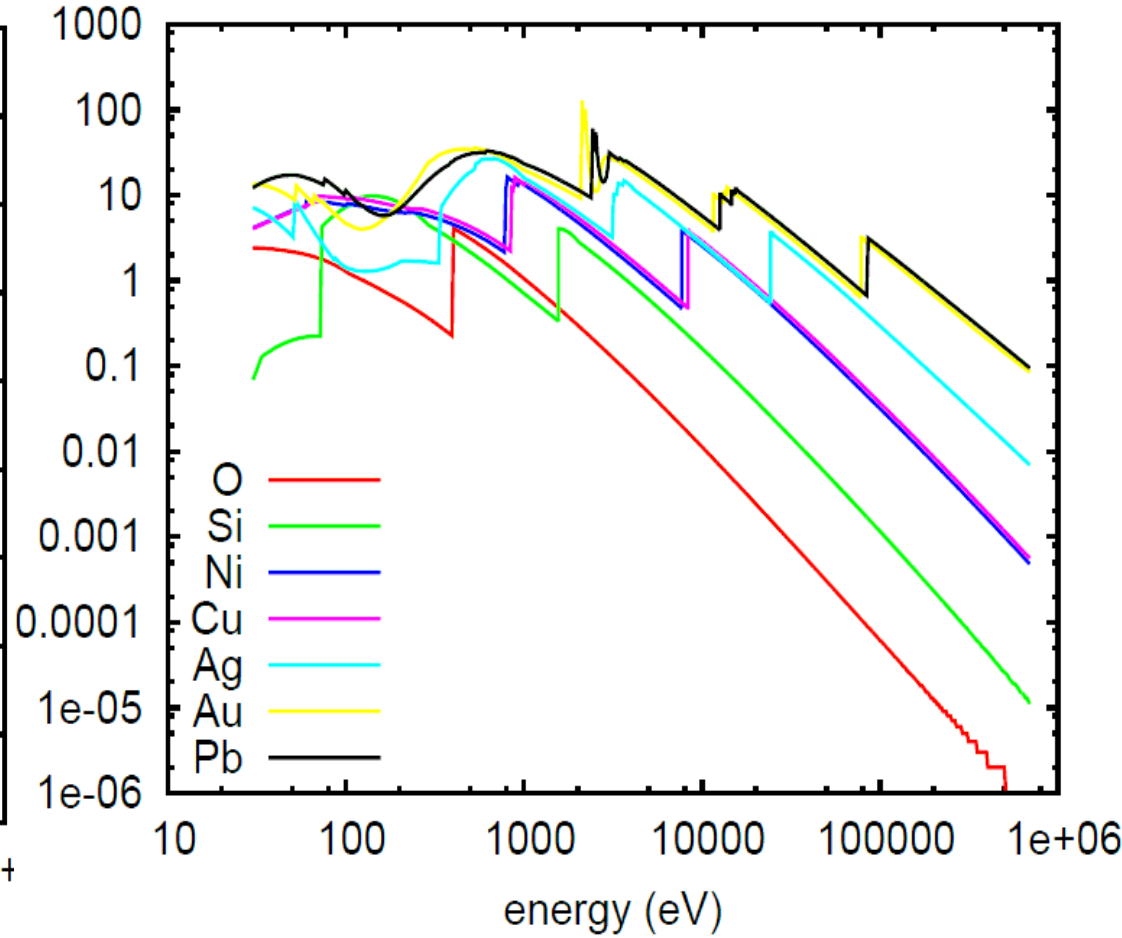
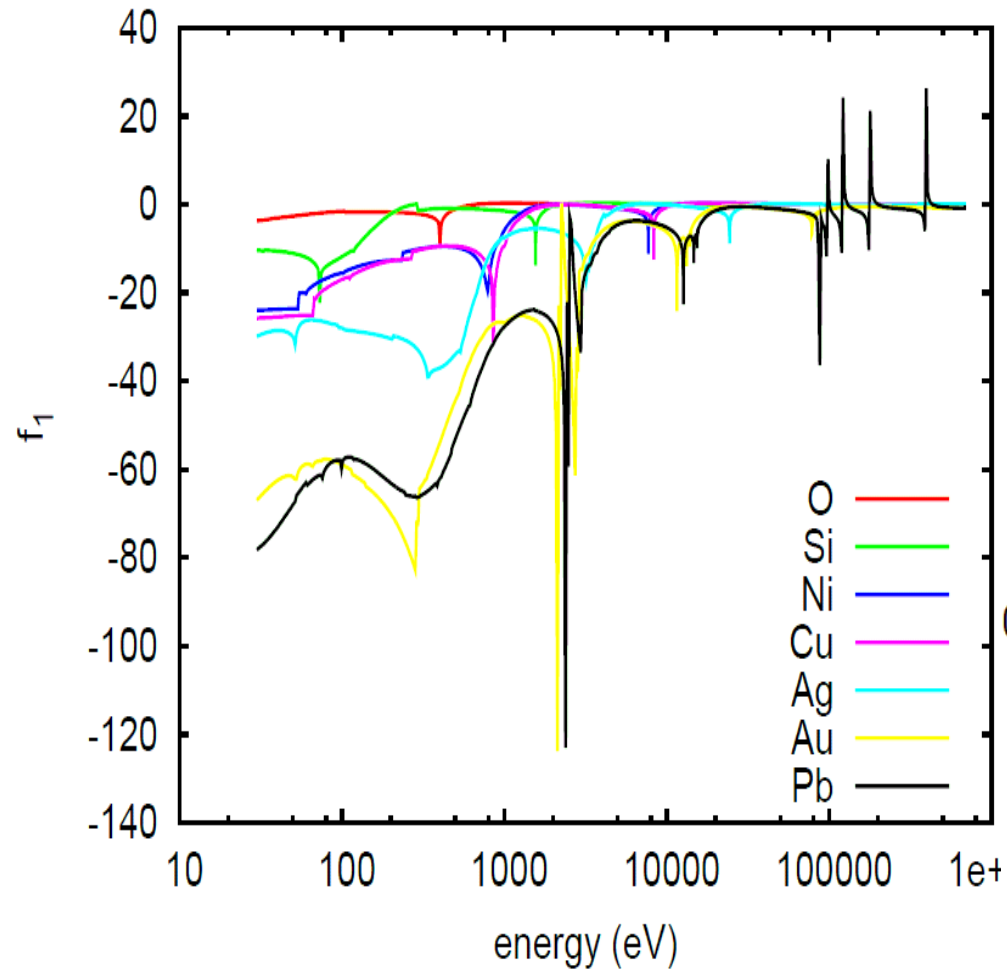
Rtg oblast

$$n=1-\delta+i\beta$$



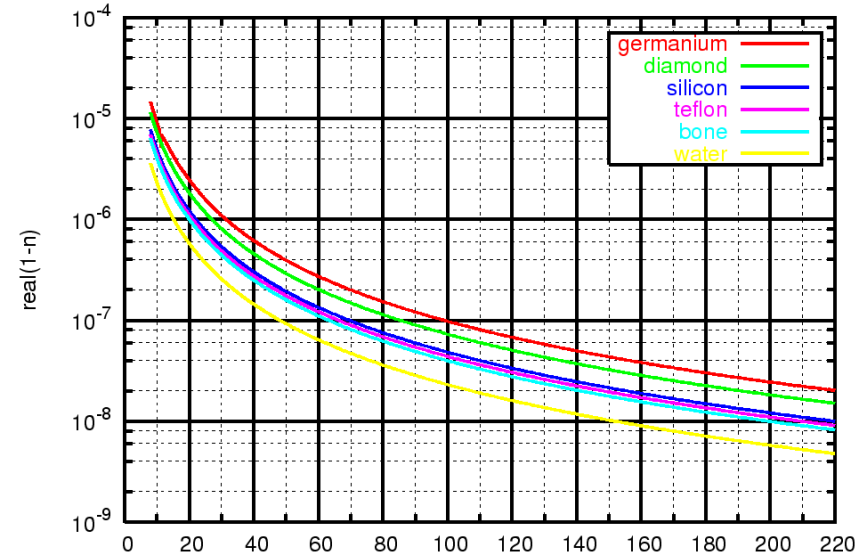
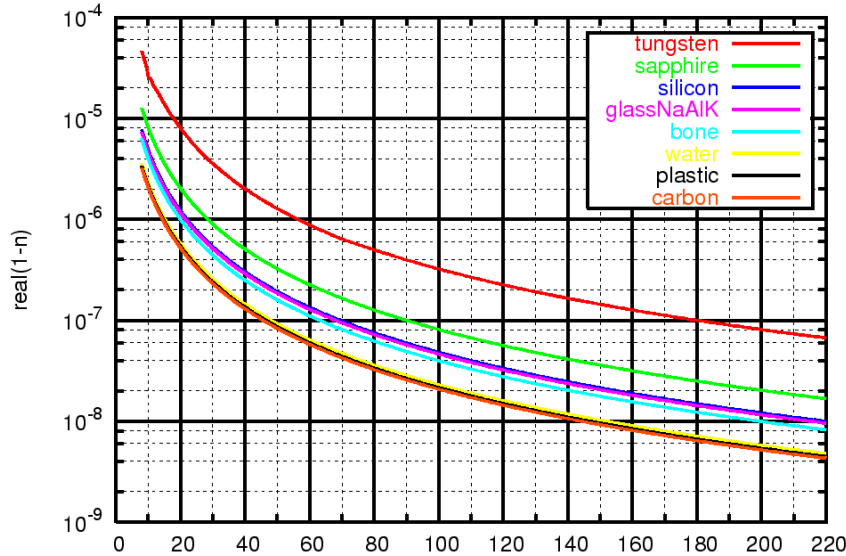
Rtg oblast

$$\varepsilon = 1 - (r_{el} \lambda^2 / \pi) \sum c_j f_j = 1 - (r_{el} \lambda^2 / \pi) \sum c_j (Z_j + f_{1j} - i f_{2j})$$

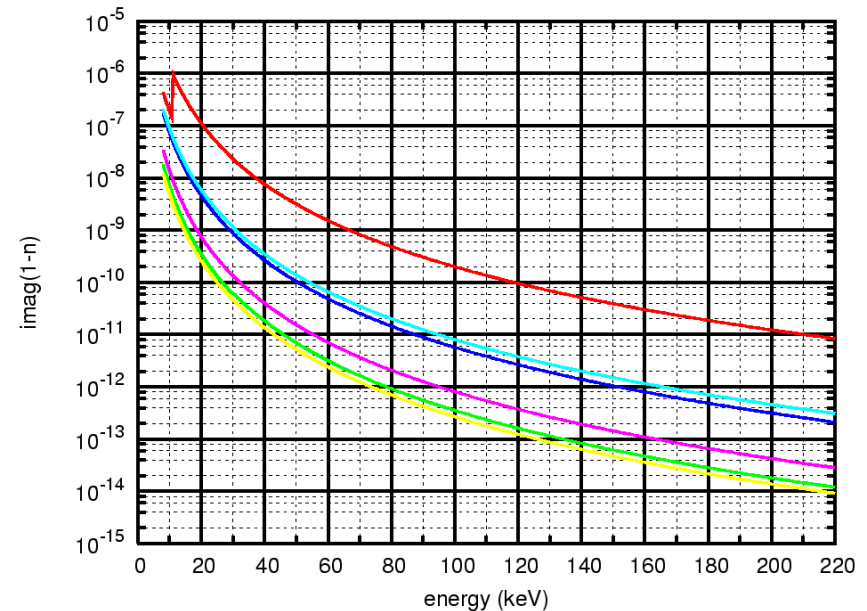
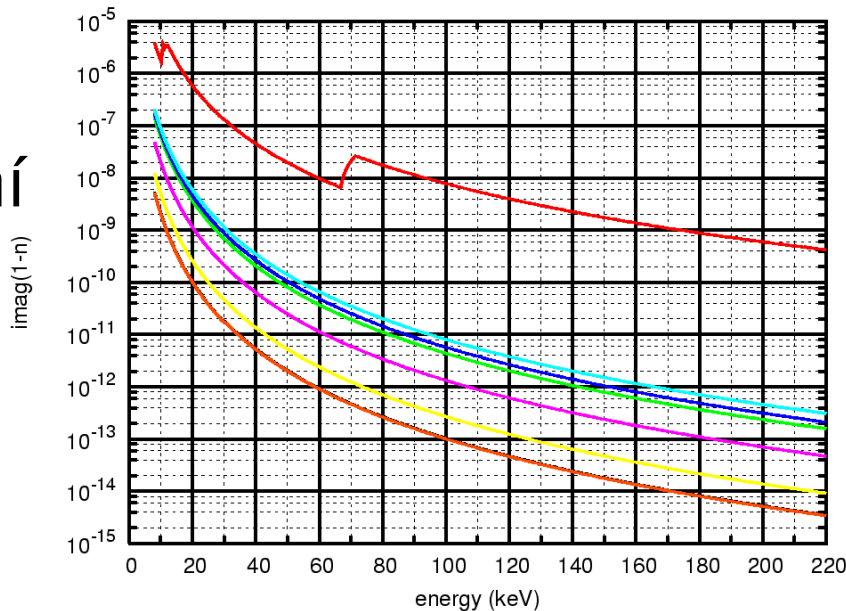


Dekrement indexu lomu $\delta(E)=1-n(E)$: závislost reálné a imaginární části na energii

Reálná
část
 $\delta \sim E^{-2}$



Imaginární
část
 $\beta \sim E^{-3}$
→ Dávka
z ozáření
klesá!



Rentgenka – laboratorní zdroj rtg záření

Lorentzův profil spektrálních čar:

$$I_R(E) = 1 / [1 + (2(E-E_0)/w)^2]$$

Cu-K α 1: 8048.06 eV = 1.54051 4.75e-4 Å rel.int. = 1.0

Cu-K α 2: 8028.10 eV = 1.54433 5.20e-4 Å rel.int. = 0.497

Polohy charakteristických čar:

CoK α 1=1.78896 Å

CuK α 1=1.54056

CuK α 2=1.54439

CuK α =1.54184

CuK β 1=1.39222 Å

MoK α 1=0.7093

MoK α 2=0.71359

MoK α =0.711445

MoK β 1=0.632288 Å

AgK α 1=0.559408

AgK α 2=0.563798

AgK α =0.561603

AgK β 2=0.497069 Å

TaK α 1=0.215947 Å

WK α 1 =0.20901 Å

